

# Point defects in ZnO single crystals and their thermal stability



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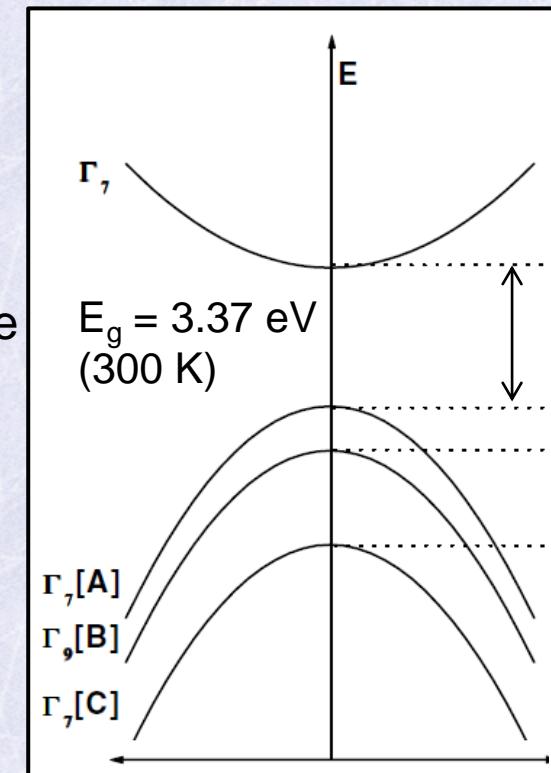
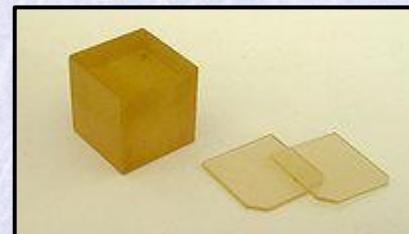
F. Selim

Center for Photochemical Sciences, Bowling Green State University, USA

# Introduction

## ZnO

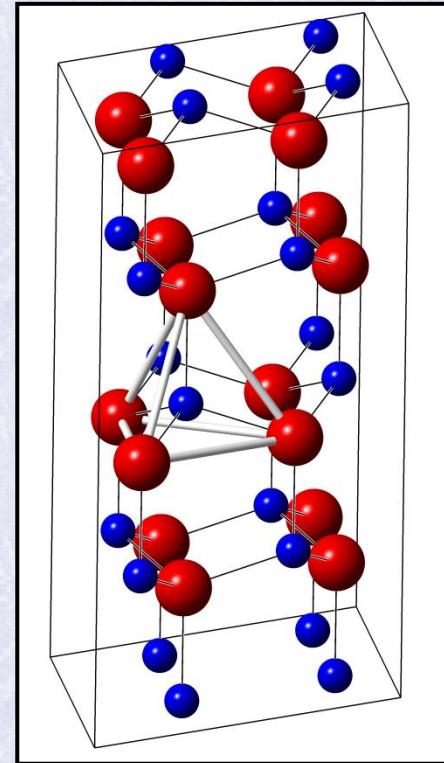
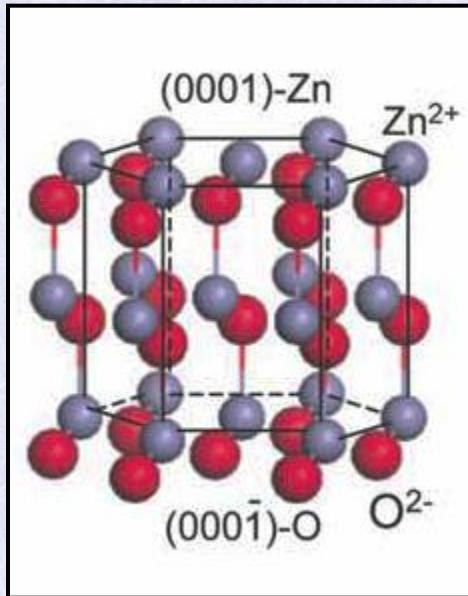
- wide band gap semiconductor  $E_g = 3.37 \text{ eV}$  ( $\lambda = 368 \text{ nm}$ ) at room temperature
- large exciton binding energy 60 meV
- promising material with many applications mainly in optoelectronics (transparent electronics, UV light emitting diodes, lasers, gas sensors)
- transparent conductive electrode for solar cells
- better resistance against radiation than GaAs or Si
- high quality ZnO single crystals are commercially available
- main problem: doping asymmetry
  - “natural” n-type doping
  - p-type doping is very difficult



# Theoretical calculations of positron lifetimes in ZnO

## ZnO

- Wurtzite structure
- $a = 3.25 \text{ \AA}$ ,  $c = 5.12 \text{ \AA}$
- Zn atoms in tetrahedral co-ordination
- Zn  $d$ -electrons hybridize with O  $p$ -electrons



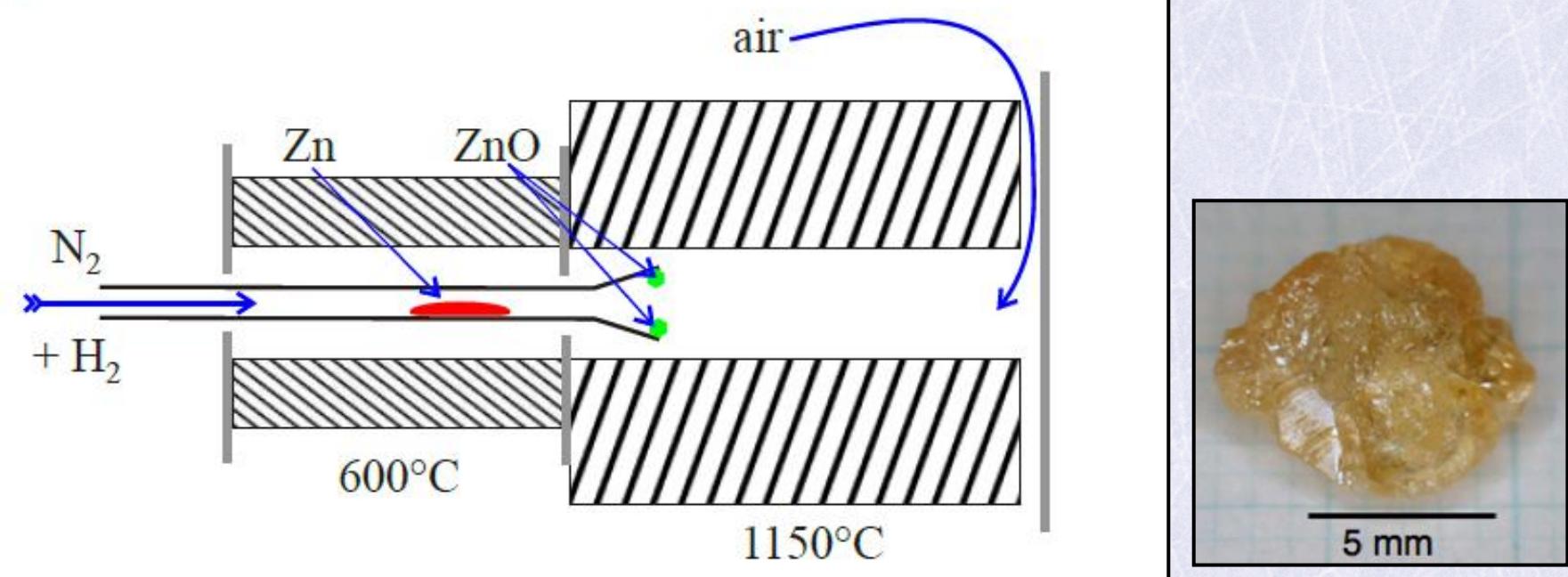
# Growth of ZnO crystals

- ZnO melting temperature  $T_m \approx 1975^\circ\text{C}$ , vapor pressure 1.06 bar

## 1. Chemically assisted vapor transport (CVT)

*Eagle-Picher Inc., USA*

- small crystals
- gas contamination ( $\text{N}_2$ ,  $\text{H}_2$ )



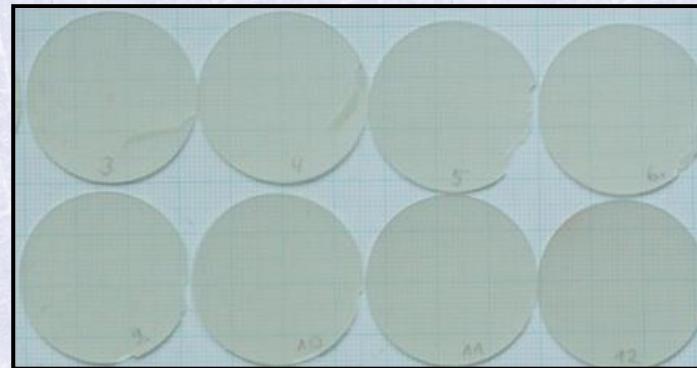
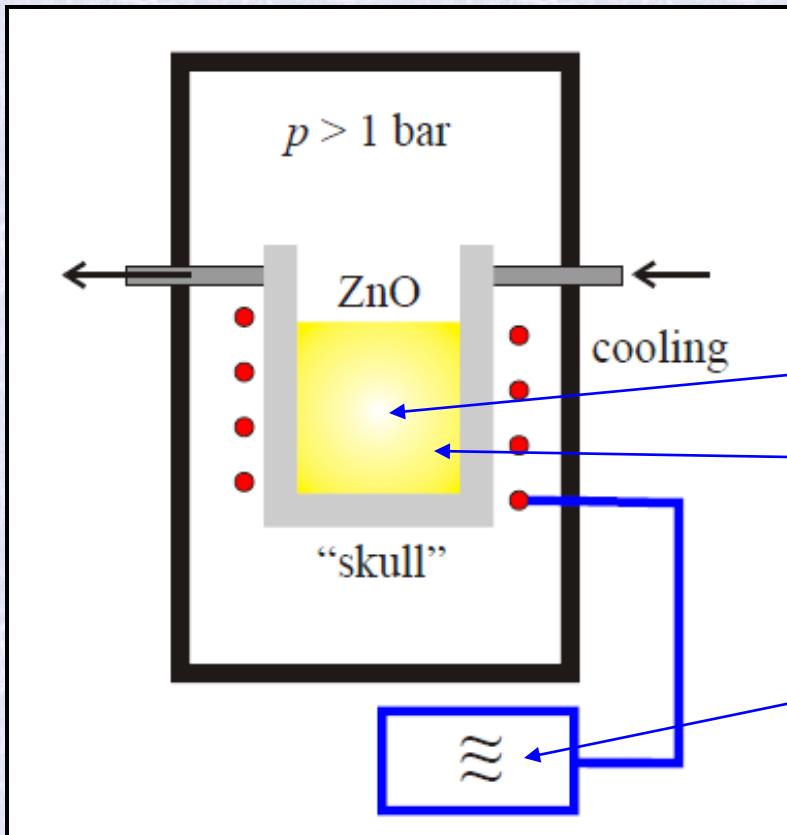
# Growth of ZnO crystals

- ZnO melting temperature  $T_m \approx 1975^\circ\text{C}$ , vapor pressure 1.06 bar

## 2. pressurized melt growth (PMG) “skull growth”

Cermet Inc., USA

- very pure environment – growing crystal is in contact with ZnO only
- temperature gradients



zone of growth  
cooled ZnO powder “skull”  
RF power  
*D.C. Reynolds et al., J. Appl. Phys. 95, 4802 (2004)*

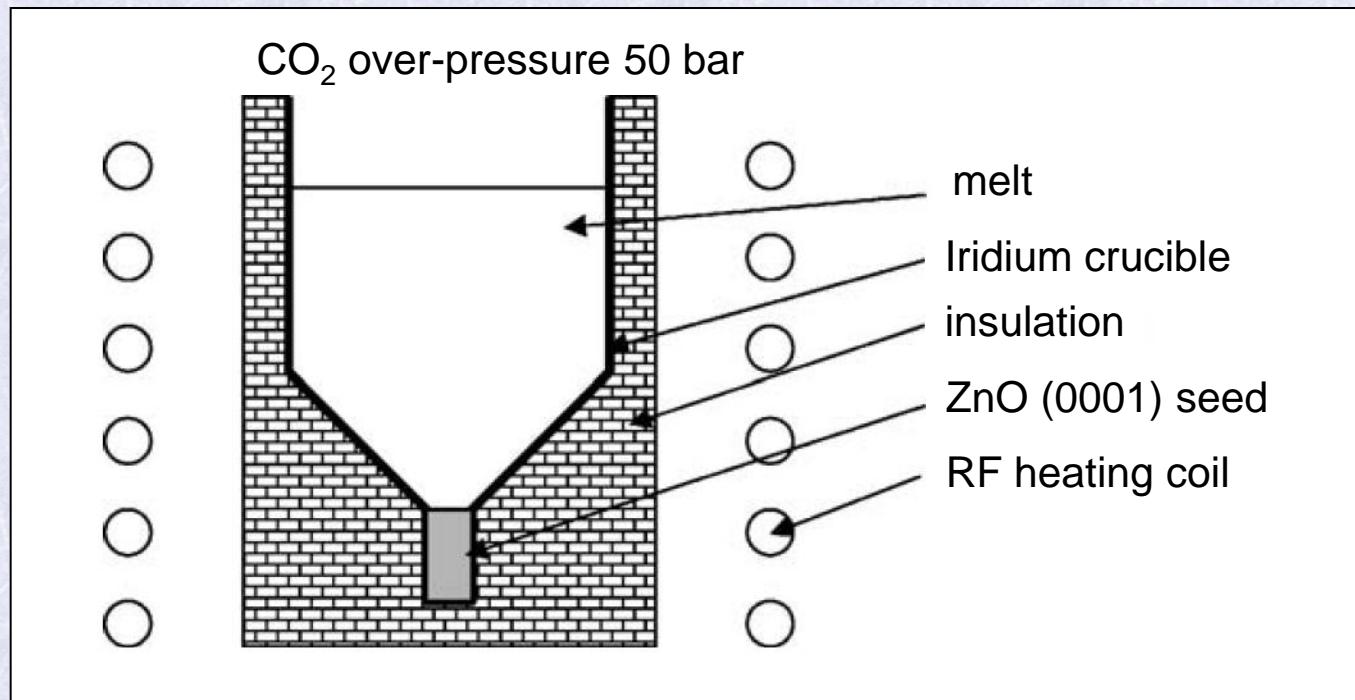
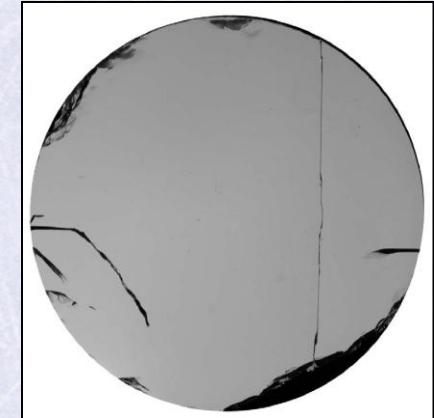
# Growth of ZnO crystals

- ZnO melting temperature  $T_m \approx 1975^\circ\text{C}$ , vapor pressure 1.06 bar

## 3. Bridgman growth (BG)

*Institut für Kristalzüchtung (IKZ) Berlin*

- problem with suitable crucible material



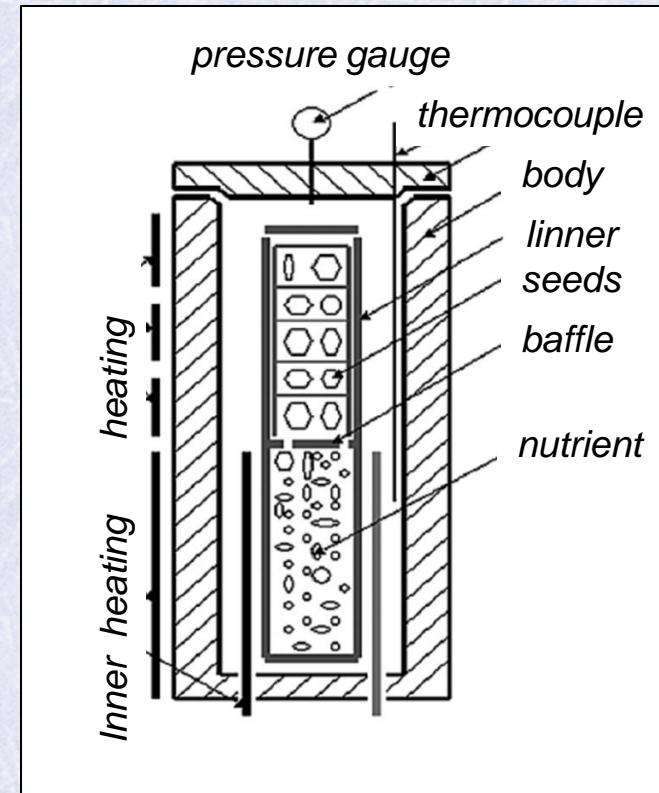
# Growth of ZnO crystals

- ZnO melting temperature  $T_m \approx 1975^\circ\text{C}$ , vapor pressure 1.06 bar

## 4. hydrothermal growth (HTG)

MaTeCK (Germany), CrysTec (Germany), Altramed(USA), MTI (USA), ...

- from aqueous alkaline solutions
- concentrated KOH / LiOH solution
- nutrient (Zn salt + hydroxide) is heated in Ti or Ag lined autoclave ( $T \approx 370^\circ\text{C}$ ,  $p \approx 220$  bar)
- small temperature gradient transports zincates from solution to the growing zone
- enable to grow large crystals (diam.  $\approx 100$  mm, length  $\approx 1$  m)
- main problem is contamination by impurities
- most common method for production of commercial ZnO crystals



## **ZnO single crystals studied**

### **Hydrothermal growth (HTG)**

- MaTecK GmbH, Jülich, Germany
- CrysTec GmbH, Berlin, Germany
- MTI Corp., Richmond, CA, USA
- Atomergic Chemetals Corp. (Altra), Farmingdale, NY, USA
- University Wafers, South Boston, MA, USA

### **Pressurized melt growth (PMG)**

- Cerment Inc., Atlanta, GA, USA

### **Bridgman growth (BG)**

- Institut für Kristalzüchtung (IKZ), Berlin, Germany

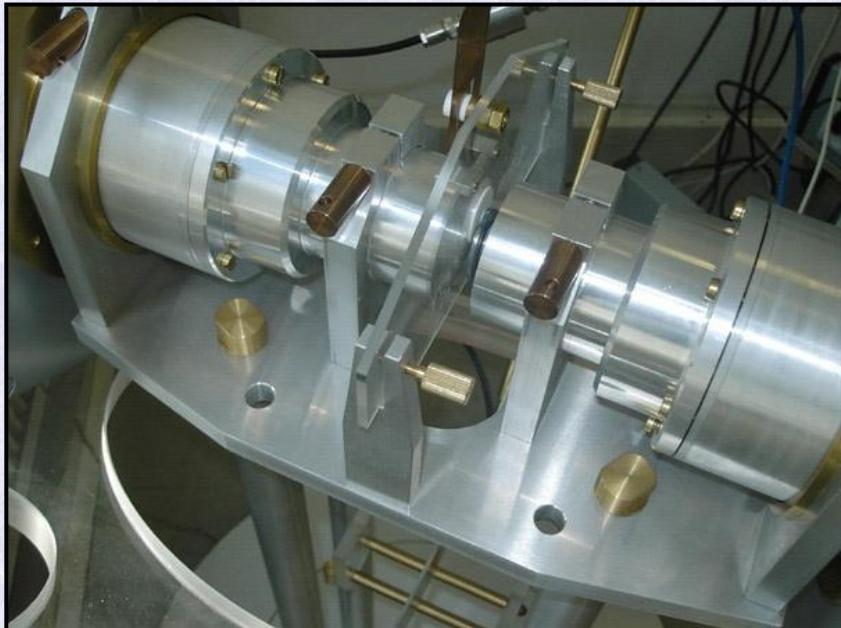
### **Chemically assisted vapor phase growth technique (CVT)**

- Oak Ridge National Laboratory (ORNL), TN, USA

# Positron lifetime spectroscopy

- digital positron lifetime spectrometer
- photomultipliers Hamamatsu H3378
- BaF<sub>2</sub> scintillators
- timing resolution 145 ps (FWHM <sup>22</sup>Na)
- effective coincidence count rate 100 s<sup>-1</sup>
- >10<sup>7</sup> positron annihilation events in each spectrum

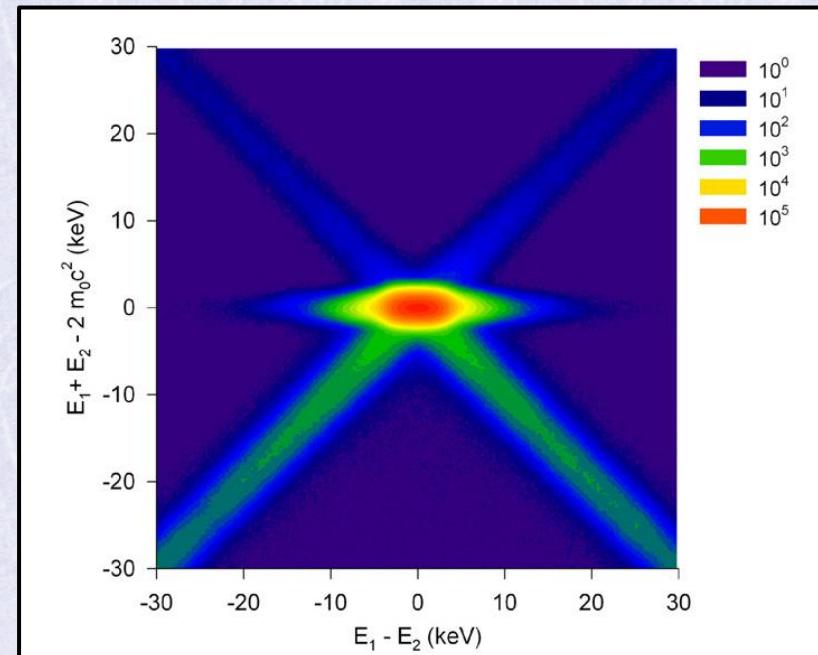
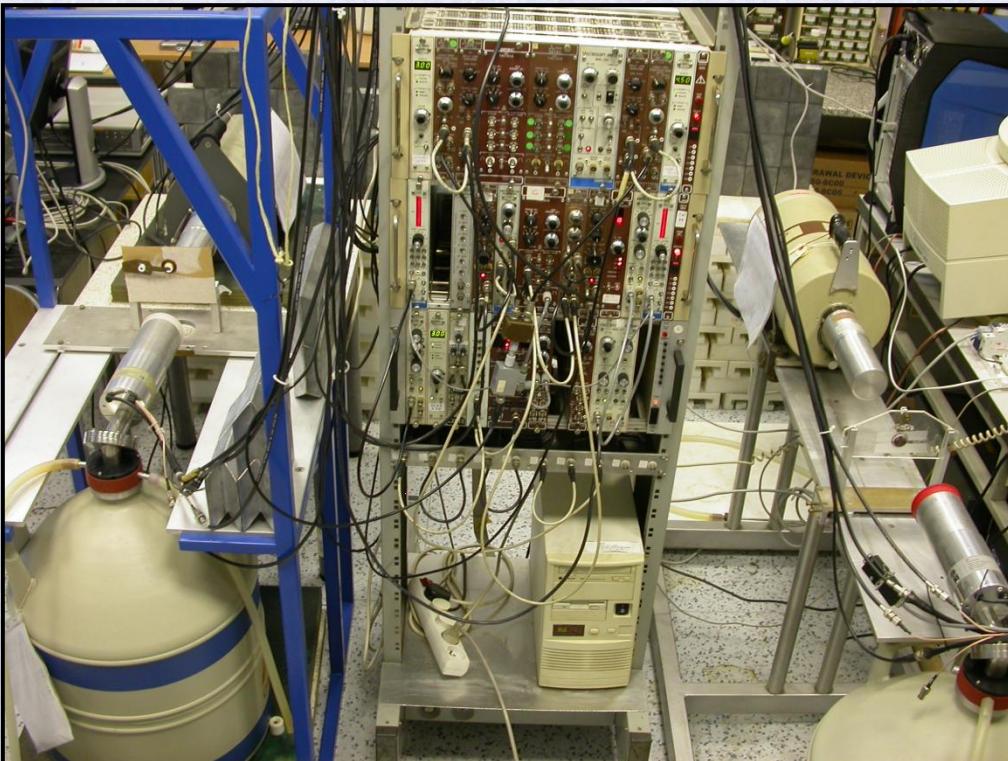
*F. Bečvář et al., Nucl. Instrum. Methods A **539**, 372 (2005)*



# Coincidence Doppler broadening

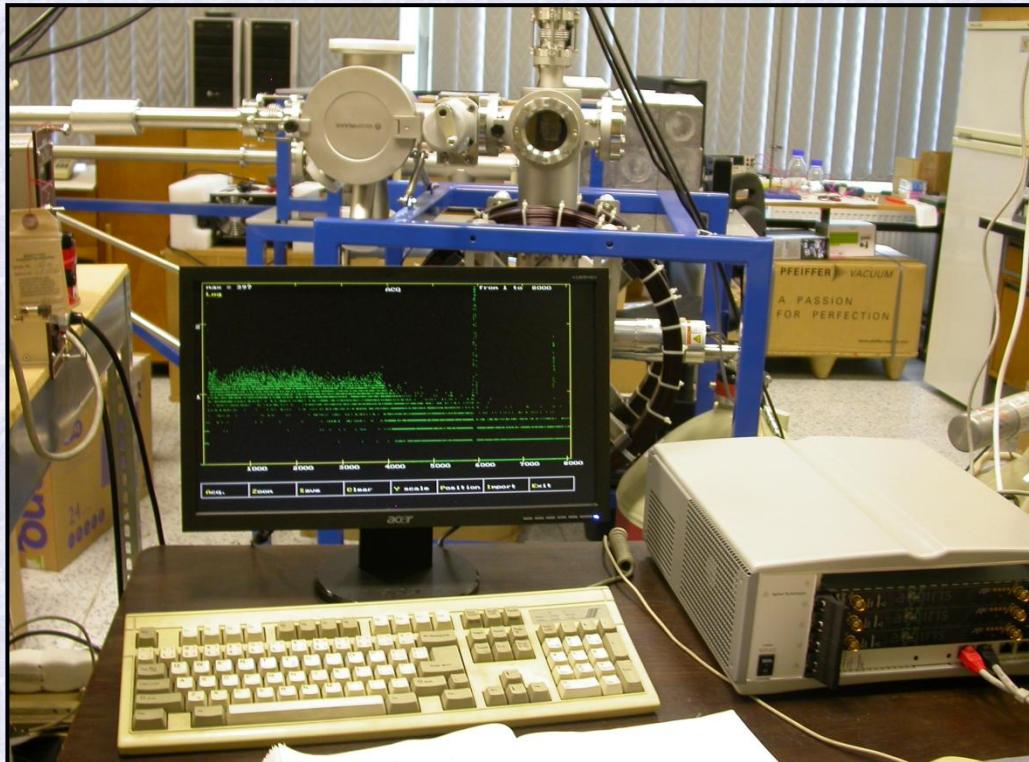
- digital CDB spectrometer
- two HPGe detectors
- resolution 0.9 keV at 511 keV
- peak-to-background ratio  $10^6$
- $>10^8$  positron annihilation events in each spectrum

*J. Čížek et al., Nucl. Instrum. Methods A **623**, 982 (2010)*



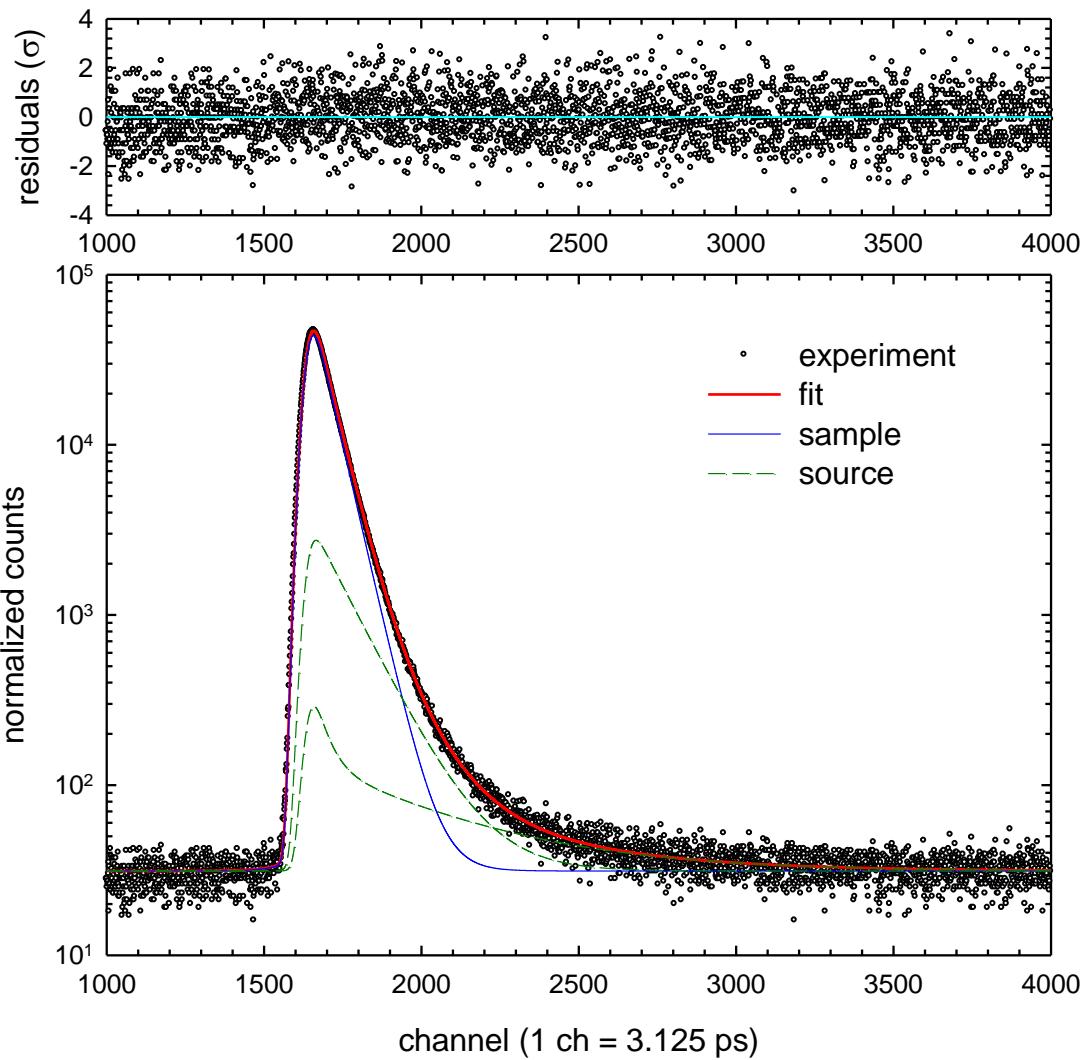
# Positron back-diffusion

- magnetically guided slow positron beam
- positron energy 0.050 – 35 keV
- HPGe detector with energy resolution  $1.09 \pm 0.01$  keV at 511 keV
- Doppler broadening of annihilation evaluated using  $S$ ,  $W$  line shape parameters
- $> 7 \times 10^5$  counts in annihilation peak



# Positron Lifetime Spectrum

## HTG ZnO crystal (MaTecK)



**single component**

$$\tau_1 = 180.7(3) \text{ ps}, I_1 = 100 \%$$

source contribution:

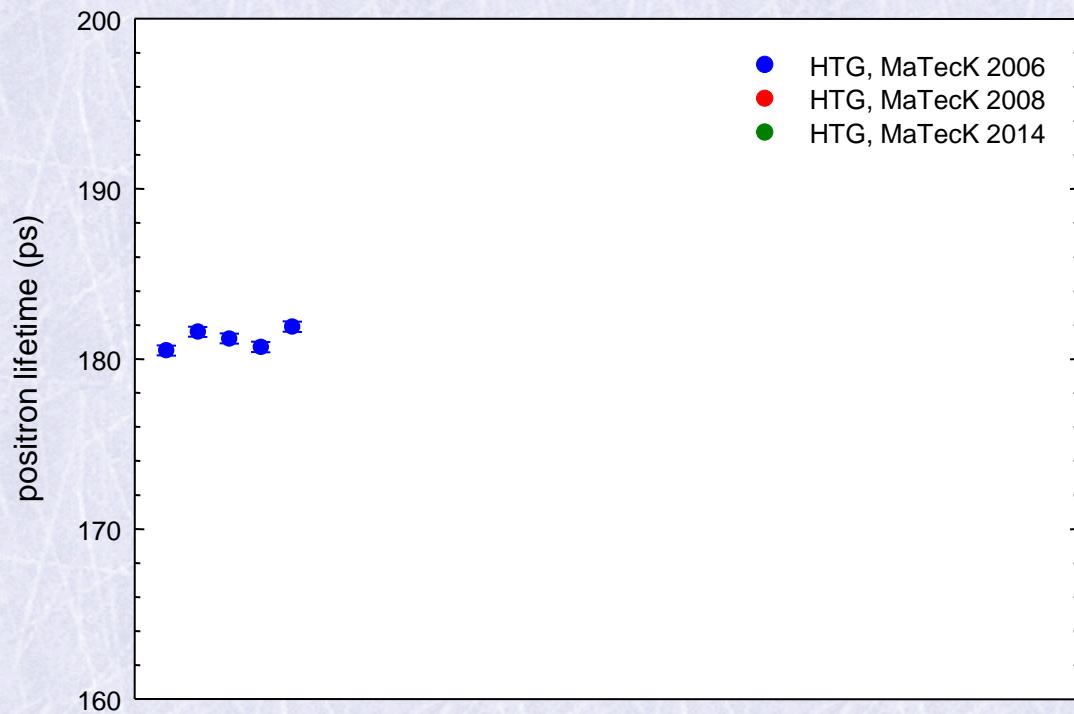
$^{22}\text{Na}$  source deposited  
on 2  $\mu\text{m}$  mylar foil

$$\tau_{s1} = 368 \text{ ps}, I_{s1} = 9 \%$$

$$\tau_{s2} = 1.26 \text{ ns}, I_{s2} = 1 \%$$

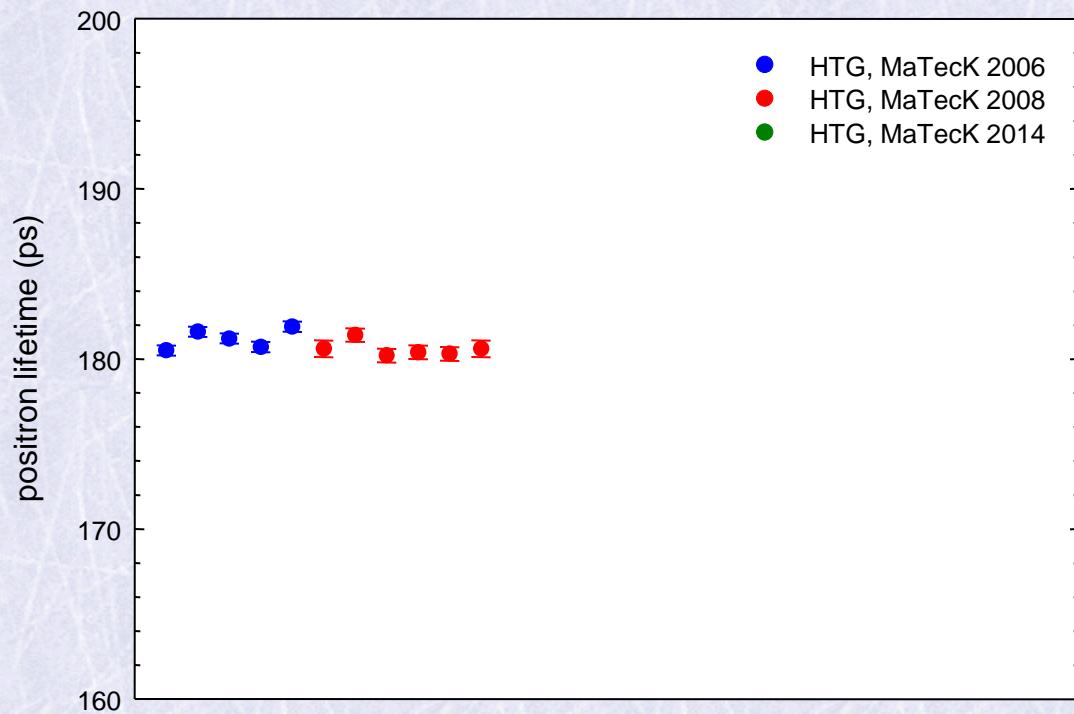
## As-grown ZnO single crystals - reproducibility

- comparison of sample batches from various periods



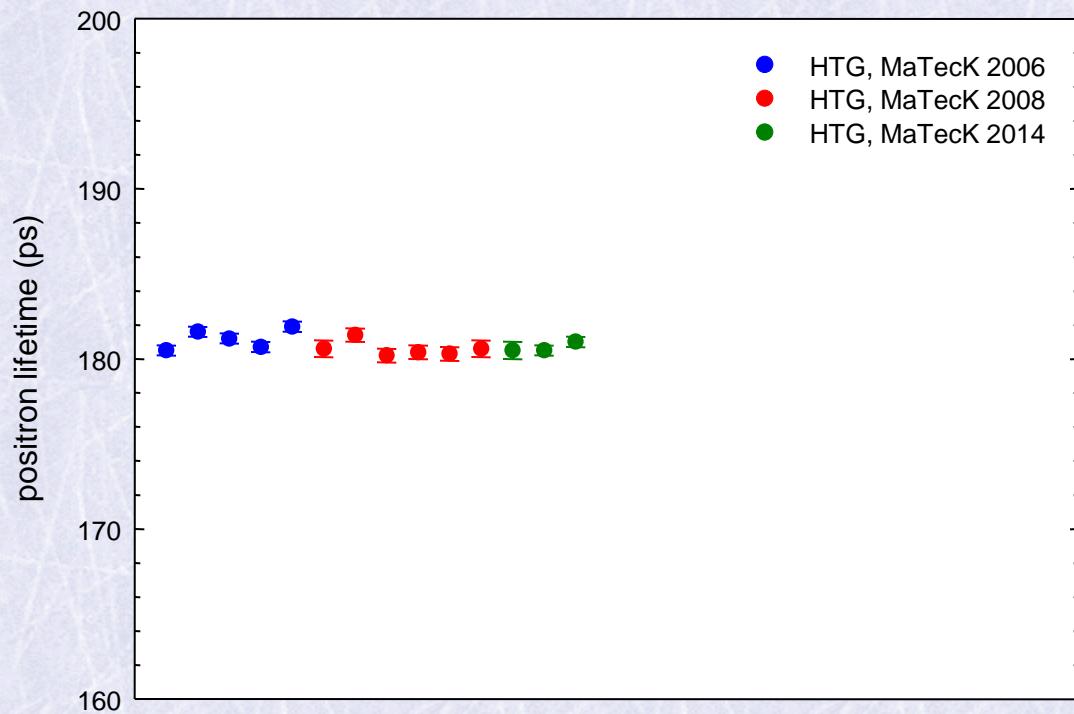
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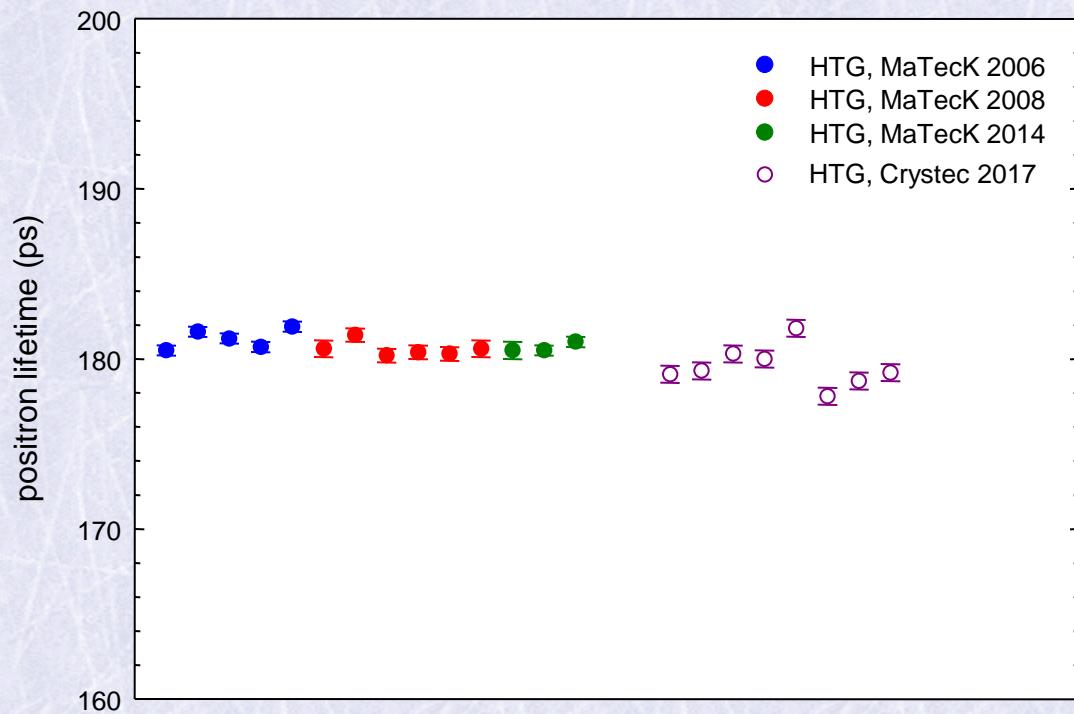
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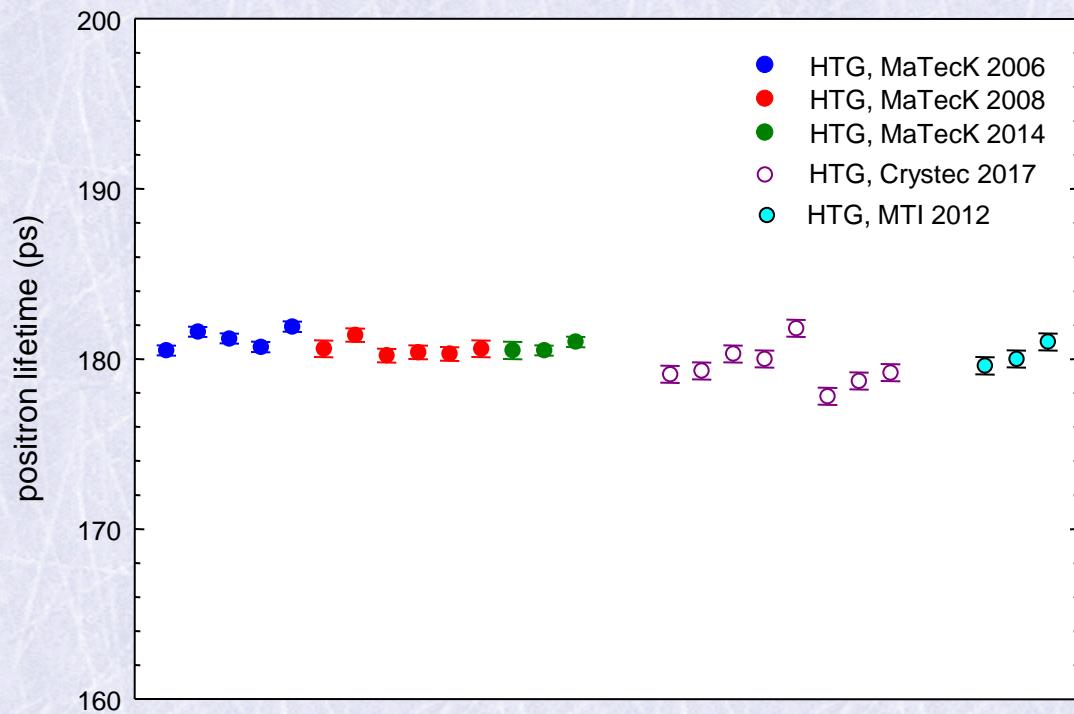
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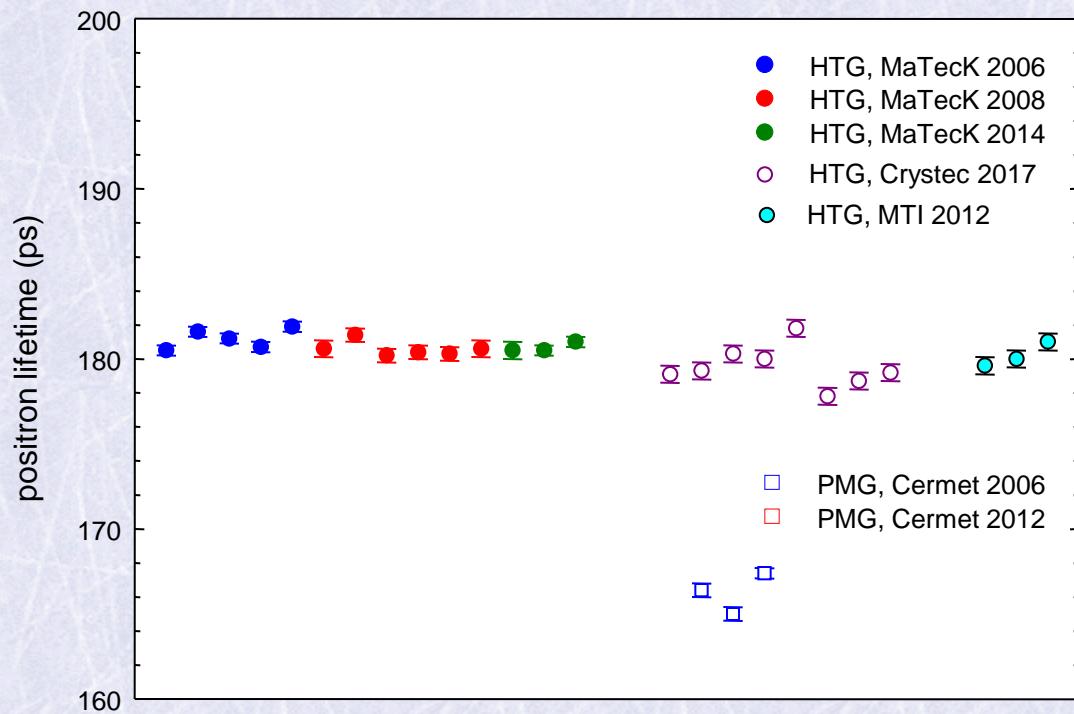
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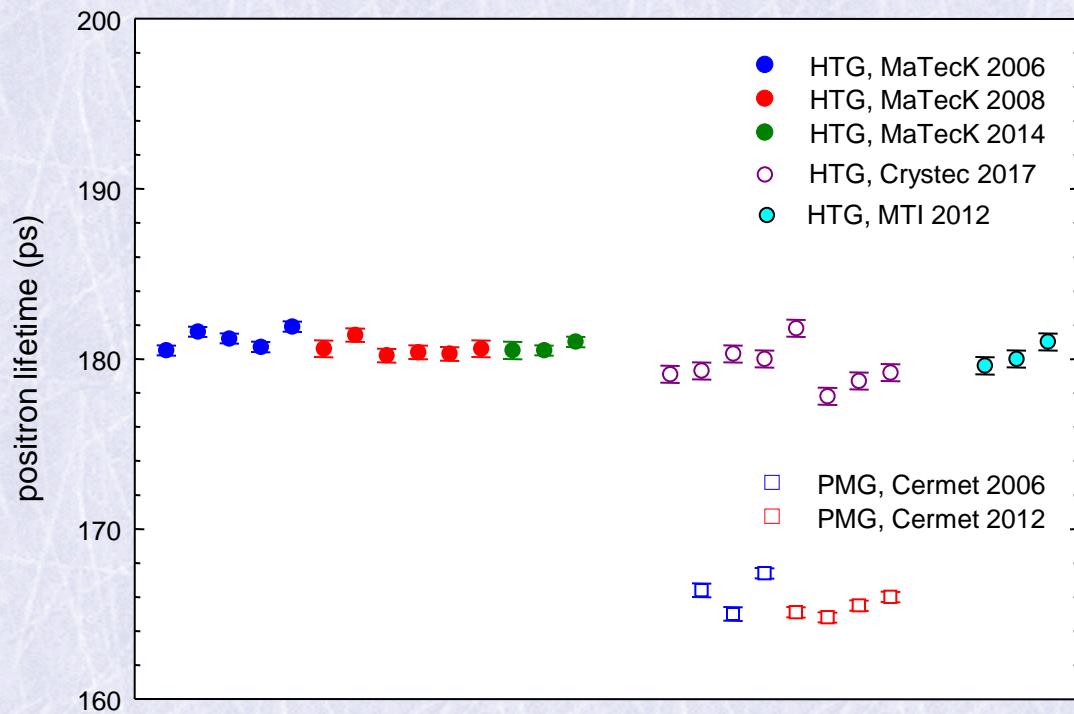
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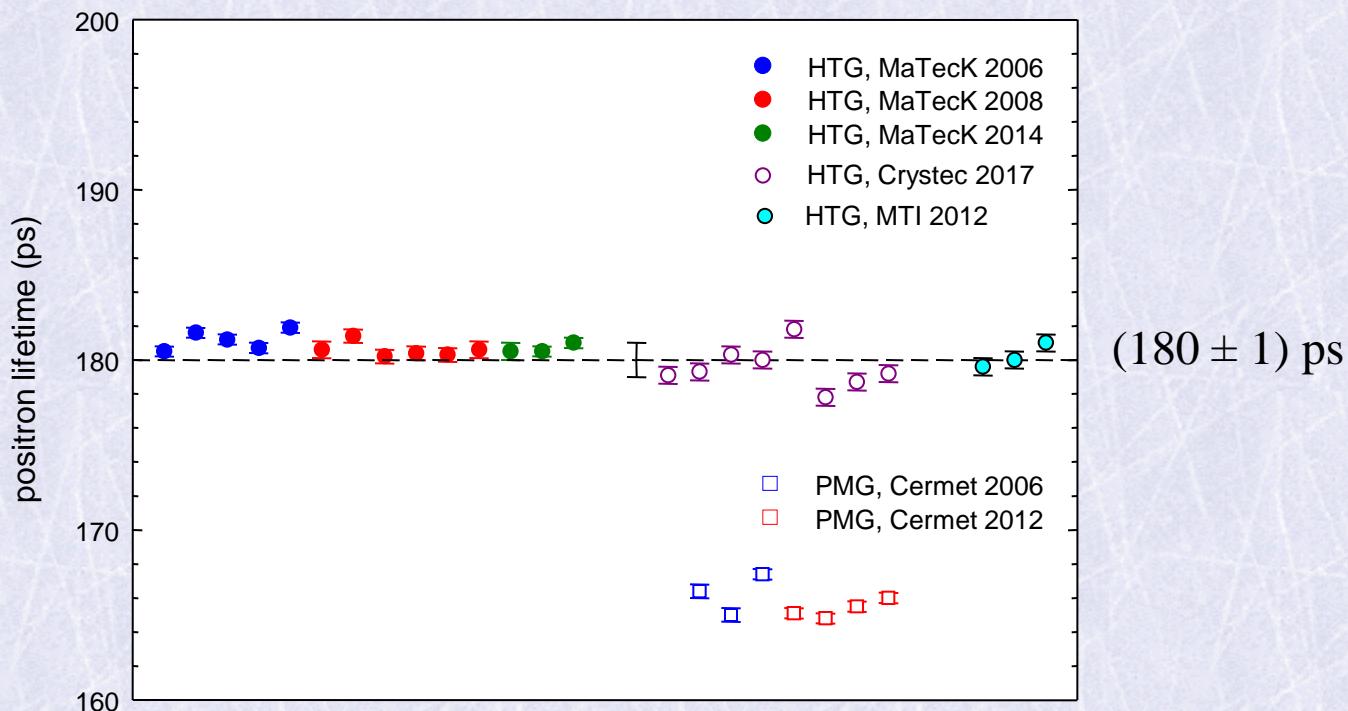
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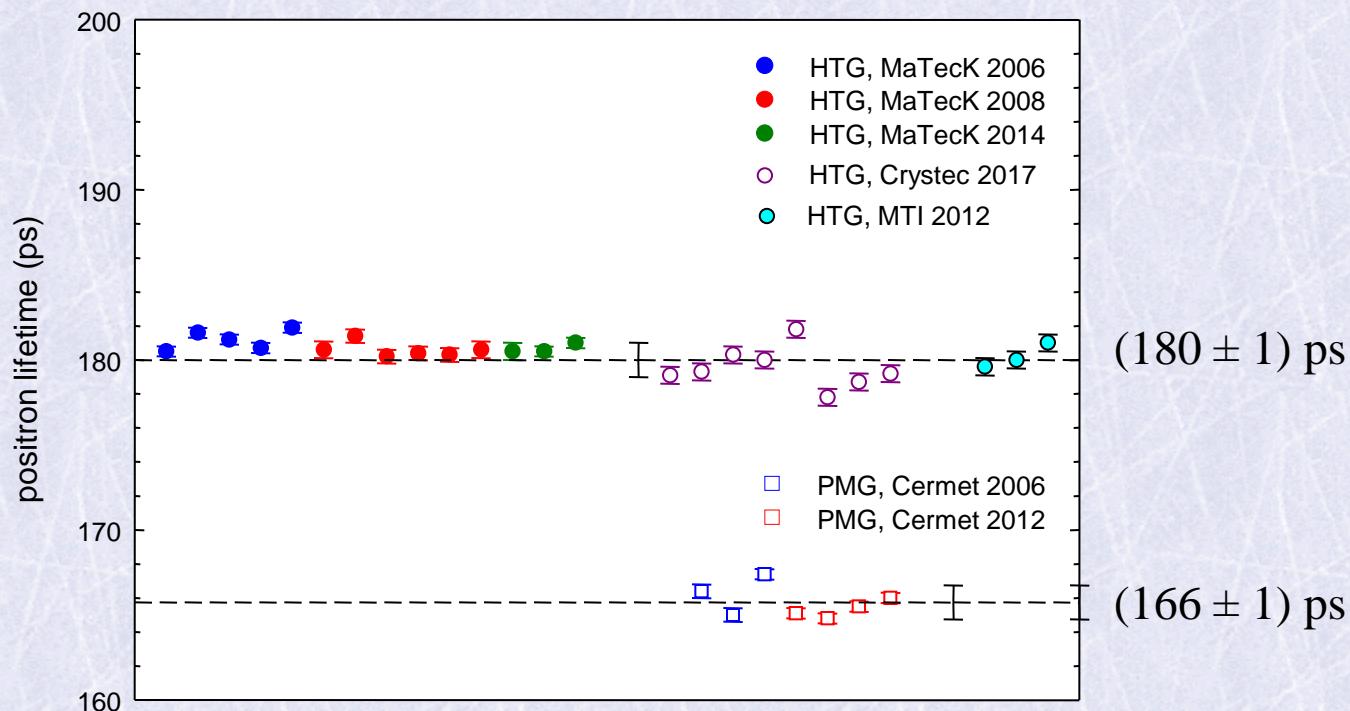
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- comparison of sample batches from various periods
- no significant differences among samples prepared in various periods and by various producers (MaTeck, Crystec, MTI)



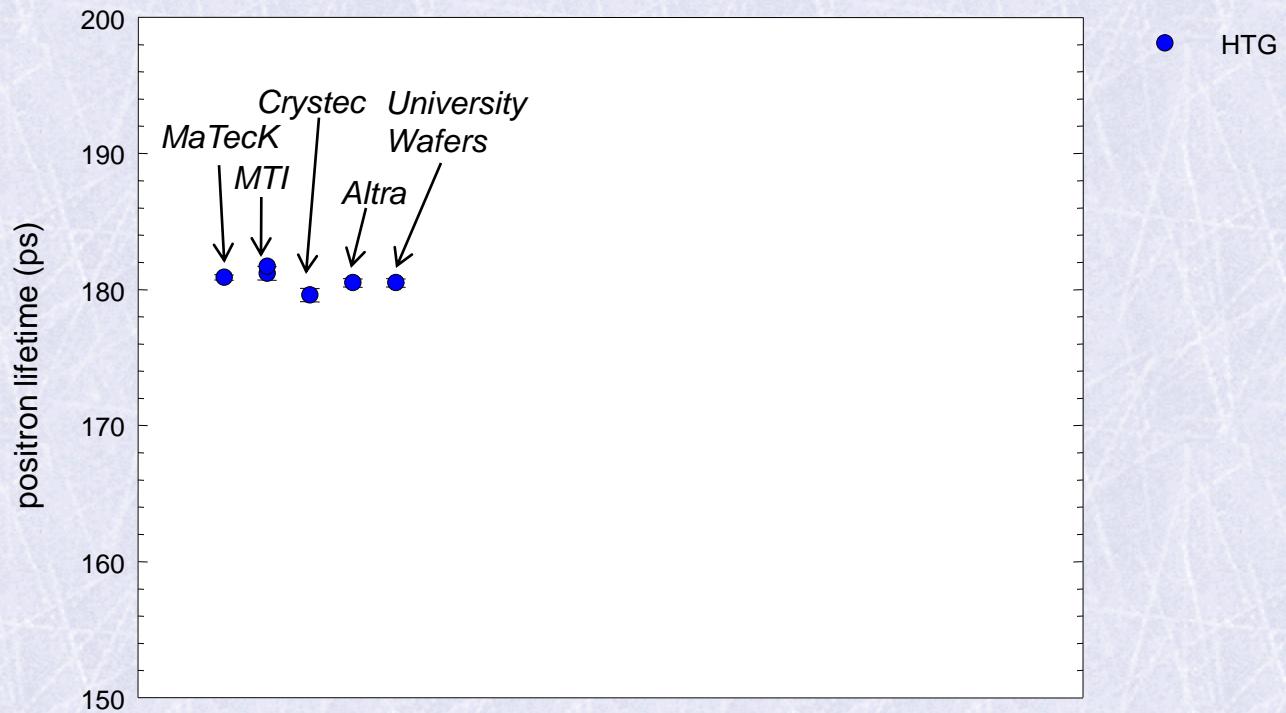
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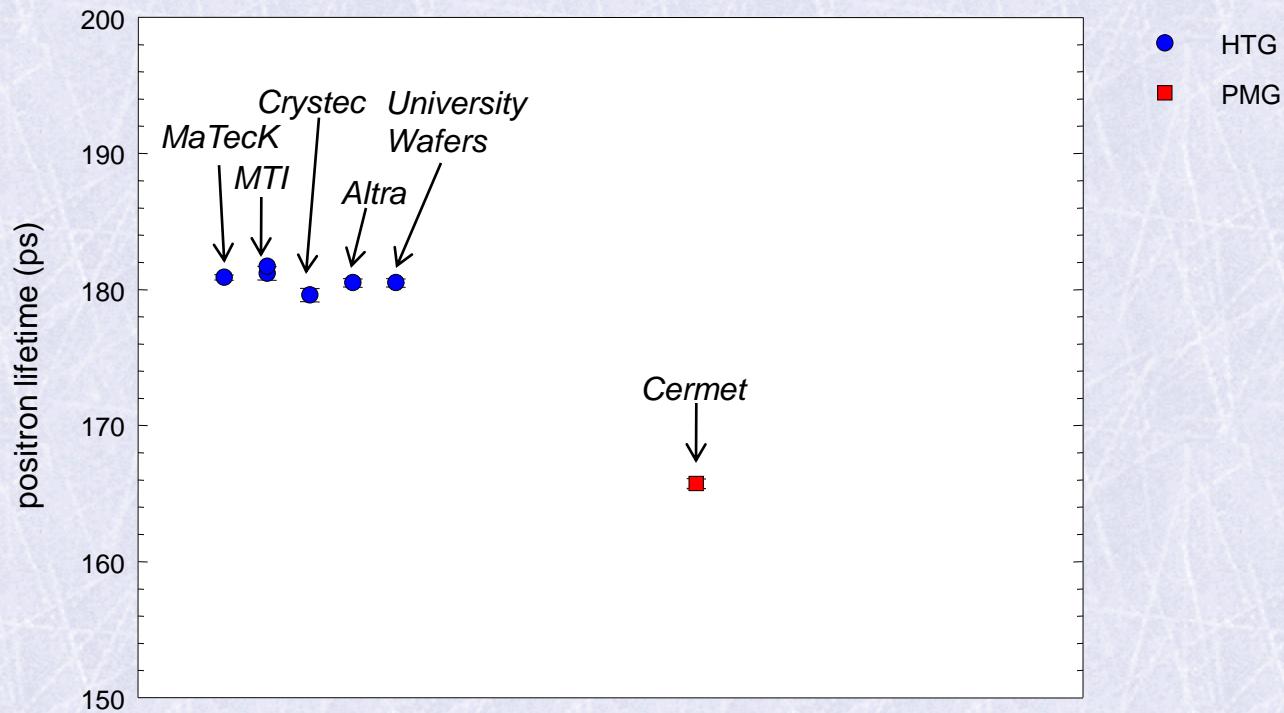
# As-grown ZnO single crystals – comparison of growth techniques

- comparison of ZnO crystals prepared by various techniques



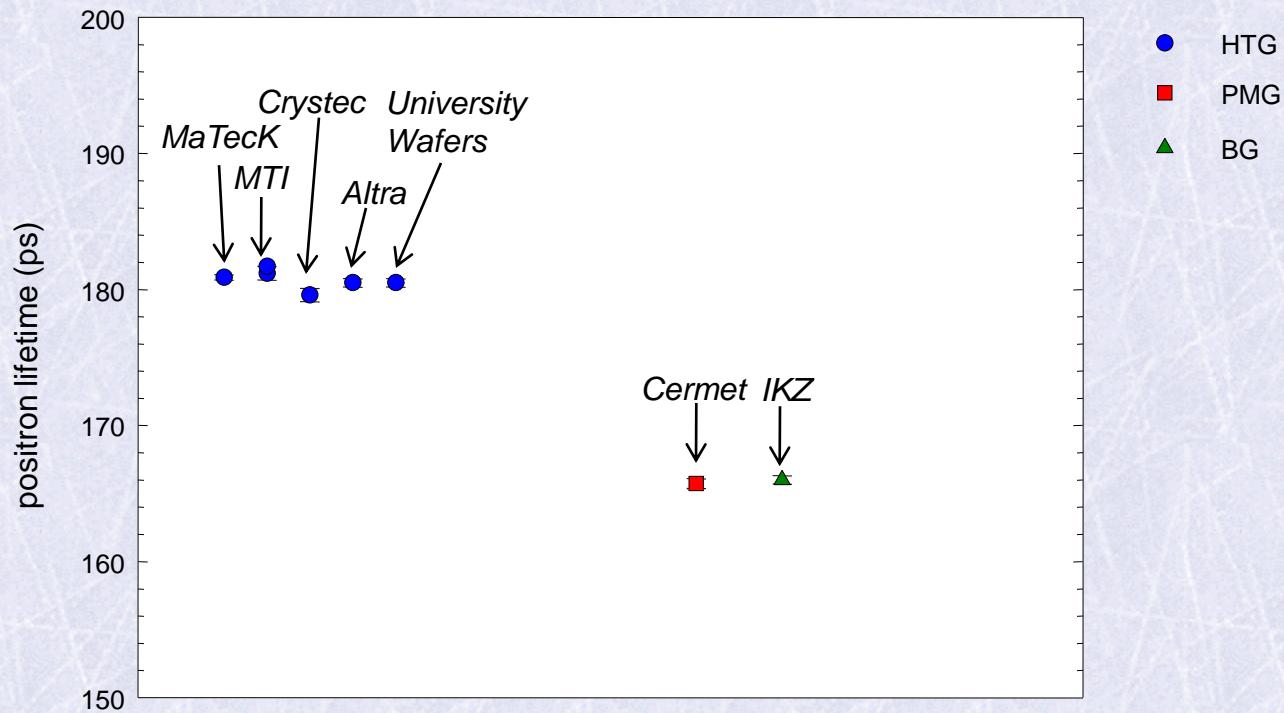
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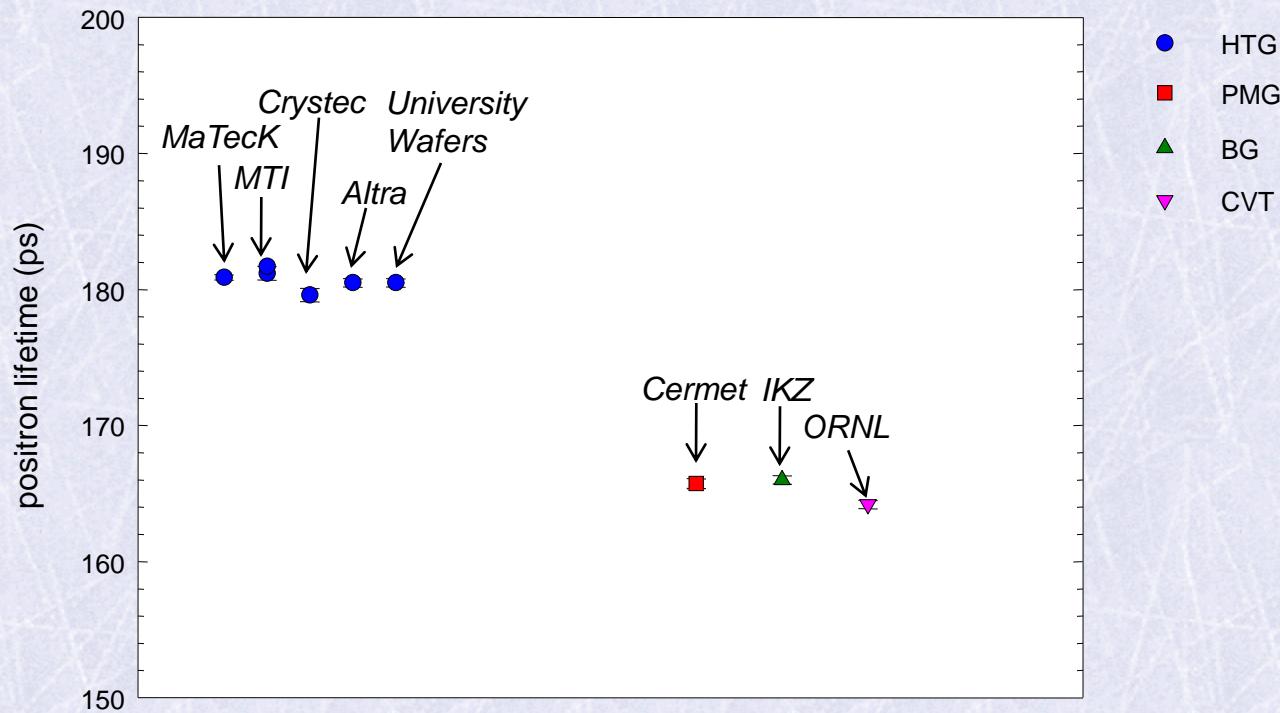
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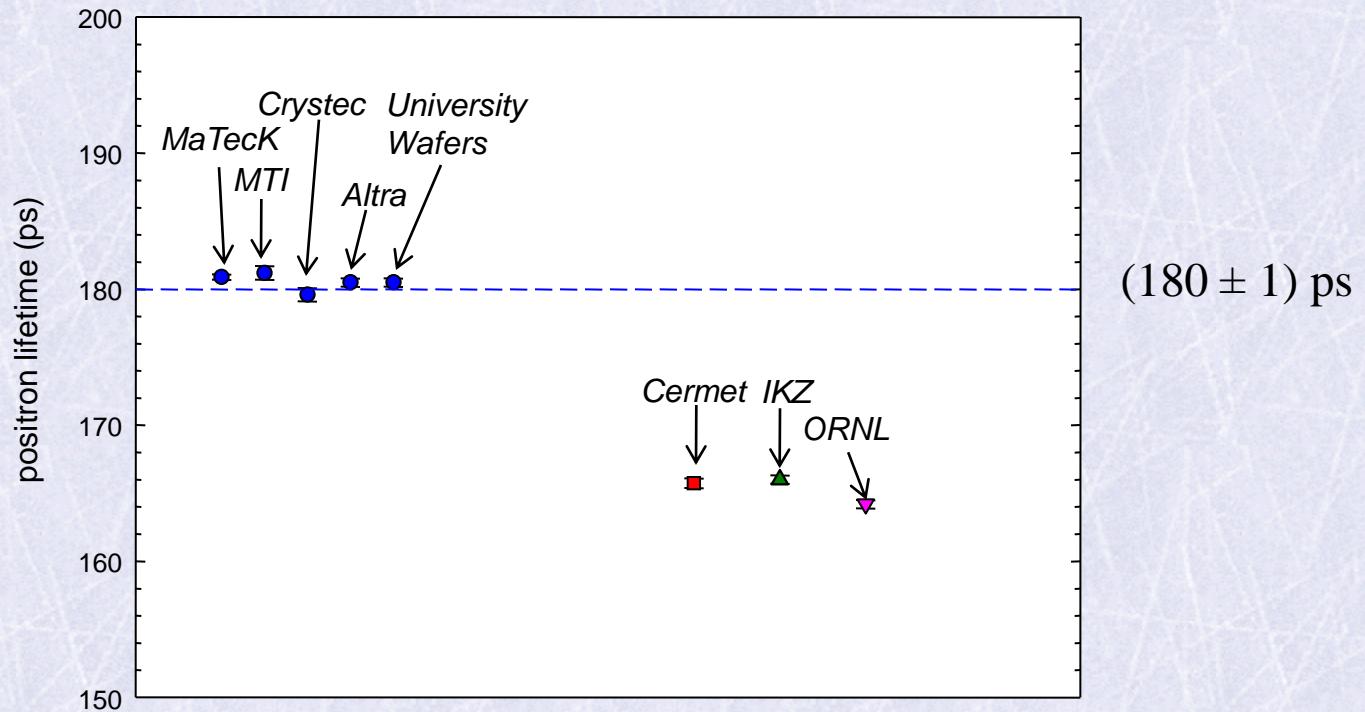
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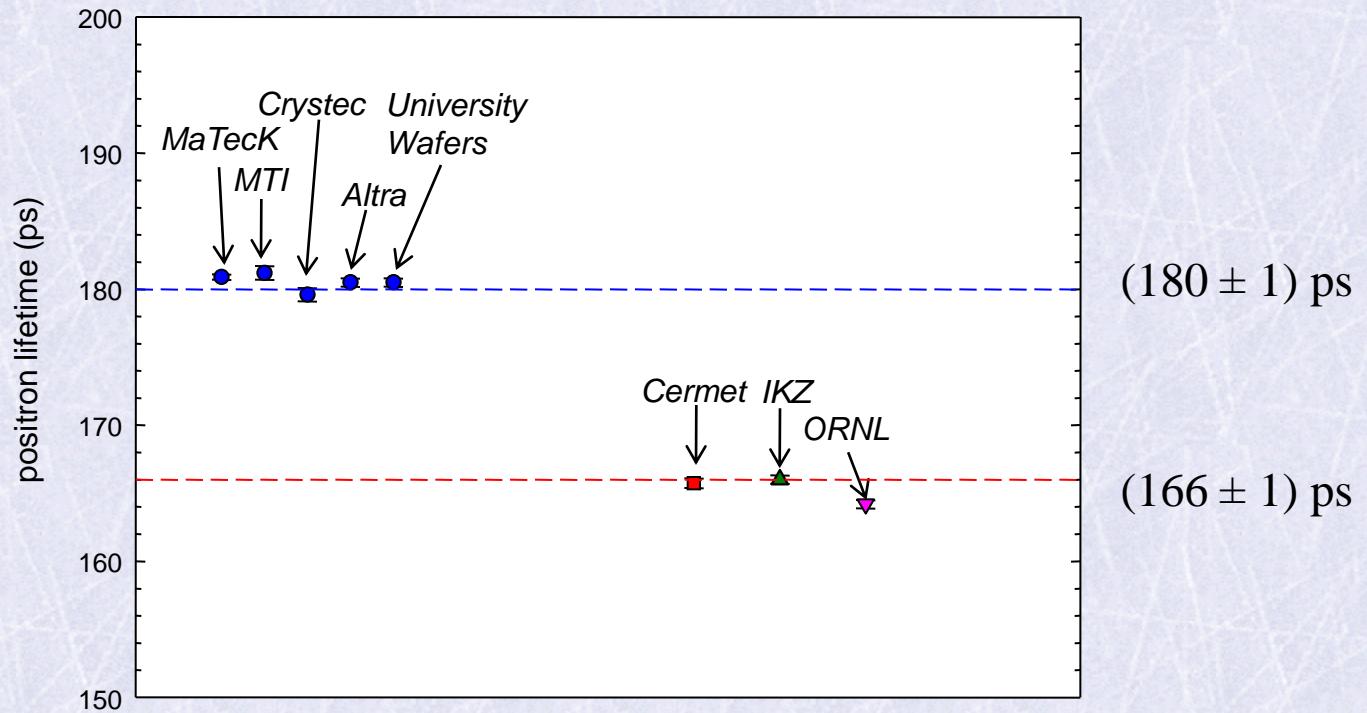
# As-grown ZnO single crystals – comparison of growth techniques

- comparison of ZnO crystals prepared by various techniques
- two groups → HTG ZnO crystals: lifetime  $\approx 180$  ps



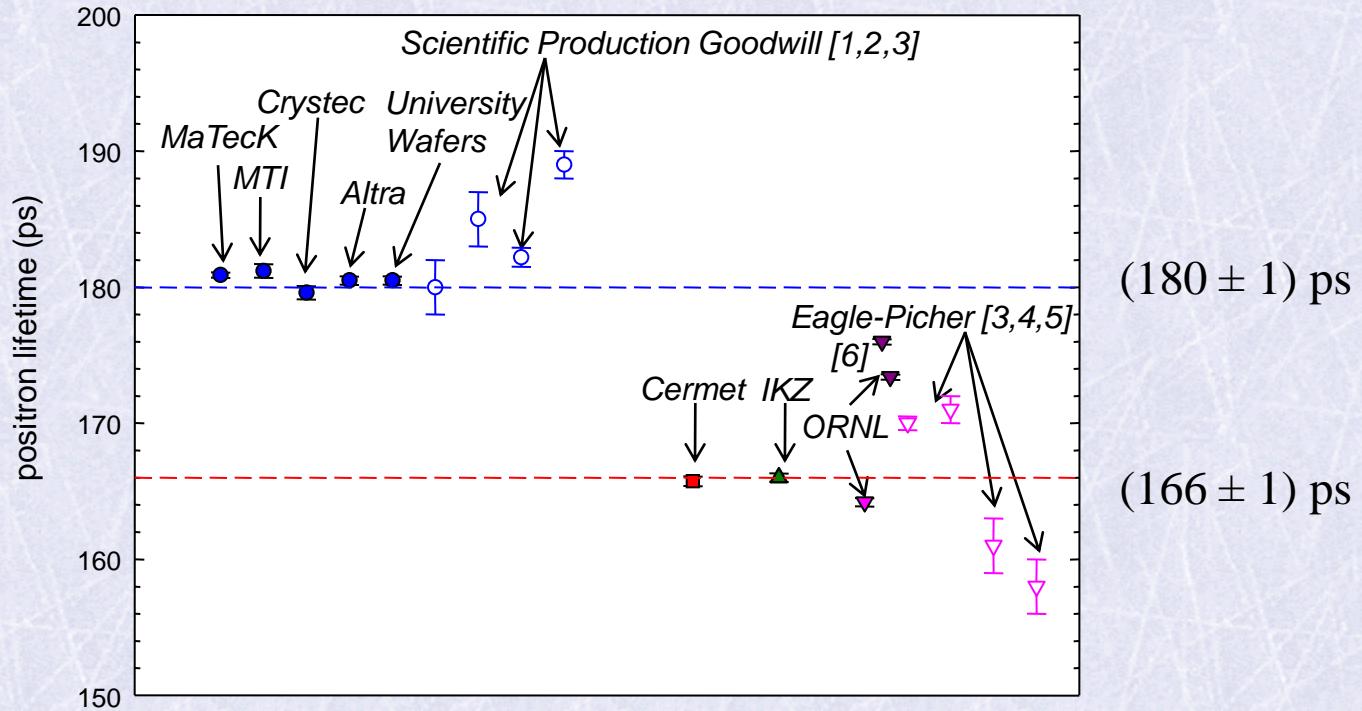
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- two groups
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  - PMG, BG, CVT ZnO crystals: lifetime  $\approx 166$  ps



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  - two groups
    - HTG ZnO crystals: lifetime  $\approx 180$  ps
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[1] F. Tuomisto, D.C. Look, Proc. SPIE **6474**, 647413 (2007)

[2] Z.Q. Chen et al., PRB **71**, 115213 (2005)

[3] Z.Q. Chen et al., JAP **94**, 4807 (2003)

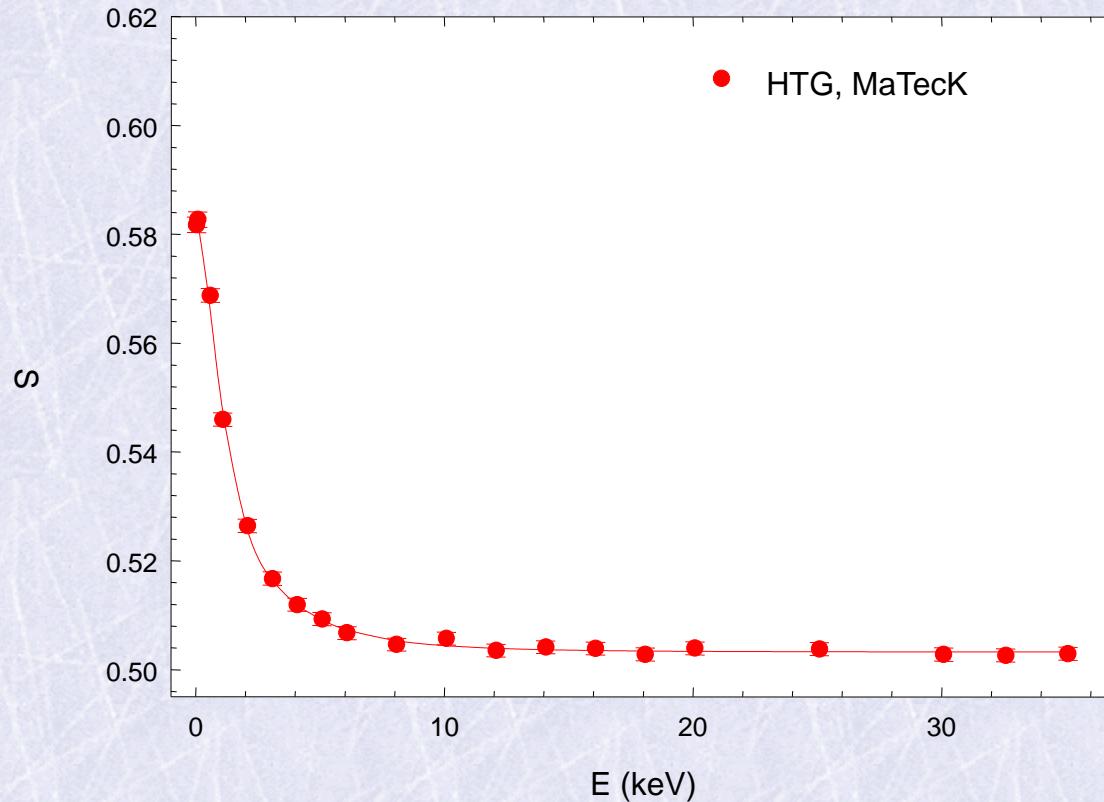
[4] F. Tuomisto et al., PRL **91**, 205502 (2003).

[5] S. Brunner et al., Mater. Sci. Forum **363-365**, 141 (2001).

[6] J. Ji et al. Sci. Reports **6**, 31238 (2016).

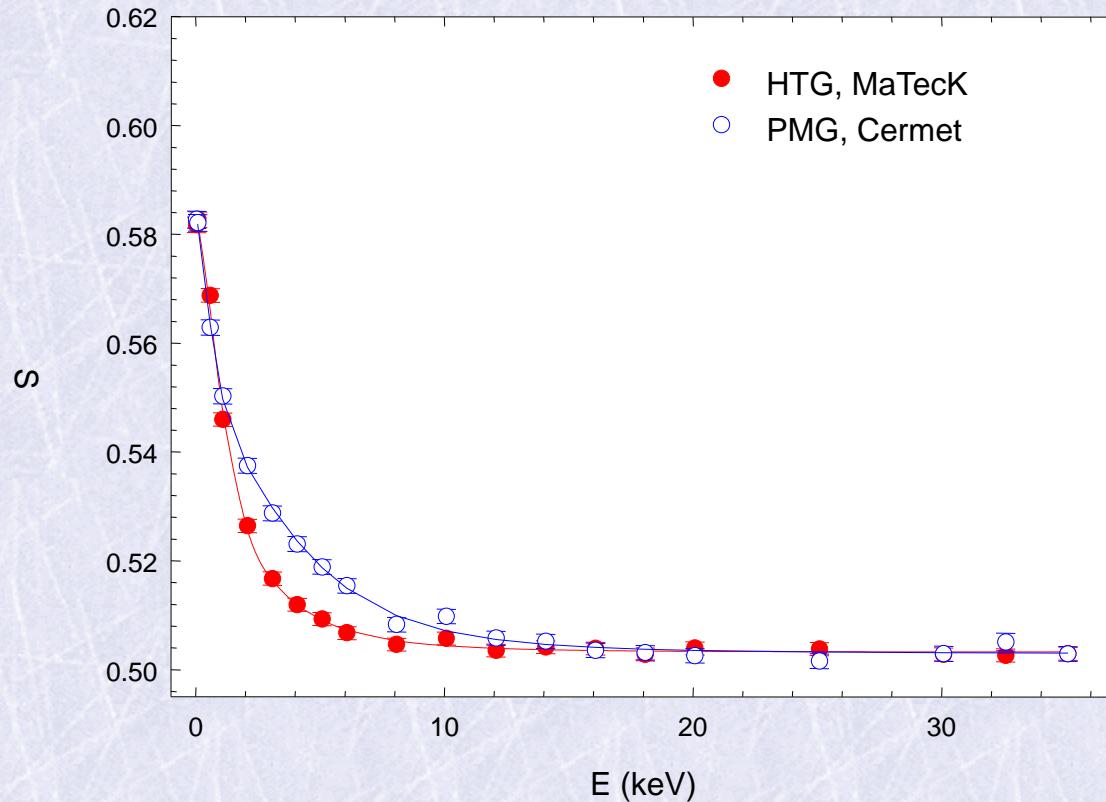
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- positron back-diffusion measurement using slow positron beam
- comparison of ZnO crystals prepared by various techniques



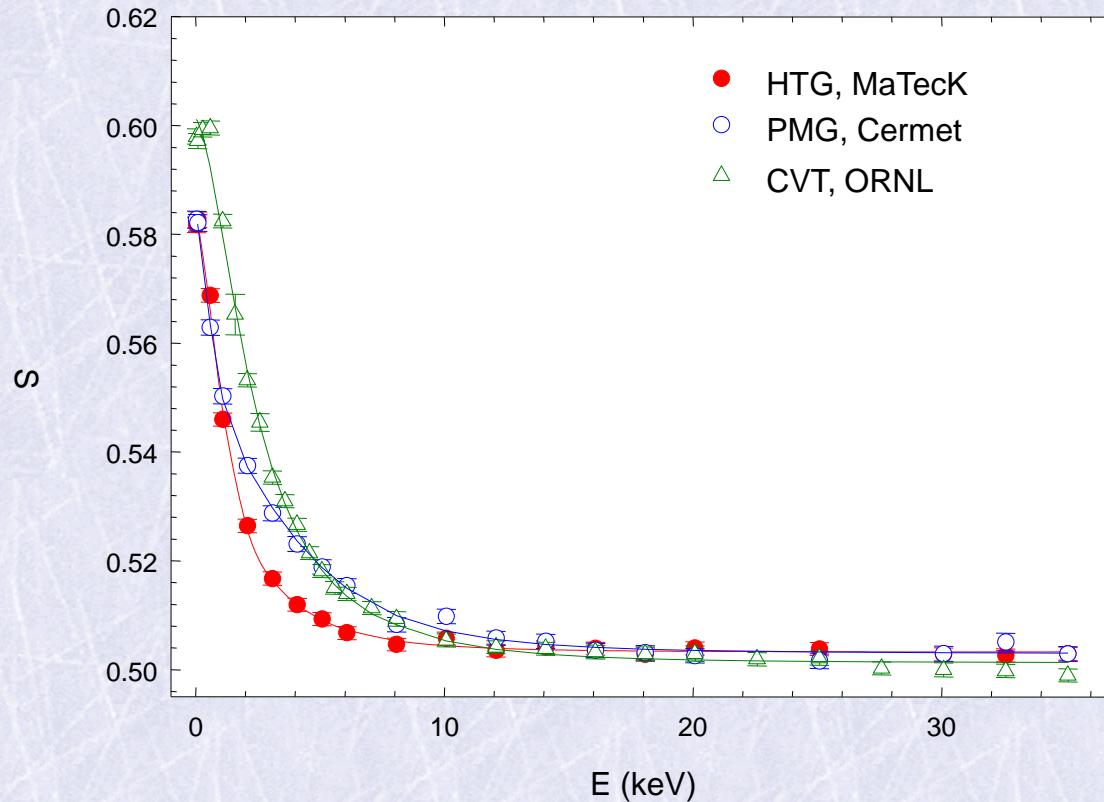
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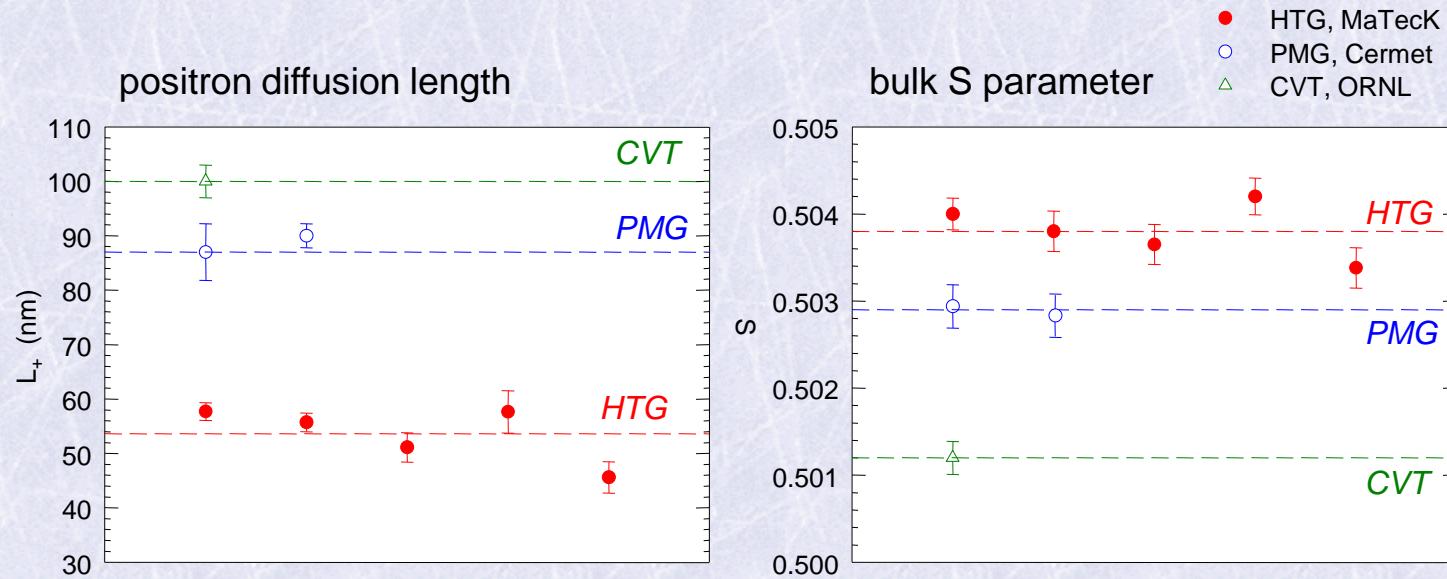
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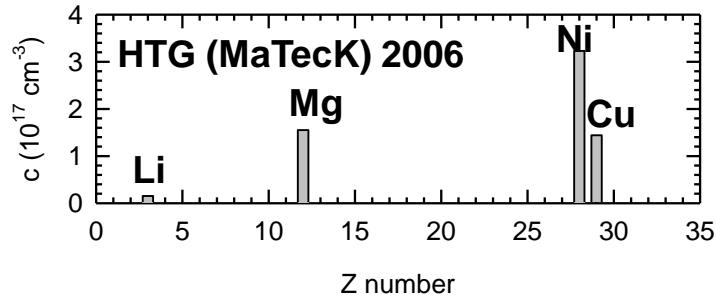
# As-grown ZnO single crystals – comparison of growth techniques

- positron back-diffusion measurement using slow positron beam
- comparison of ZnO crystals prepared by various techniques
- concentration of defects: CVT → PMG → HTG
- HTG crystals from various producers (MaTecK, Crystec, MTI,...) are comparable



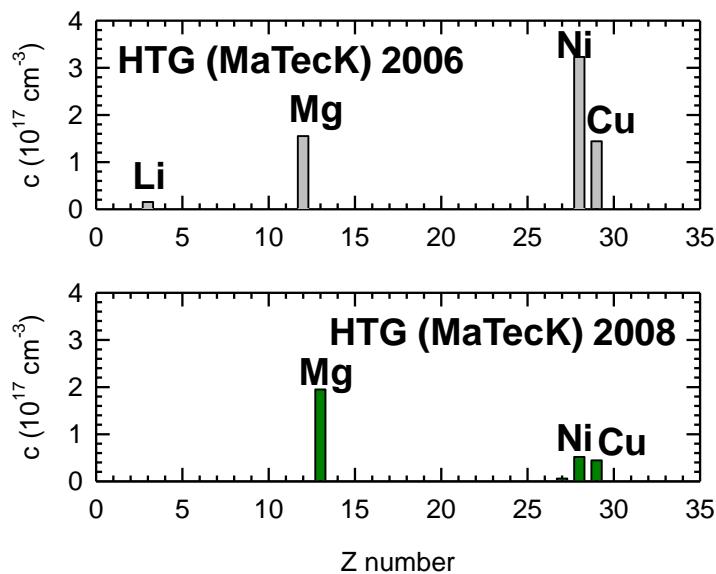
# Chemical Analysis of ZnO crystals

- Inductively Coupled Plasma Source – Mass Spectrometry (ICP-MS)
- Glow discharge Mass Spectrometry (GDMS)      sensitivity 5 ppb ( $2 \times 10^{14} \text{ cm}^{-3}$ )



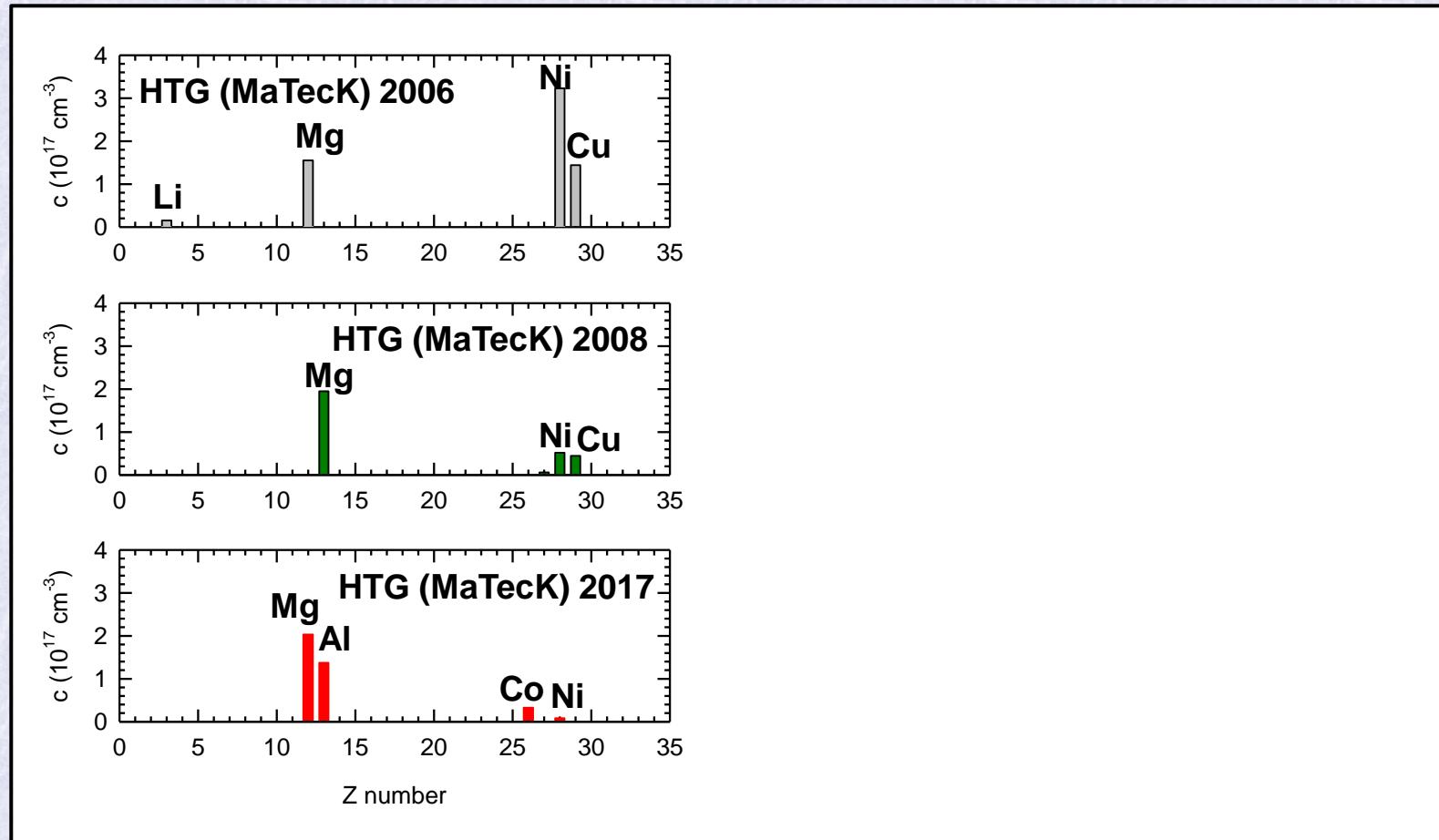
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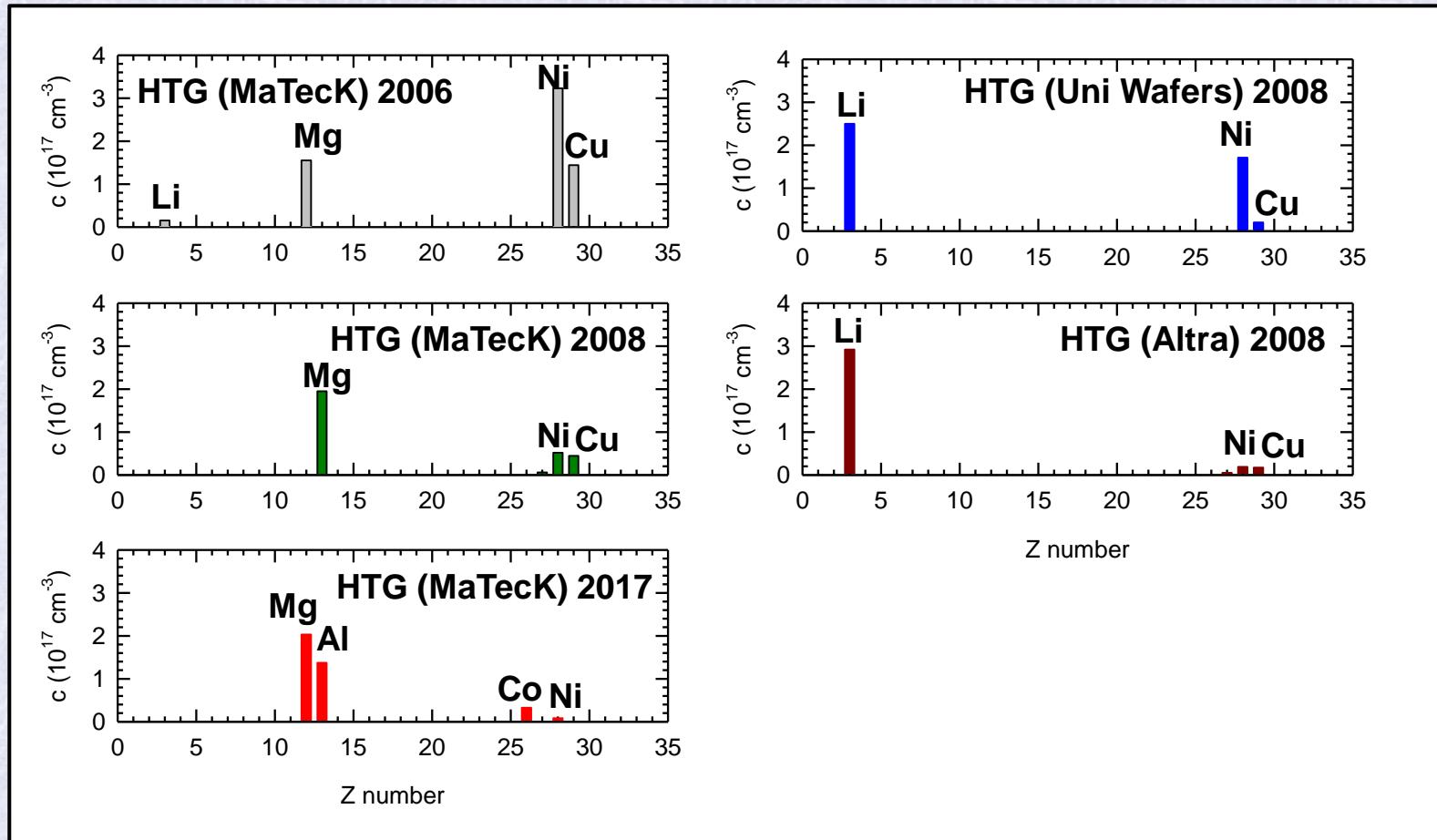
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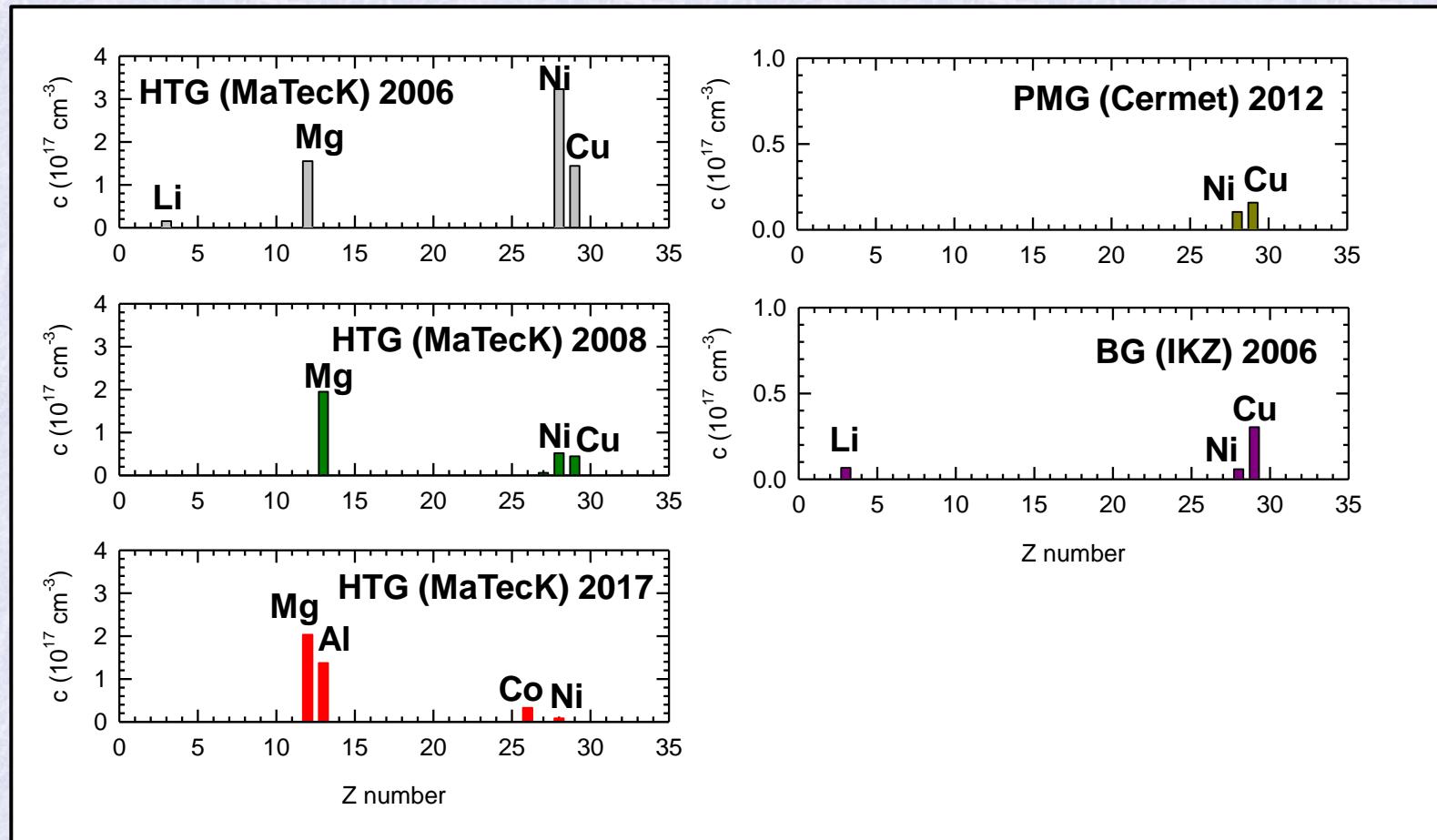
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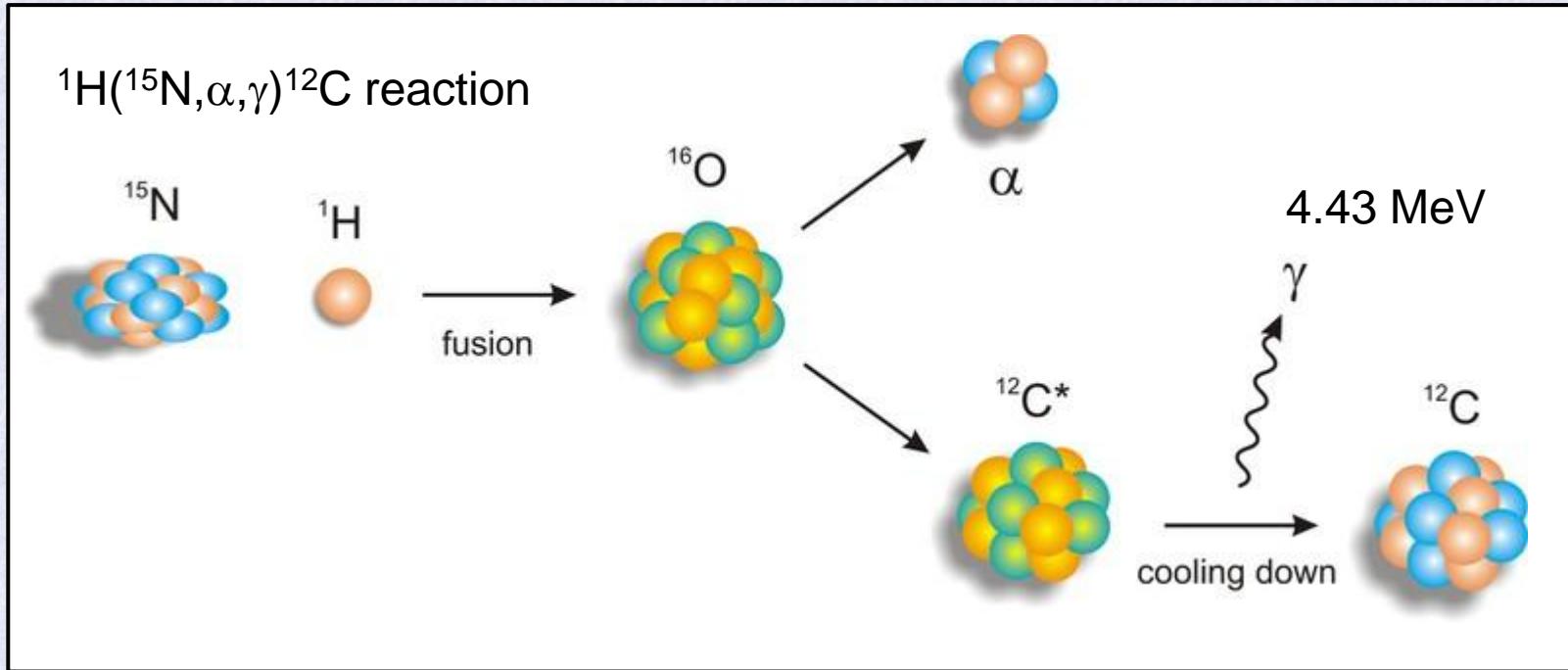
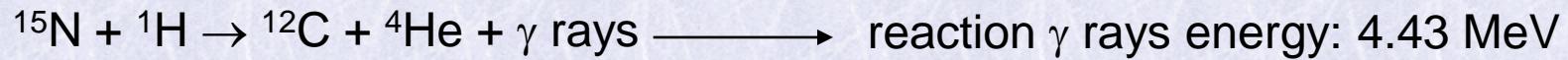
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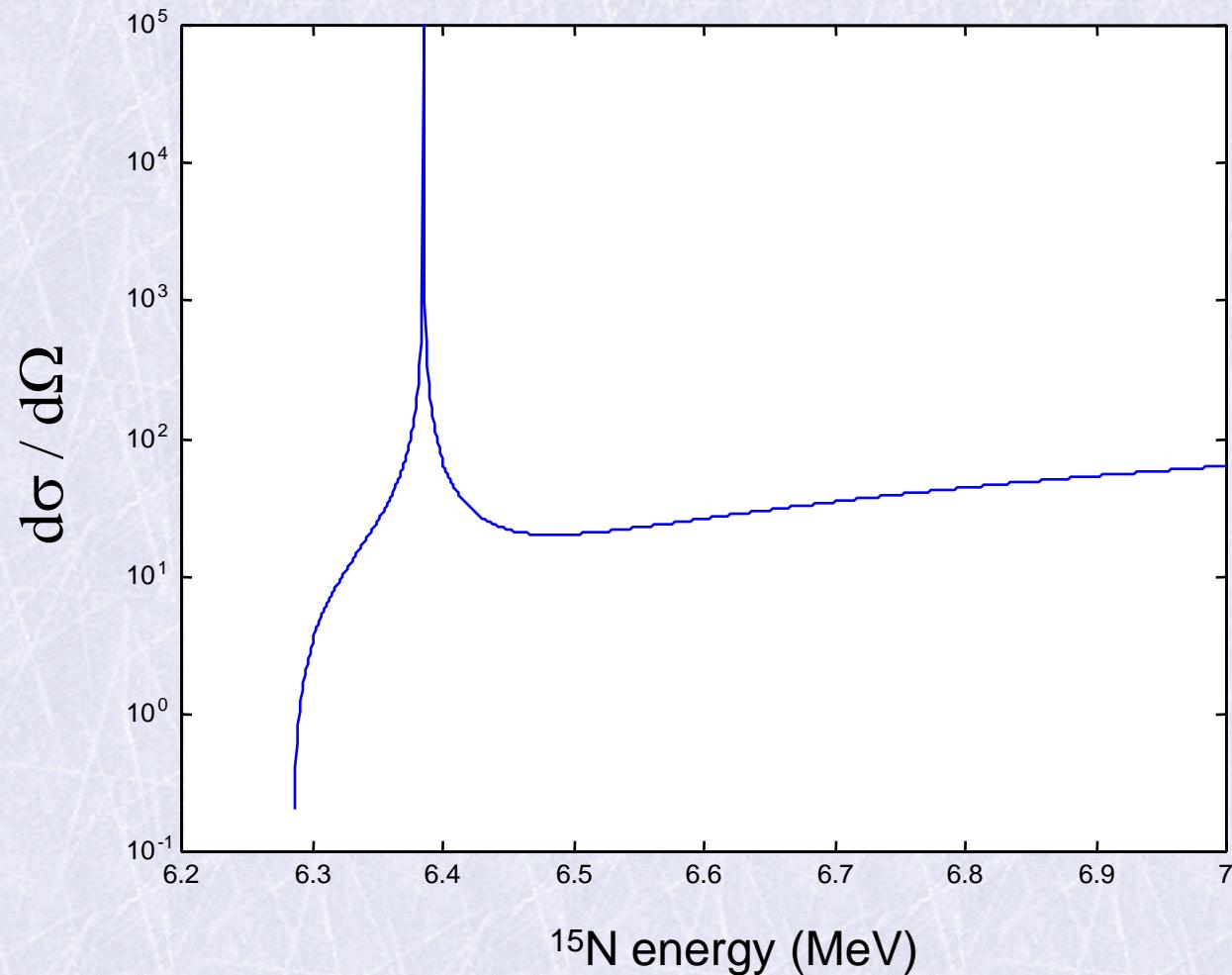
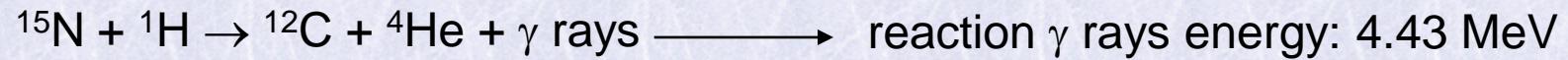
# Determination of hydrogen concentration

## nuclear reaction analysis (NRA)



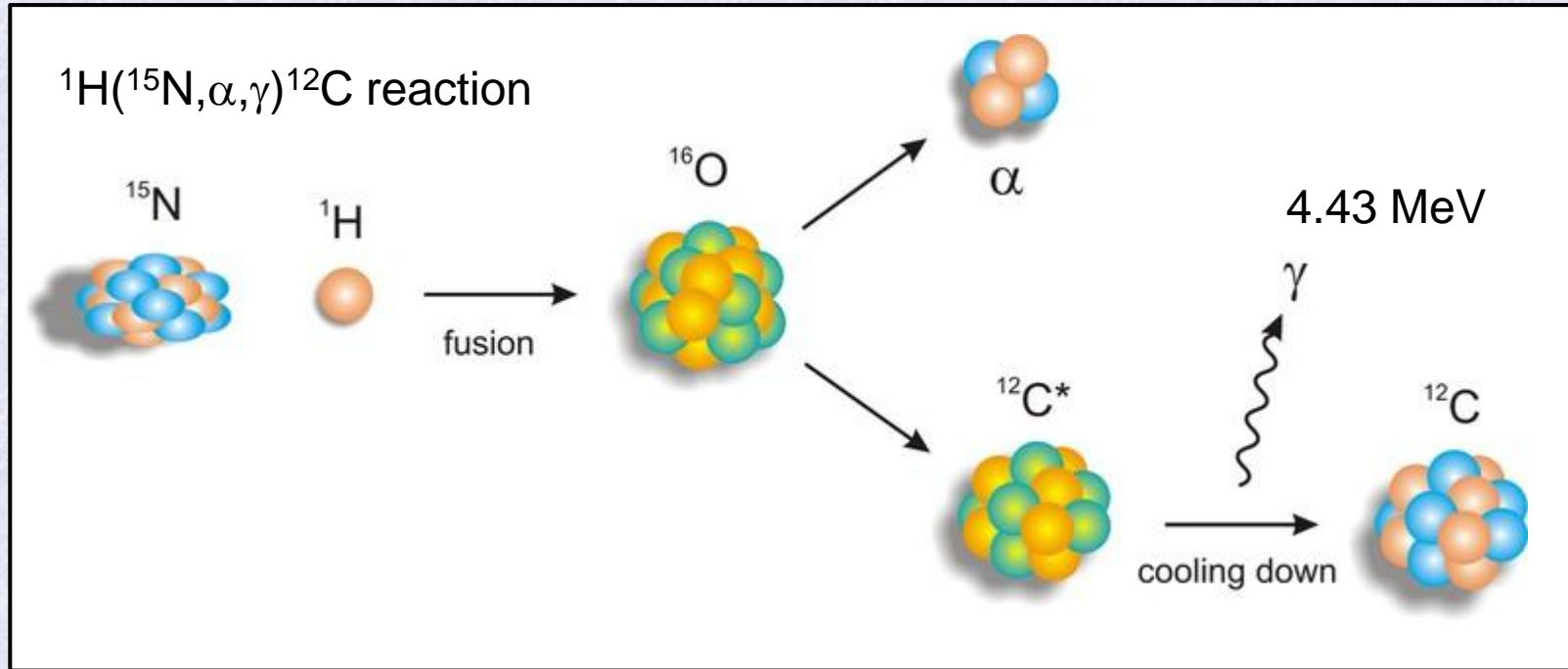
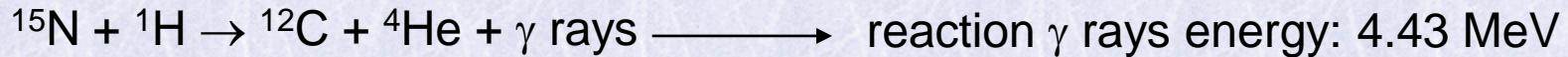
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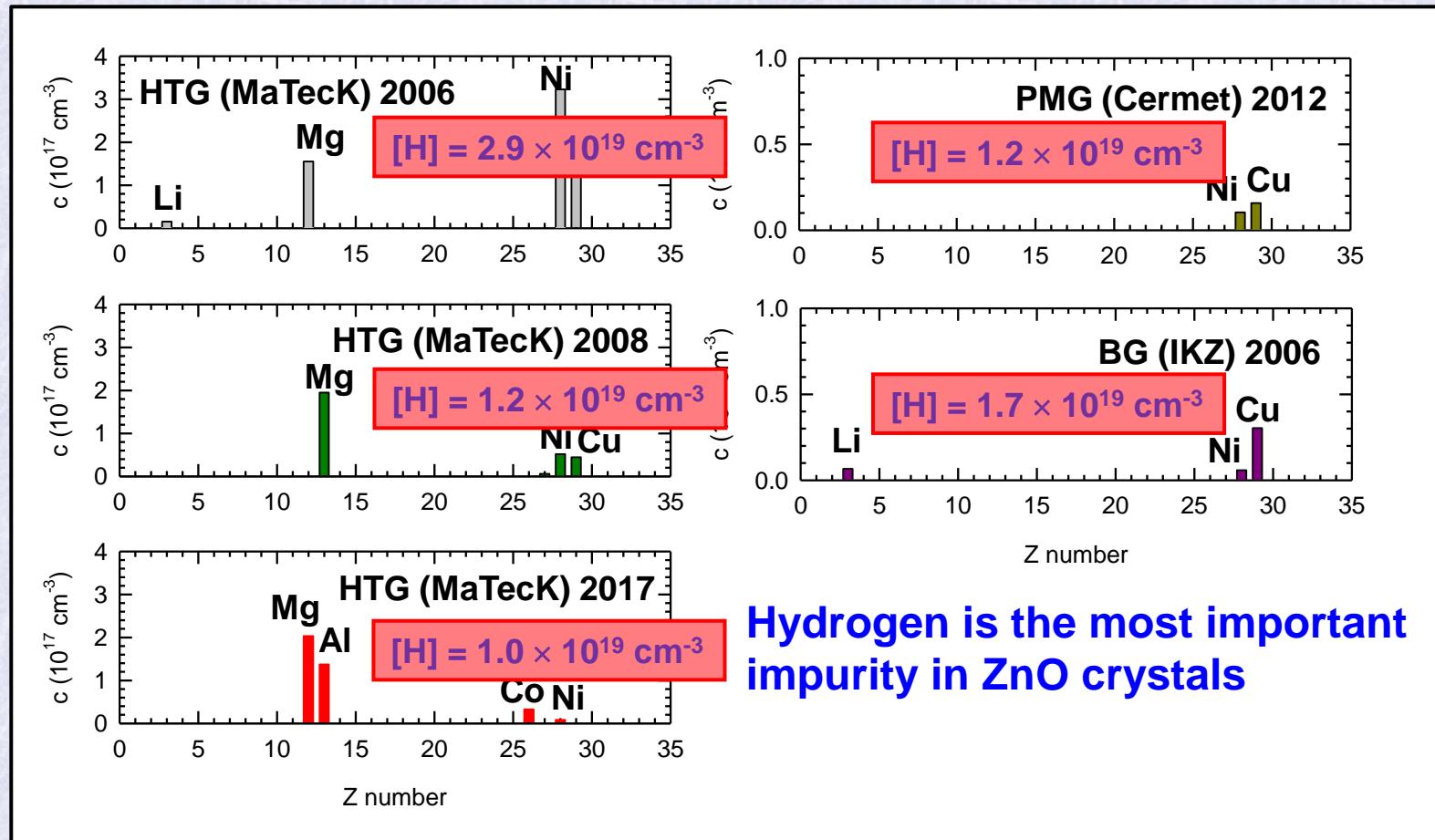


- depth NRA scan

- gradually increasing energy of  $^{15}\text{N}$  ions:  $E = 6.4 - 7.1 \text{ MeV}$
- detection depth in ZnO increasing from surface up to 300 nm
- detection limit: 5 ppm

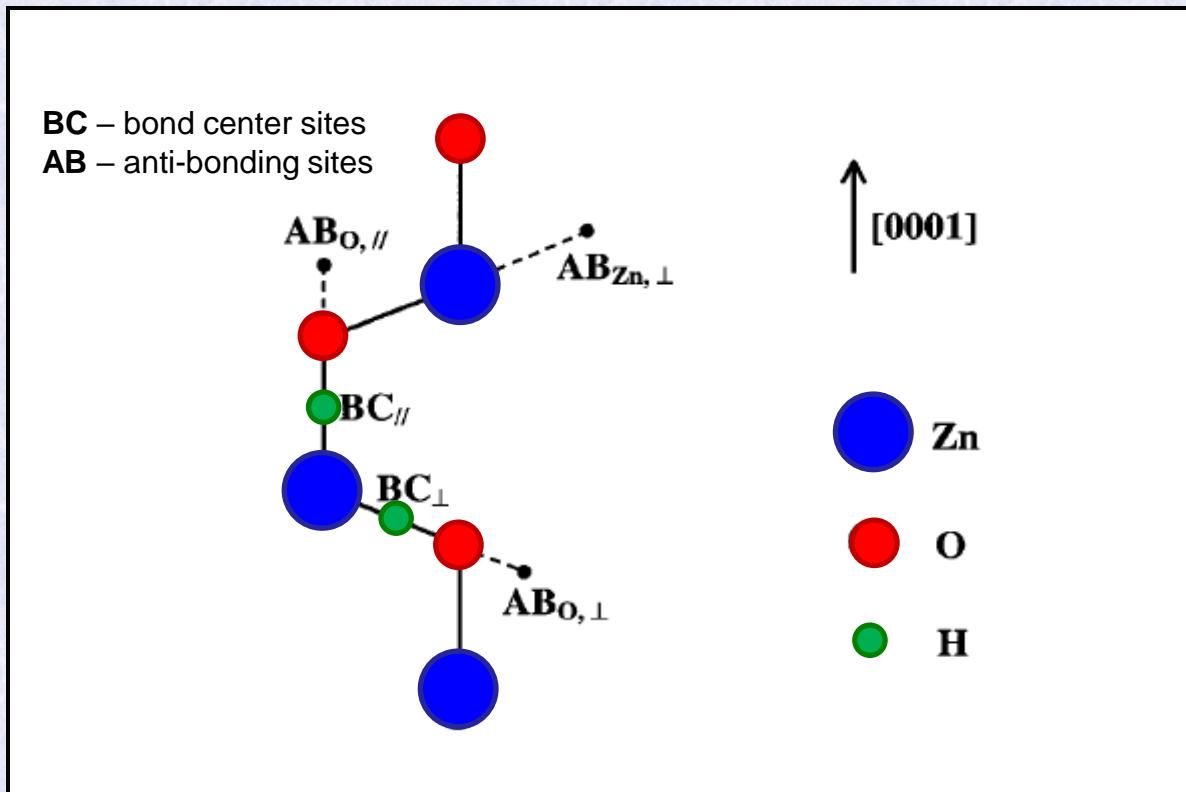
# Chemical Analysis of ZnO crystals

- Inductively Coupled Plasma Source – Mass Spectrometry (ICP-MS)
- Nuclear reaction analysis (NRA)



# Interstitial hydrogen in ZnO

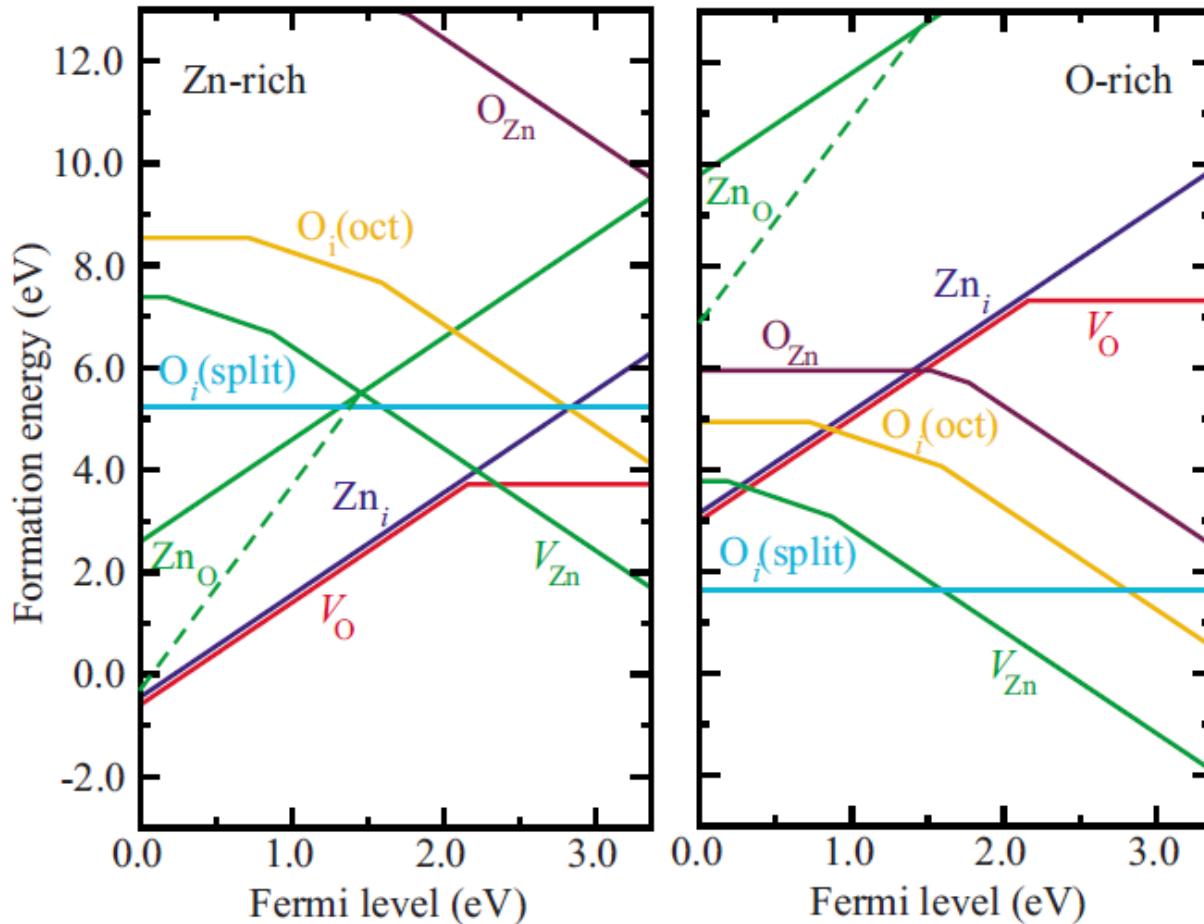
- Hydrogen occupies bond centered (BC) sites in ZnO lattice
- *Van de Walle et al., PRL 85, 1012 (2000)*
- *Janotti et al., Nature Mater. 6, 44 (2007)*



# Points defects in ZnO

A. Janotti, C.G. Van de Walle, PRB **76**, 165202 (2007)

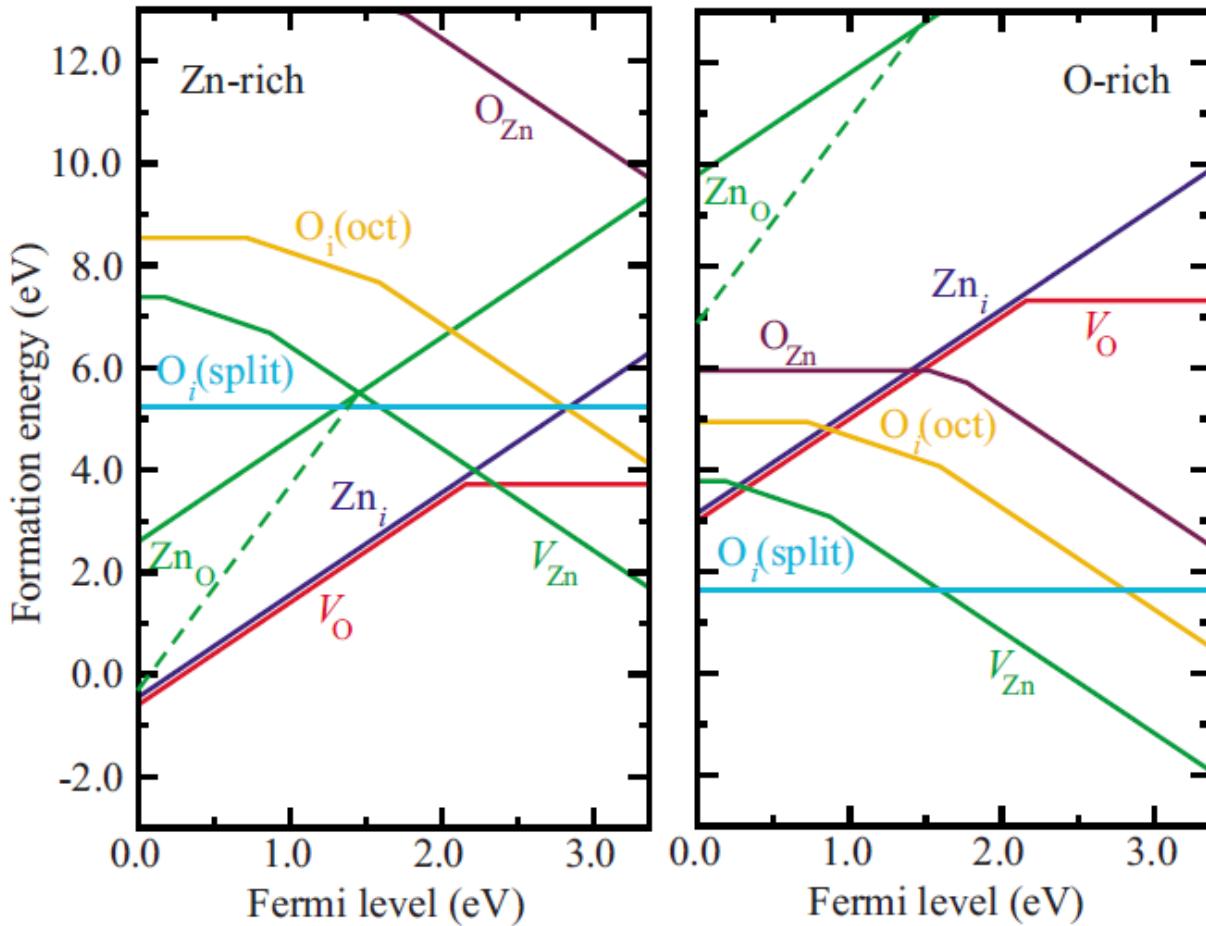
- calculated formation energies of intrinsic points defects in ZnO



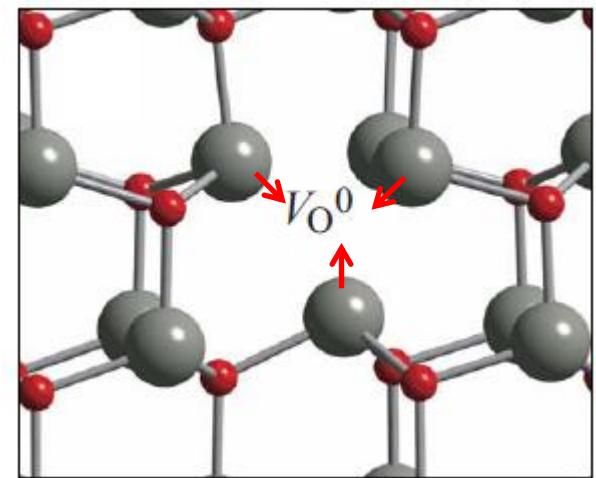
# Oxygen vacancy ( $V_O$ )

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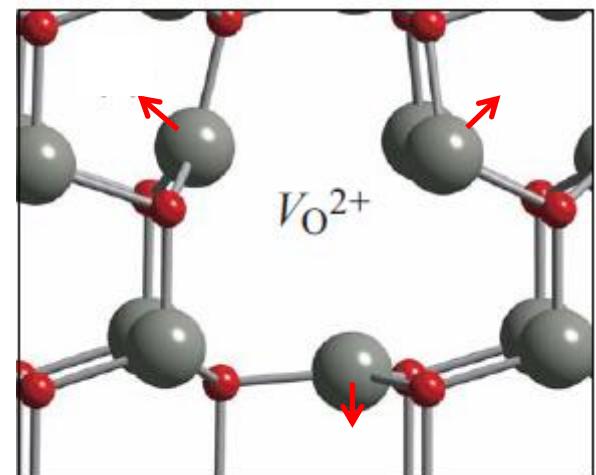
- $V_O^+$  is thermodynamically unstable (negative U-centre)



$V_O^0$  12% inward relaxation



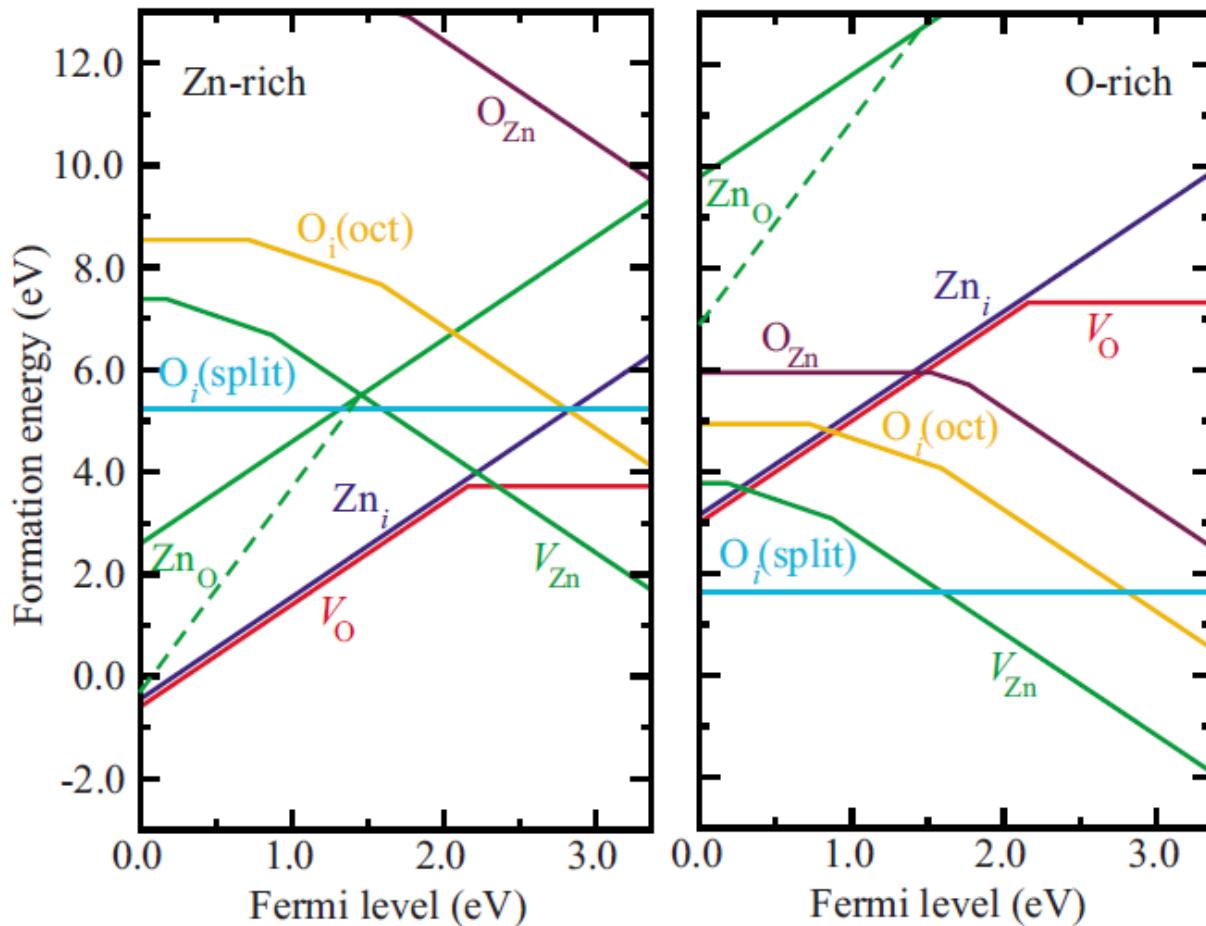
$V_O^{2+}$  23% outward relaxation



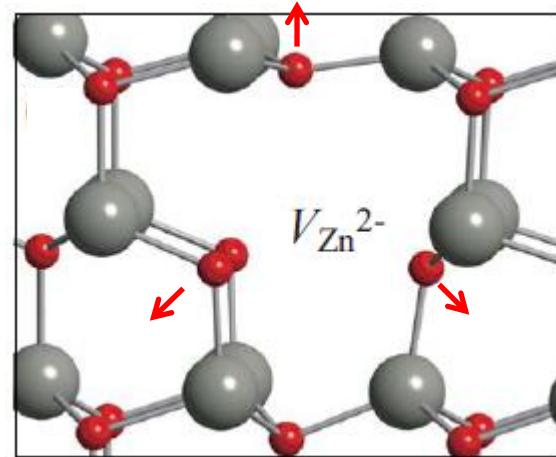
# Zinc vacancy ( $V_{\text{Zn}}$ )

A. Janotti, C.G. Van de Walle, PRB **76**, 165202 (2007)

- low formation energy in n-type ZnO in O-rich conditions



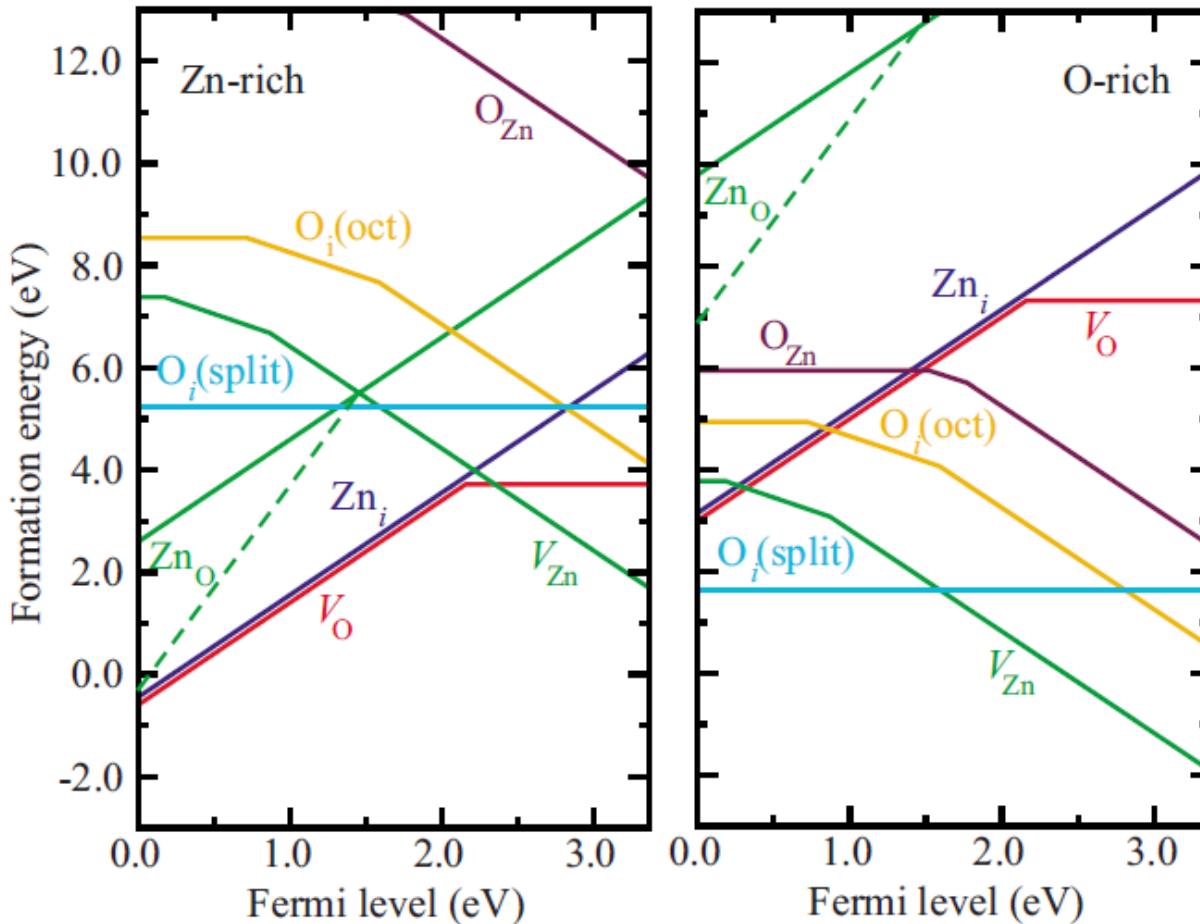
$V_{\text{Zn}}$  10% outward relaxation



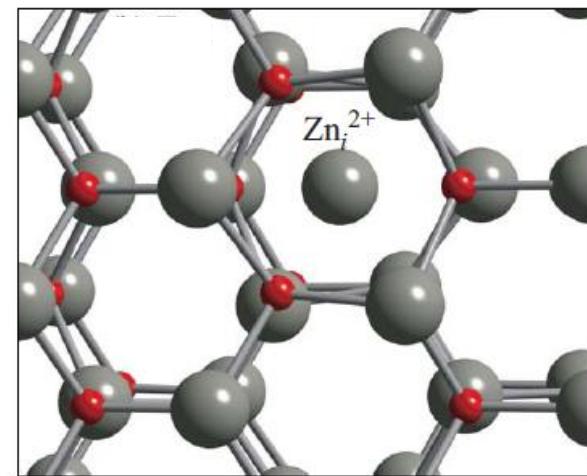
# Zinc interstitial ( $\text{Zn}_i$ )

A. Janotti, C.G. Van de Walle, PRB **76**, 165202 (2007)

- high formation energy in n-type ZnO even in Zn-rich conditions

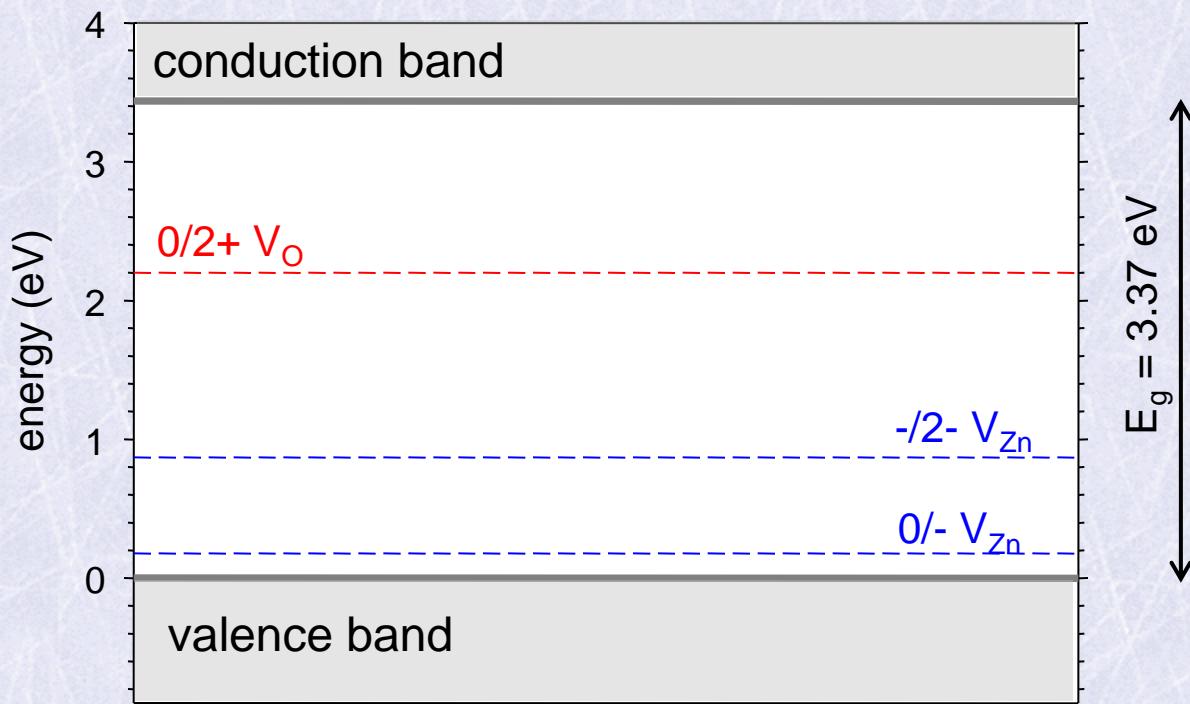


octahedral interstitial site  
in the “channel” along the c-axis



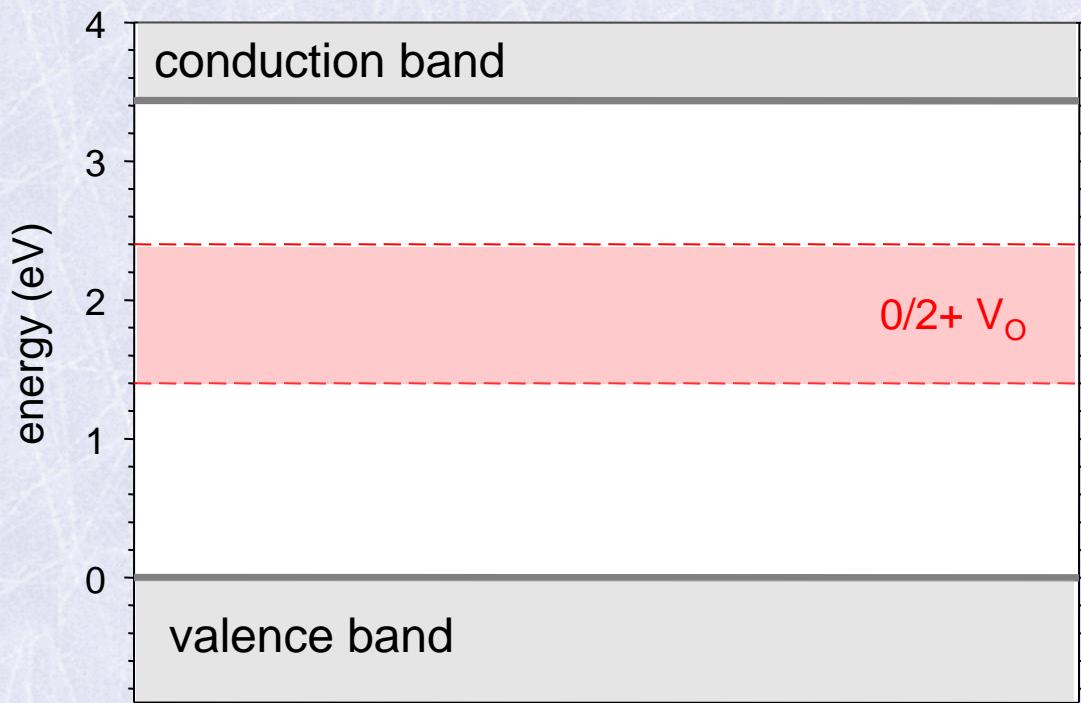
# Points defects in ZnO

- calculated defect charge transition levels
- A. Janotti, C.G. Van de Walle, PRB **76**, 165202 (2007)



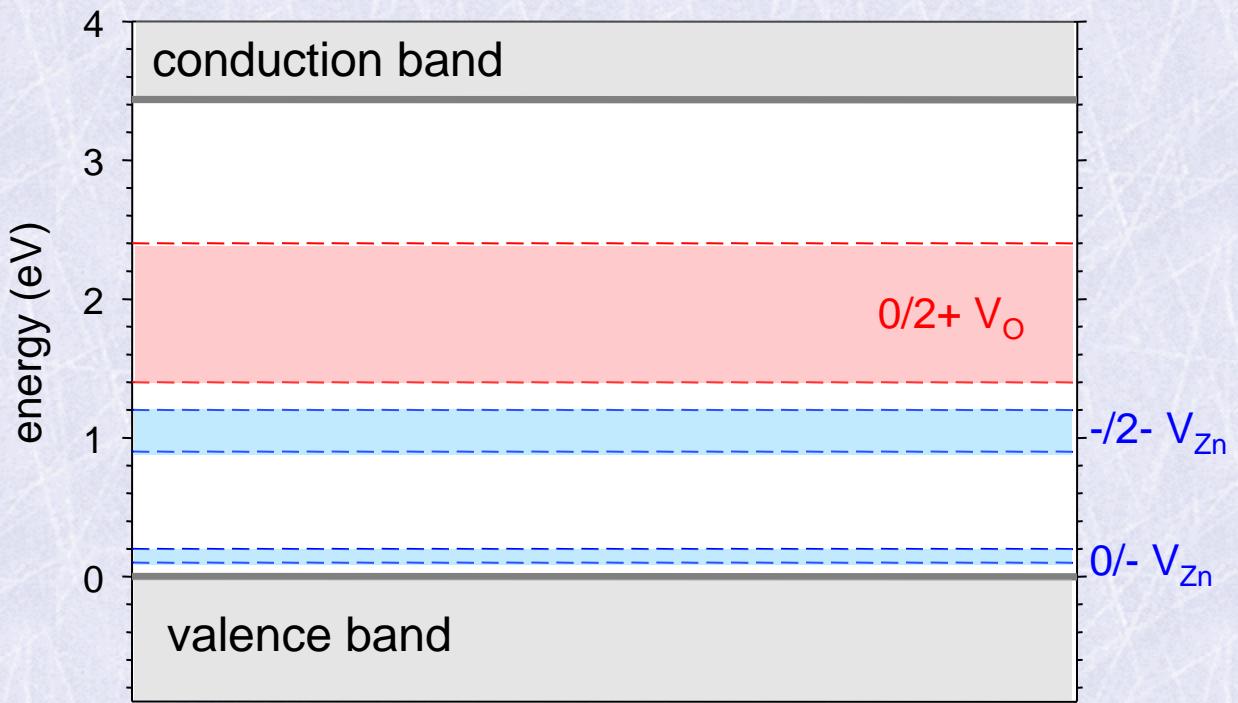
## Points defects in ZnO

- calculated defect charge transition levels
- $V_O$  is deep donor



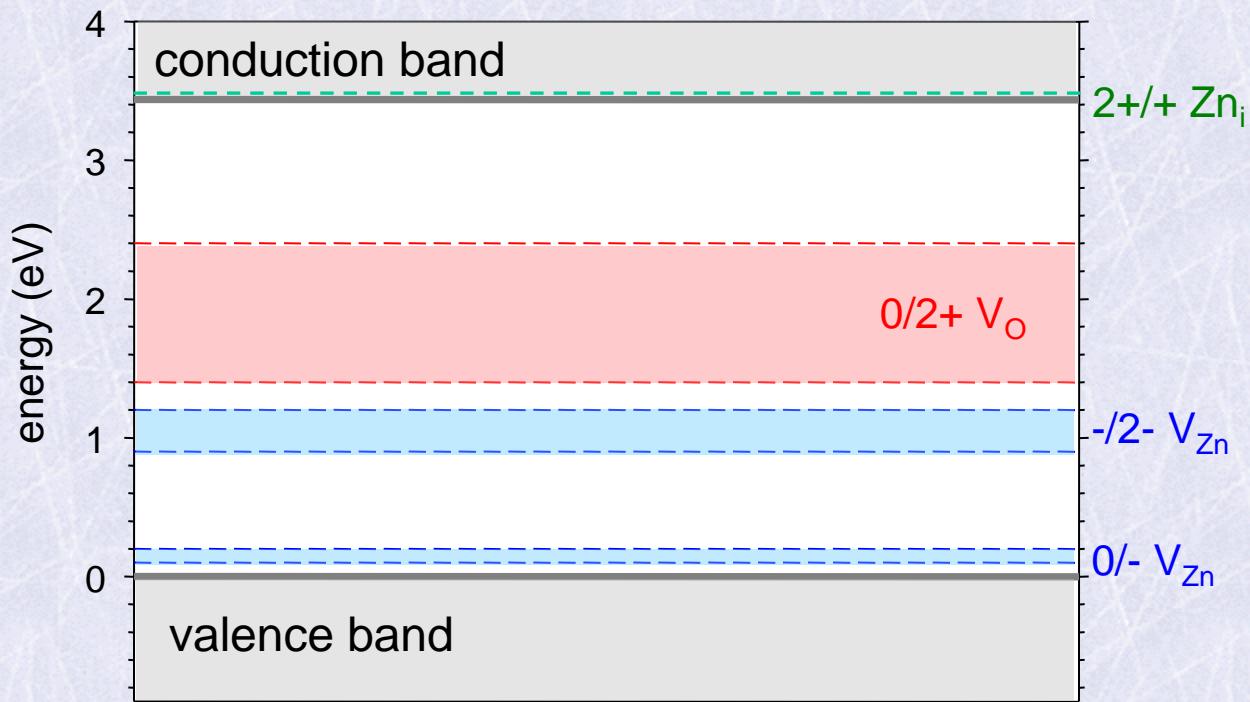
## Points defects in ZnO

- calculated defect charge transition levels
- $V_O$  is deep donor
- $V_{Zn}$  is deep acceptor



## Points defects in ZnO

- calculated defect charge transition levels
- $V_O$  is deep donor
- $V_{Zn}$  is deep acceptor
- $Zn_i$  is shallow donor

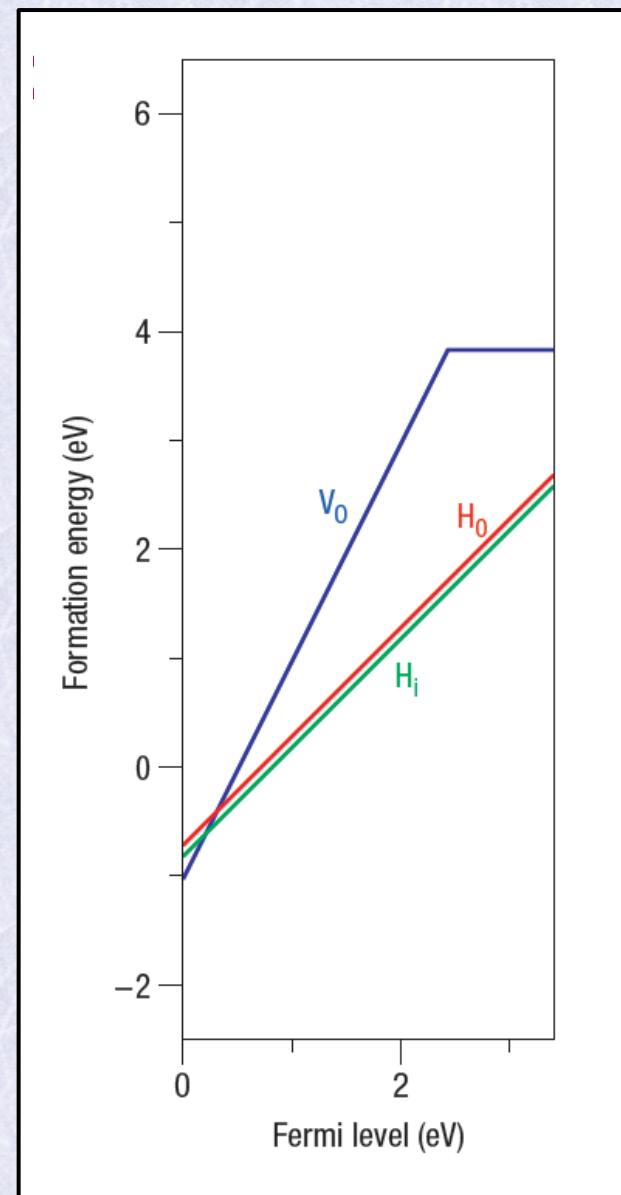
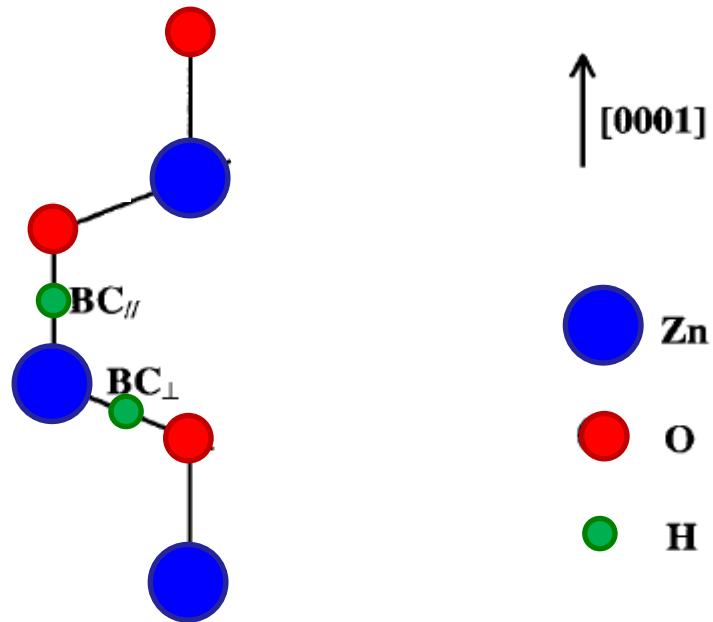


# Hydrogen in ZnO

A. Janotti, Ch. Van de Walle,  
Nature Mater. **6**, 44 (2007)

- interstitial hydrogen in ZnO is shallow donor
- hydrogen is in  $H^+$  charge state

**BC** – bond center sites



# Theoretical calculations of positron lifetimes in ZnO

Vacancies in ZnO    *G. Brauer et al., PRB 79, 115212 (2009)*

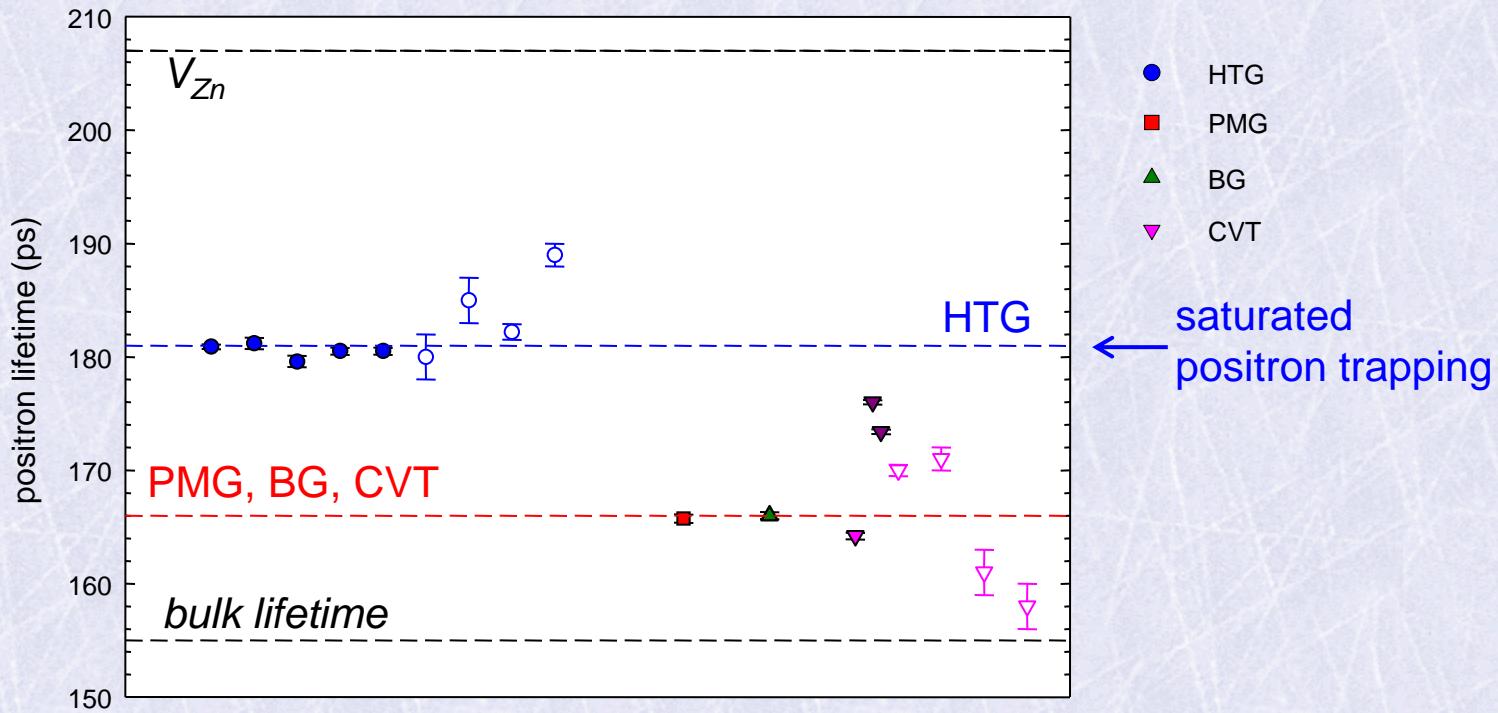
- LDA (Boroński-Nieminen) approach for electron-positron correlation
- with correction for incomplete positron screening,  $\varepsilon_\infty = 4$
- self consistent electron density and potential from VASP
- relaxed geometry of vacancies determined by VASP
- positron-induced forces were taken into account

|   | $\tau$ (ps)                         | $E_B$ (ev) | $\tau / \tau_B$ |
|---|-------------------------------------|------------|-----------------|
| e <sup>-</sup> e <sup>+</sup> correlation | LDA (BN, $\varepsilon_\infty = 4$ ) |            |                 |
| ZnO bulk                                  | 154                                 | -          | -               |
| O-vacancy                                 | 154                                 | ~ 0.0      | 1.00            |
| Zn-vacancy                                | 207                                 | 1.11       | 1.34            |
| Zn+O di-vacancy                           | 253                                 | 1.87       | 1.64            |

----->  $V_O$  is unable of positron trapping  
----->  $V_{Zn}$  is deep positron trap

# As-grown ZnO single crystals – comparison of growth techniques

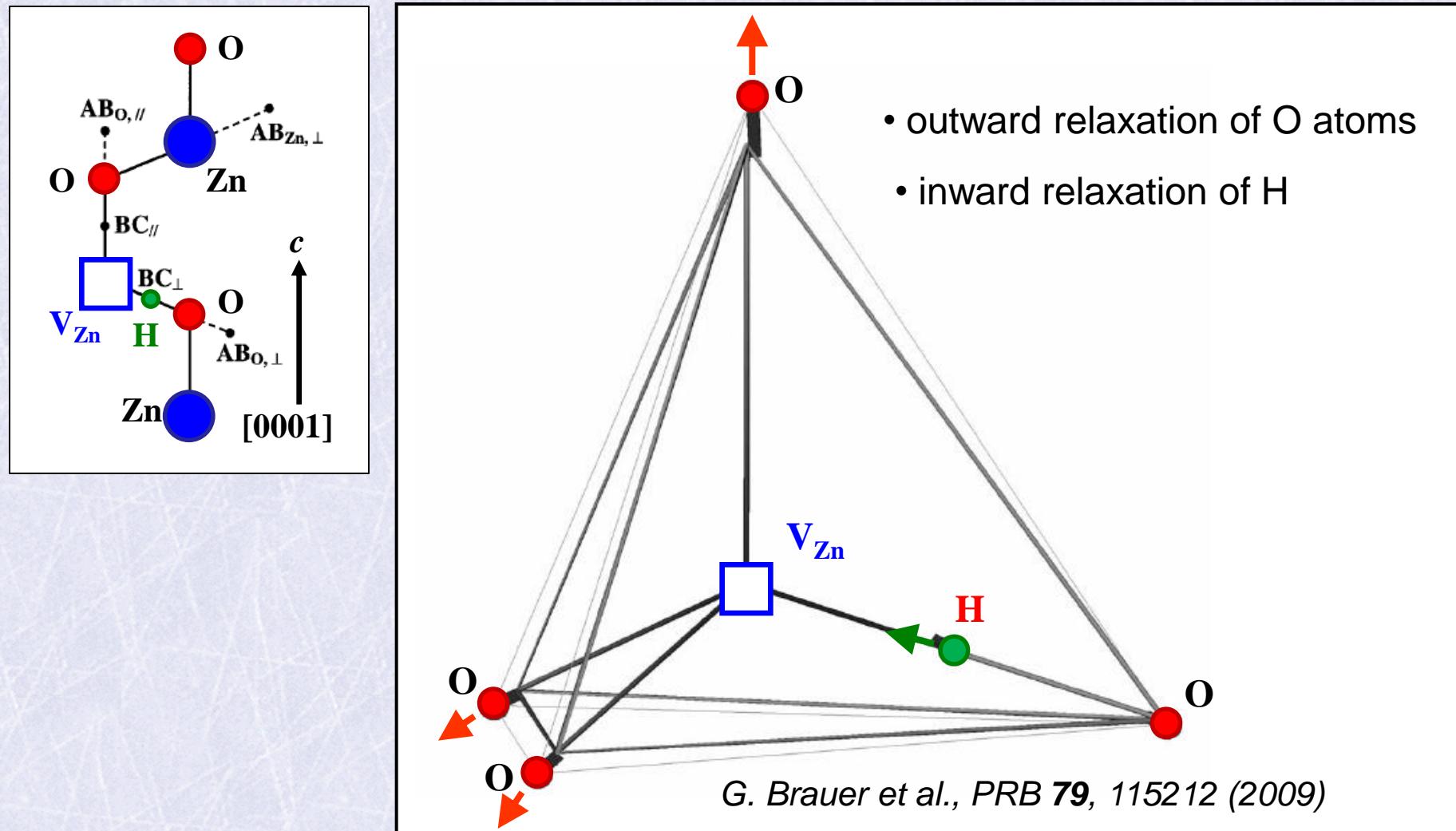
- comparison of ZnO crystals prepared by various techniques
  - two groups
    - HTG ZnO crystals:  $\tau \approx 180$  ps  $\rightarrow \tau_B < \tau < \tau_{\text{Zn-vacancy}}$
    - PMG, BG, CVT ZnO crystals:  $\tau \approx 166$  ps



# Complexes $V_{Zn} + H$

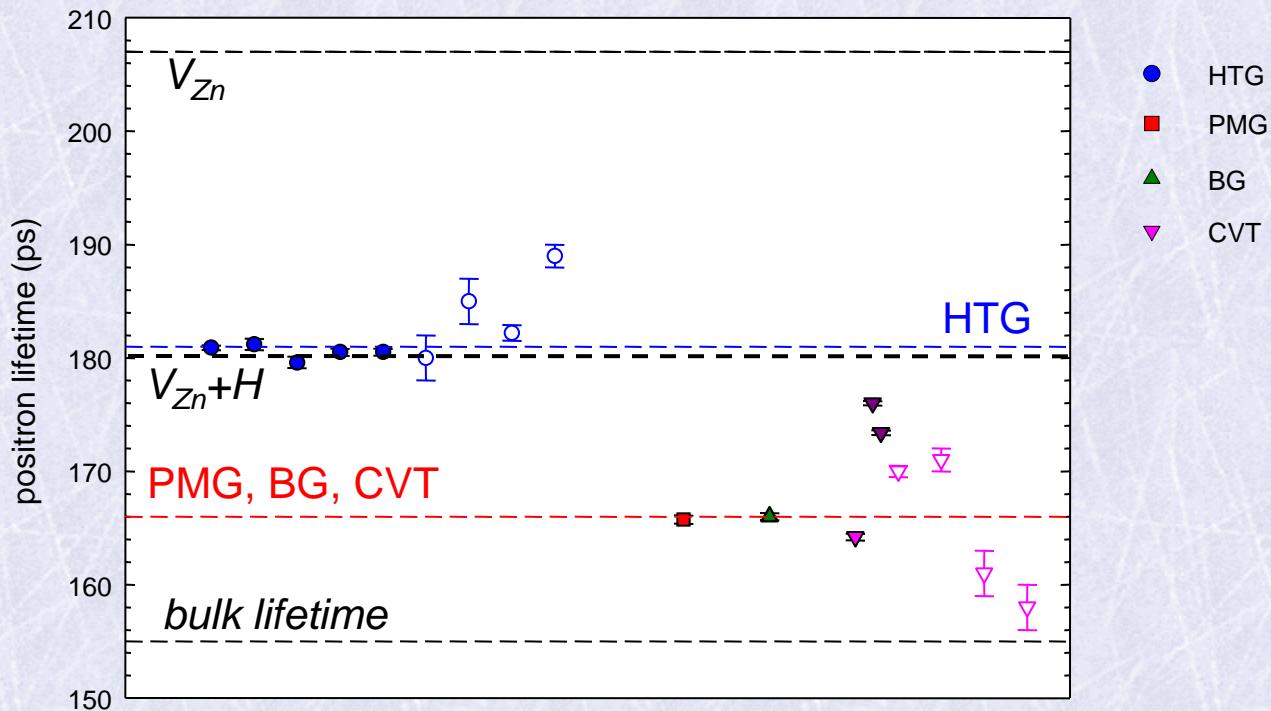
Calculated lowest energy configuration:  $V_{Zn} + 1H$ ,  $BC_{\perp}$  site,  $\tau = 179$  ps

relaxation of O atoms and H



# As-grown ZnO single crystals – comparison of growth techniques

- comparison of ZnO crystals prepared by various techniques
  - two groups
    - HTG ZnO crystals:  $\tau \approx 180$  ps  $\rightarrow V_{Zn}+H$  complexes
    - PMG, BG, CVT ZnO crystals:  $\tau \approx 166$  ps



# Estimation of $V_{Zn+H}$ concentration

HTG ZnO, MaTecK

- estimation of  $V_{Zn}+H$  concentration

$$\left. \begin{array}{l} c_V = \frac{1}{\nu_v} \frac{1}{\tau_B} \left( \frac{L_{+,B}^2}{L_+^2} - 1 \right) \\ L_{+,B} \approx 100 \text{ nm (CVT ZnO)} \\ \nu_v \approx 10^{15} \text{ at.s}^{-1} \\ \tau_B = 154 \text{ ps} \end{array} \right\} \text{HTG ZnO} \quad [V_{Zn+H}] \Rightarrow c_v \approx 10 \text{ ppm} \quad (4 \times 10^{17} \text{ cm}^{-3})$$

simple trapping model

positron trapping rate

$$K_\nu \approx 2 \times 10^{10} \text{ s}^{-1}$$



free positron component

$$I_I \approx 4 \%, \tau_1 \approx 30 \text{ ps}$$



too weak & short  
to be resolved in PL spectrum

- hydrogen concentration (NRA)

$$[H] = (1-3) \times 10^{19} \text{ cm}^{-3} \rightarrow [H] \approx 50 [V_{Zn+H}]$$

# **Li<sub>Zn</sub> defect**

## **HTG ZnO, MaTecK**

- positron trapping in negatively charged substitution Li (Li<sub>Zn</sub>)

*K.M. Johansen et al., PRB **83**, 245208 (2011)*

$$c_V = \frac{1}{\nu_v} \frac{1}{\tau_B} \left( \frac{L_{+,B}^2}{L_+^2} - 1 \right)$$

$$L_{+,B} \approx 100 \text{ nm (CVT ZnO)}$$

$$\nu_v \approx 10^{15} \text{ at.s}^{-1}$$

$$\tau_B = 154 \text{ ps}$$

} **HTG ZnO**  
**[V<sub>Zn</sub>+H]**  
 $\Rightarrow c_v \approx 10 \text{ ppm}$   
 $(4 \times 10^{17} \text{ cm}^{-3})$

- Li concentration (ICPMS, GDMS)

$$[\text{Li}] = (0.008-2.5) \times 10^{17} \text{ cm}^{-3}$$

→ lower than concentration of positron traps

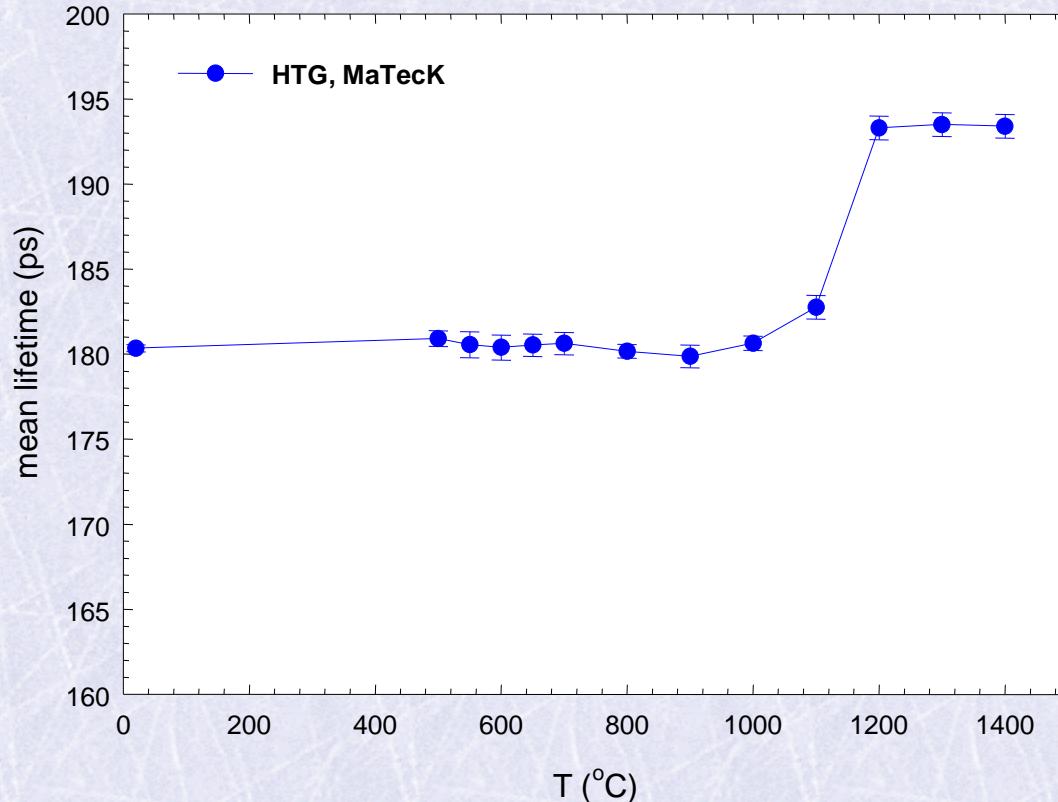
→ strong variations of [Li]  
 but no variations of positron lifetime

| Sample                  | [Li]<br>10 <sup>17</sup> cm <sup>-3</sup> |                    |
|-------------------------|---|--------------------|
| HT-grown<br>MaTecK 2006 | 1.5                                       | <b>181.2(4) ps</b> |
| HT-grown<br>MaTecK 2008 | 0.02                                      | <b>179.6(3) ps</b> |
| HT-grown<br>MaTecK 2017 | 0.008                                     | <b>180.1(3) ps</b> |
| HT-grown<br>Uni-Wafers  | 2.5                                       | <b>180.5(3) ps</b> |
| HT-grown<br>Altramet    | 2.3                                       | <b>180.7(3) ps</b> |
| PM-grown<br>Cermet      | 0.004                                     |                    |
| BG-grown<br>IKZ Berlin  | 0.06                                      |                    |

## Annealing of ZnO crystals in air

- ZnO easily decomposes to its components  $\text{ZnO} \leftrightarrow \text{Zn} + \frac{1}{2} \text{O}_2$ ,  $\Delta H = 350.5 \text{ kJ/mol}$
- upon heating ZnO dissociates
- high vapour pressure of Zn and  $\text{O}_2 \Rightarrow \text{ZnO evaporation}$
- $p_{\text{Zn}} > p_{\text{O}_2} \Rightarrow \text{Zn evaporation is more intensive} \Rightarrow \text{formation of } V_{\text{Zn}}$

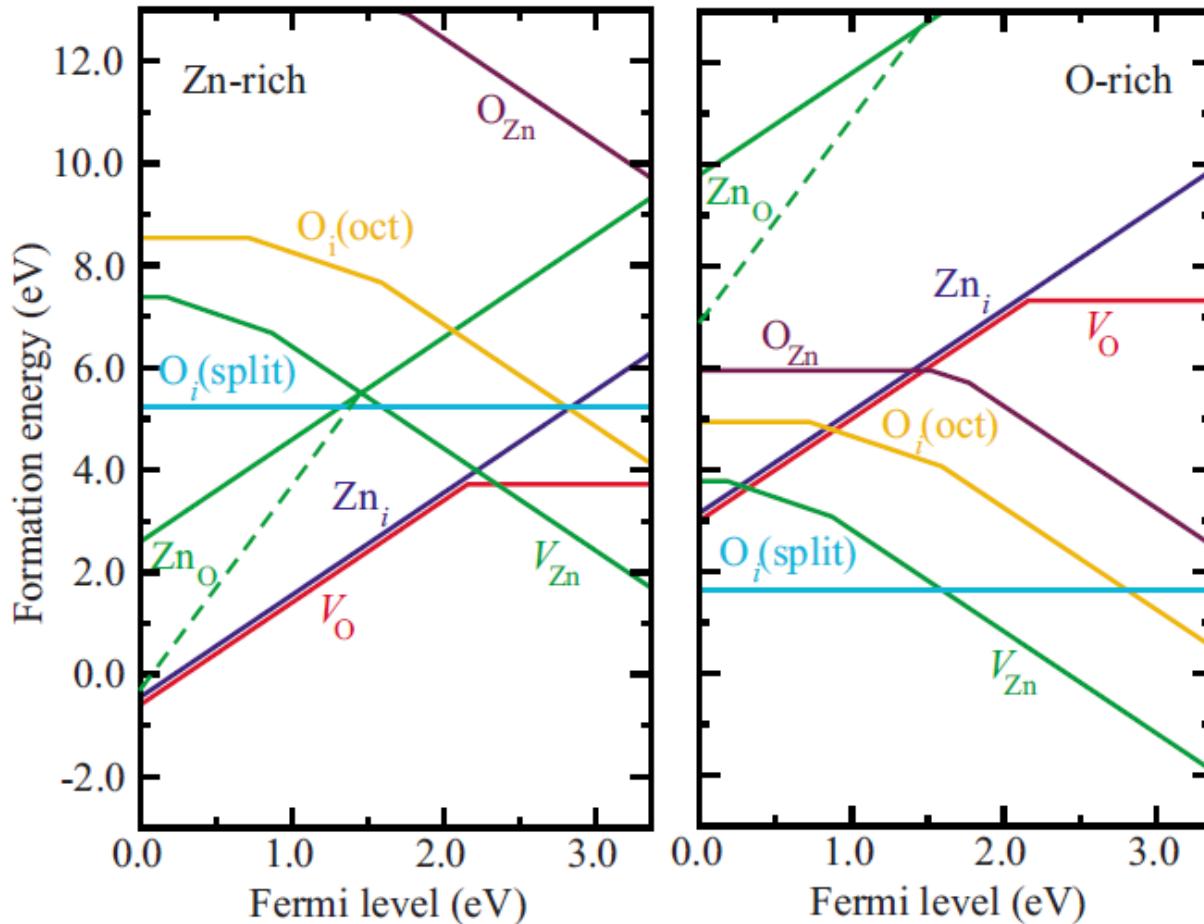
HTG, MaTeck



# Points defects in ZnO

A. Janotti, C.G. Van de Walle, PRB **76**, 165202 (2007)

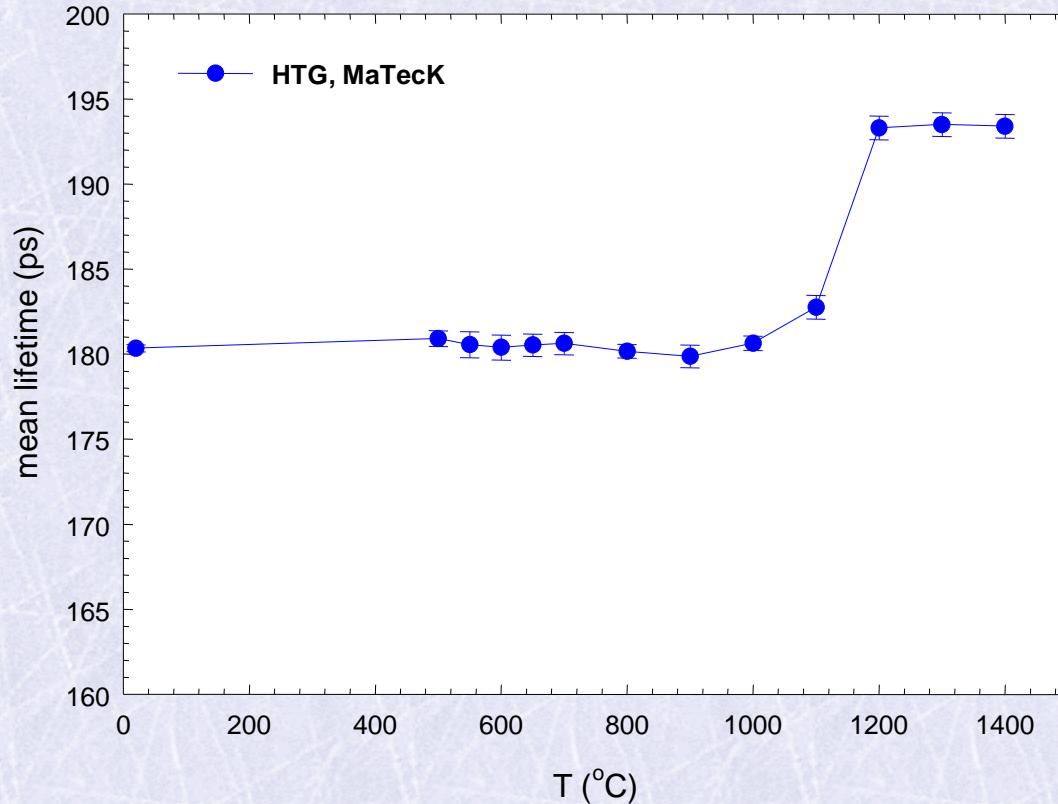
- calculated formation energies of intrinsic points defects in ZnO



## Annealing of ZnO crystals in air

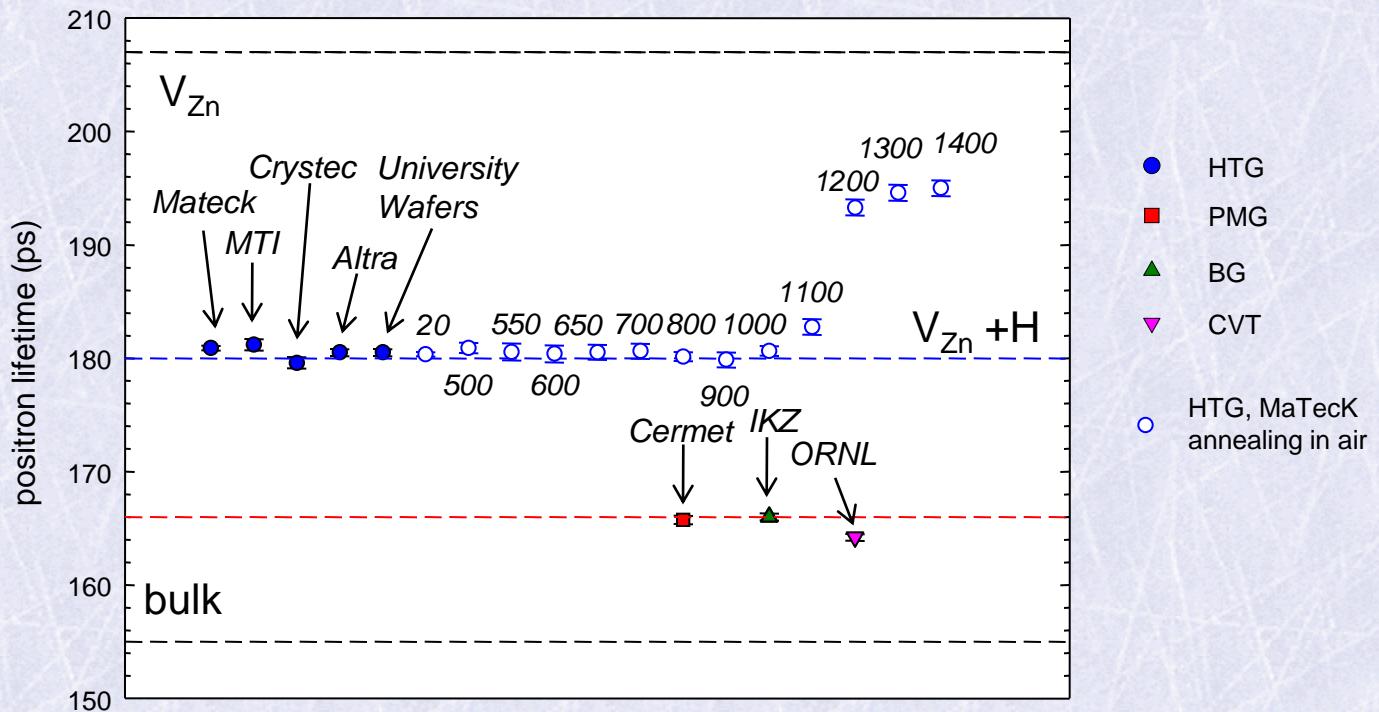
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HTG, MaTeck



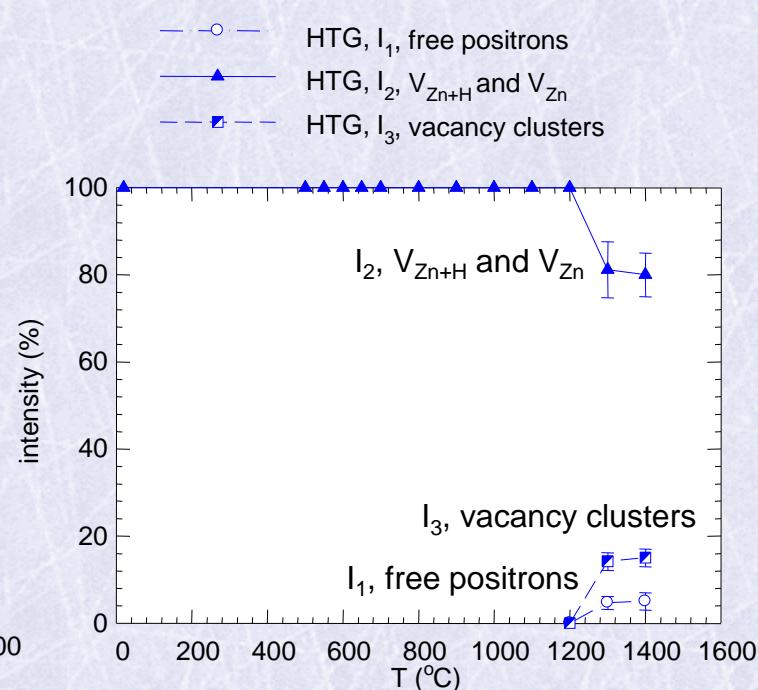
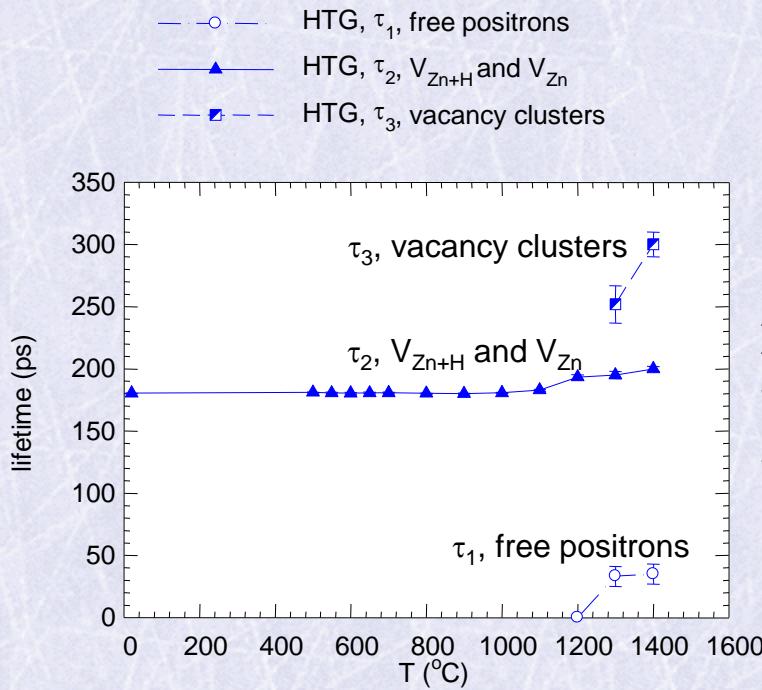
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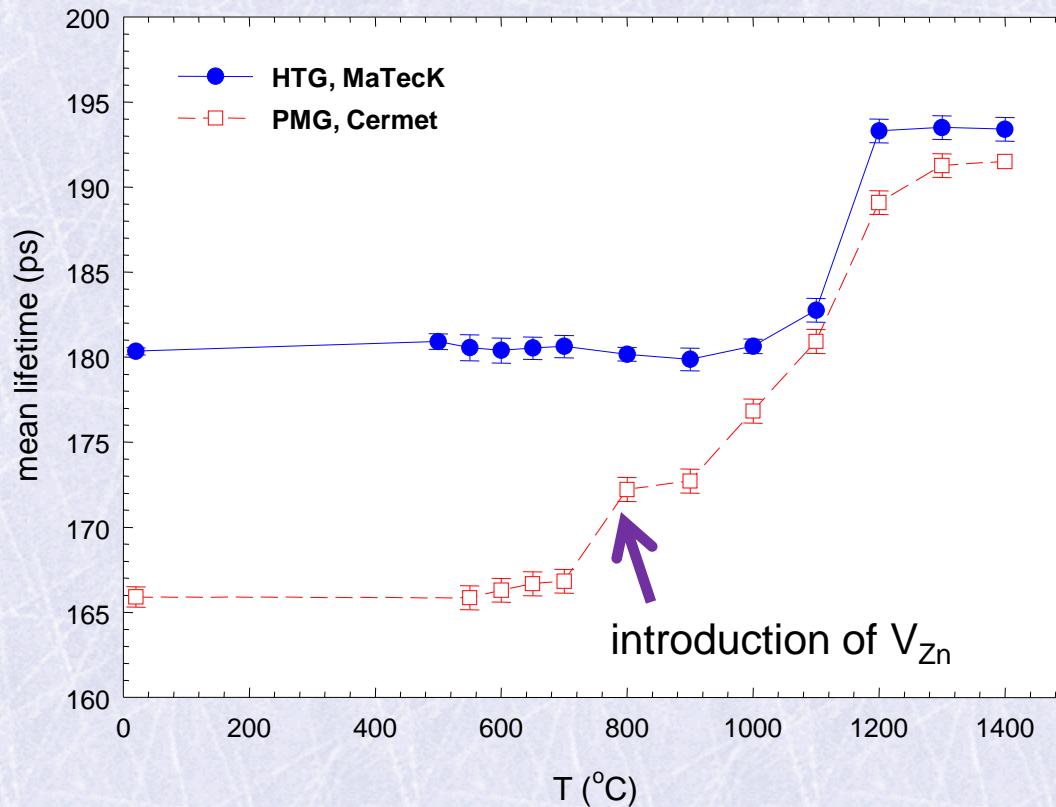
# Annealing of ZnO crystals in air

- HTG ZnO (MaTeck)
- decomposition of positron lifetime spectra
- free positron component appeared at  $T > 1200^\circ\text{C}$  when  $V_{\text{Zn}}$  agglomerate to clusters



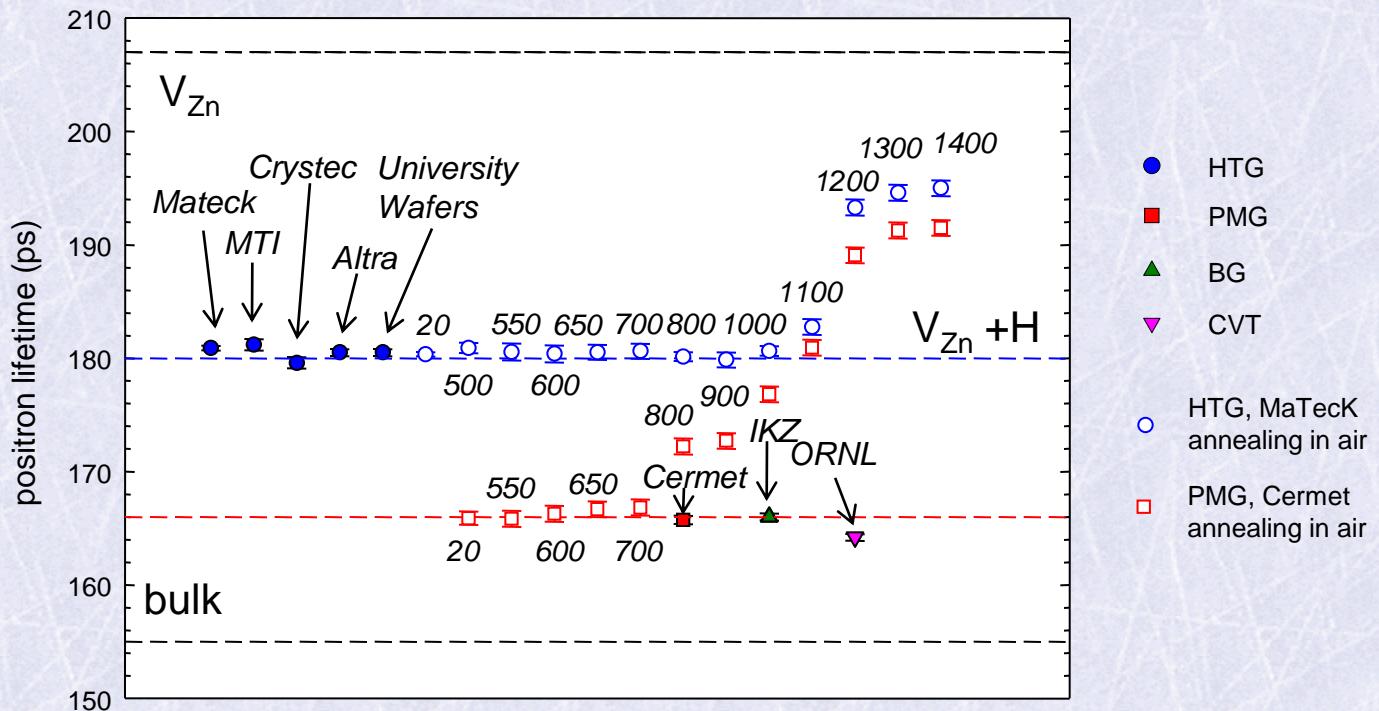
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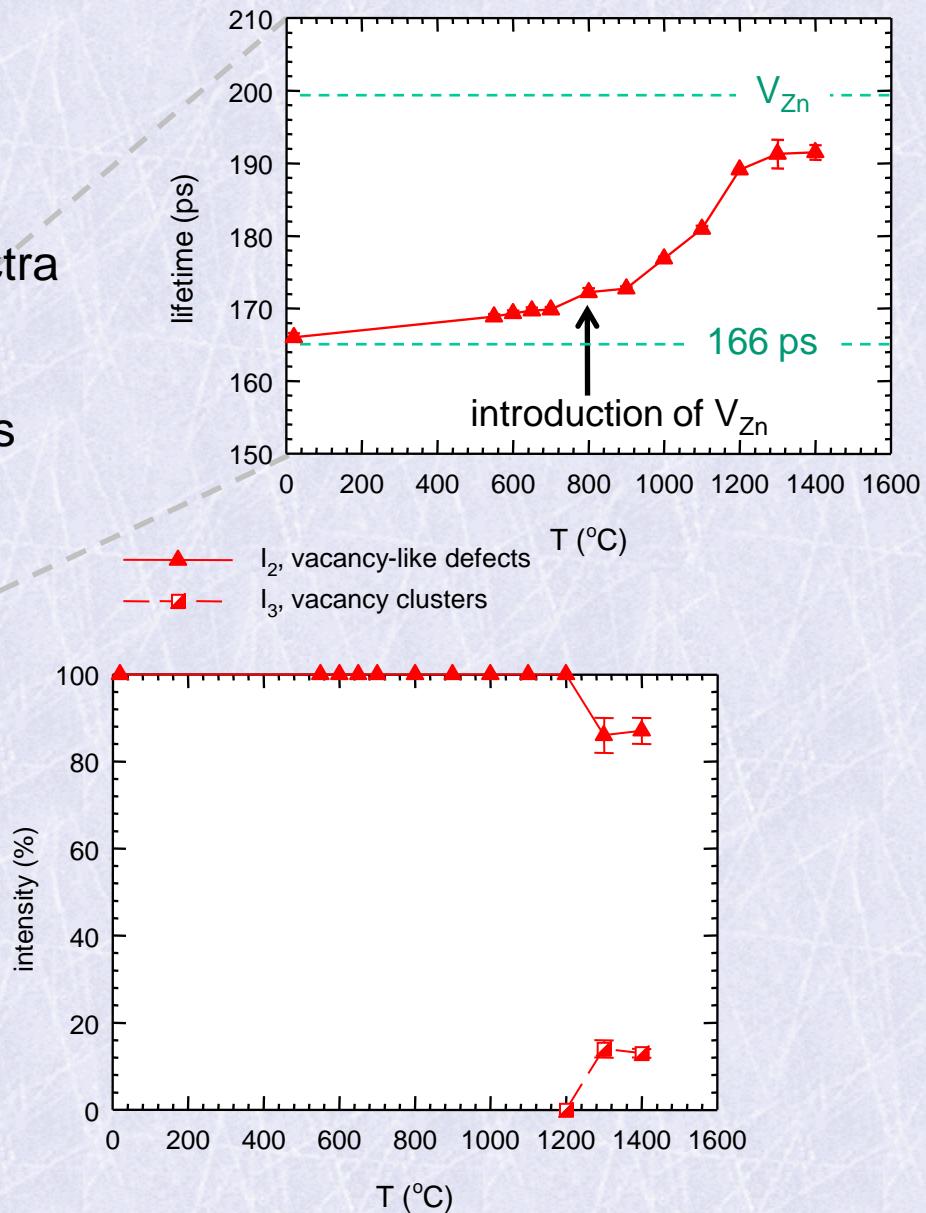
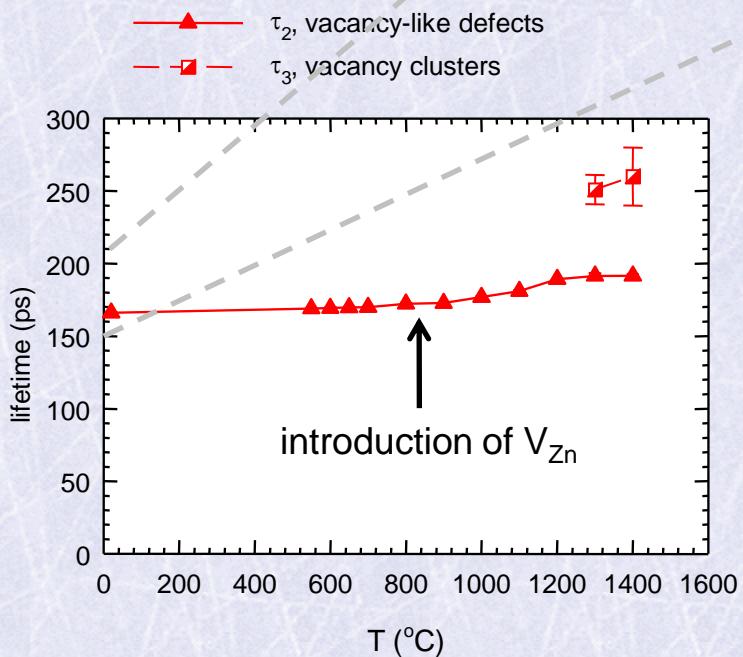
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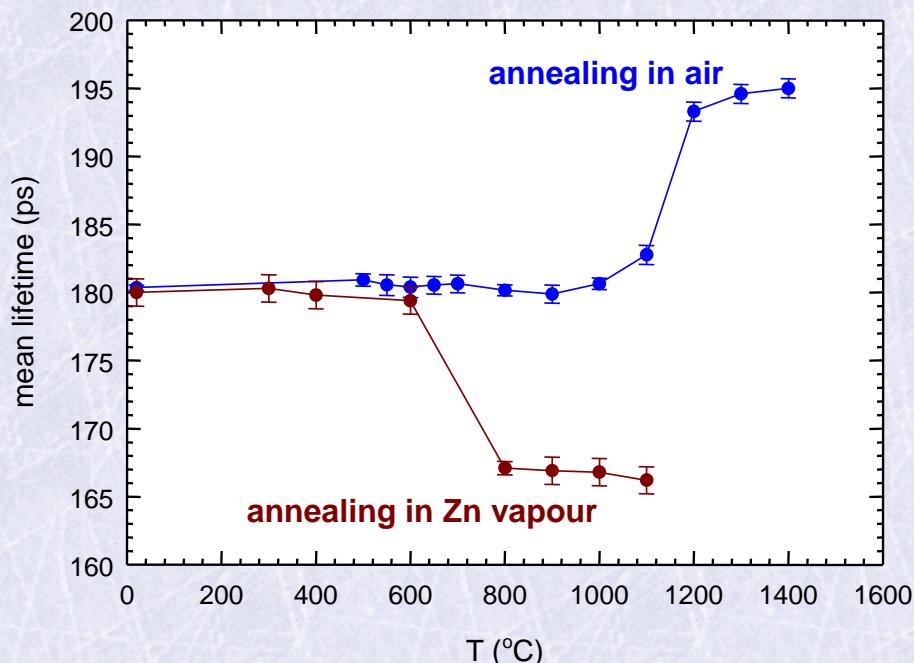
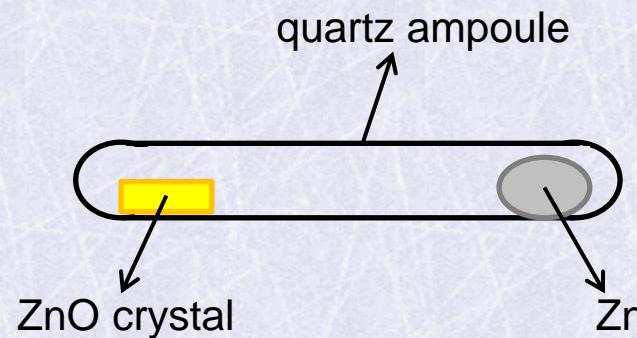
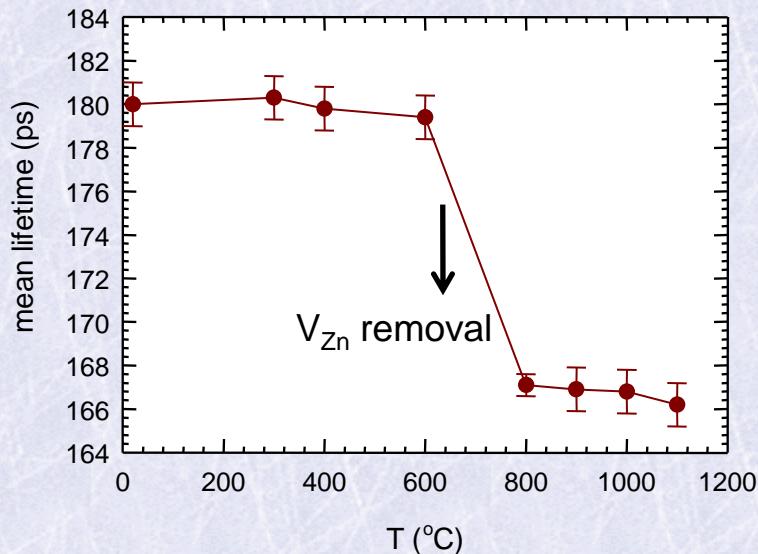
# Annealing of ZnO crystals in air

- PMG ZnO (Cermet)
- decomposition of positron lifetime spectra
- $V_{Zn}$  introduced at  $T > 800^{\circ}\text{C}$
- $T > 1200^{\circ}\text{C}$  agglomeration of vacancies



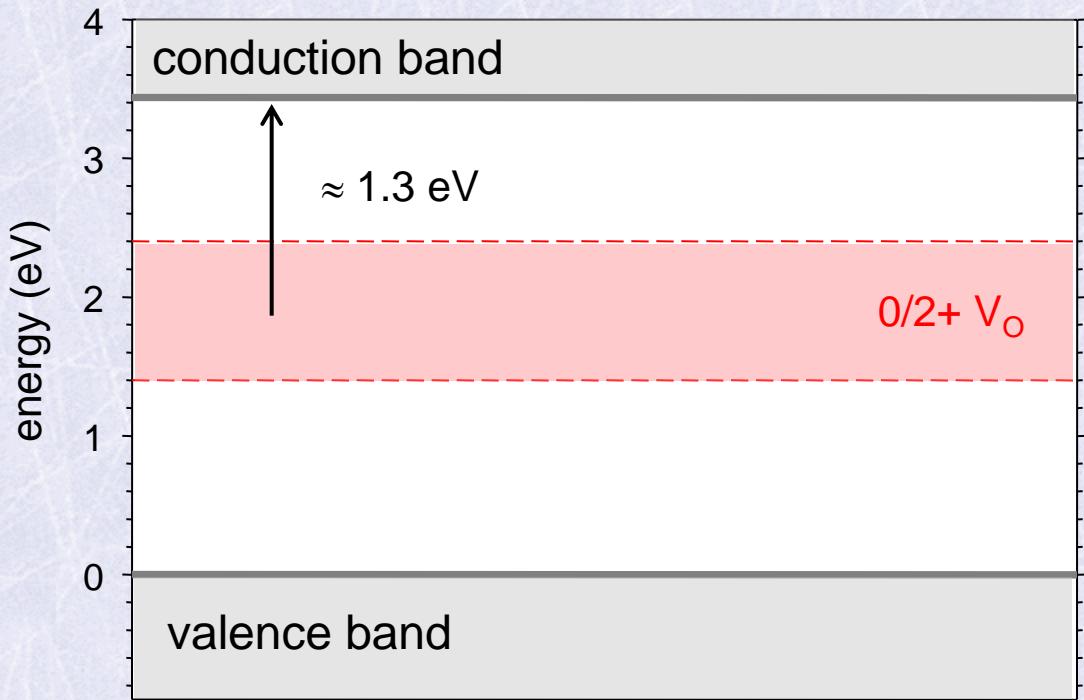
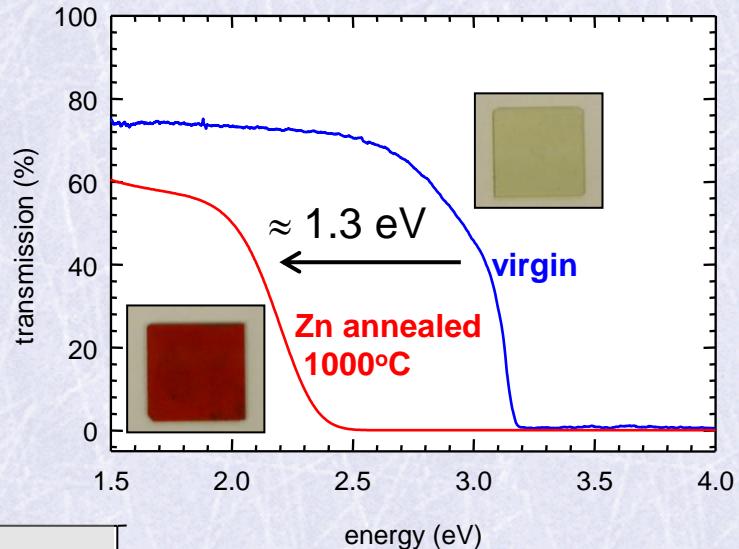
# Annealing of ZnO crystals in Zn vapour

- HTG ZnO (MaTeCK)
- annealing in evacuated ampoule with metallic Zn at various temperatures for 12 h



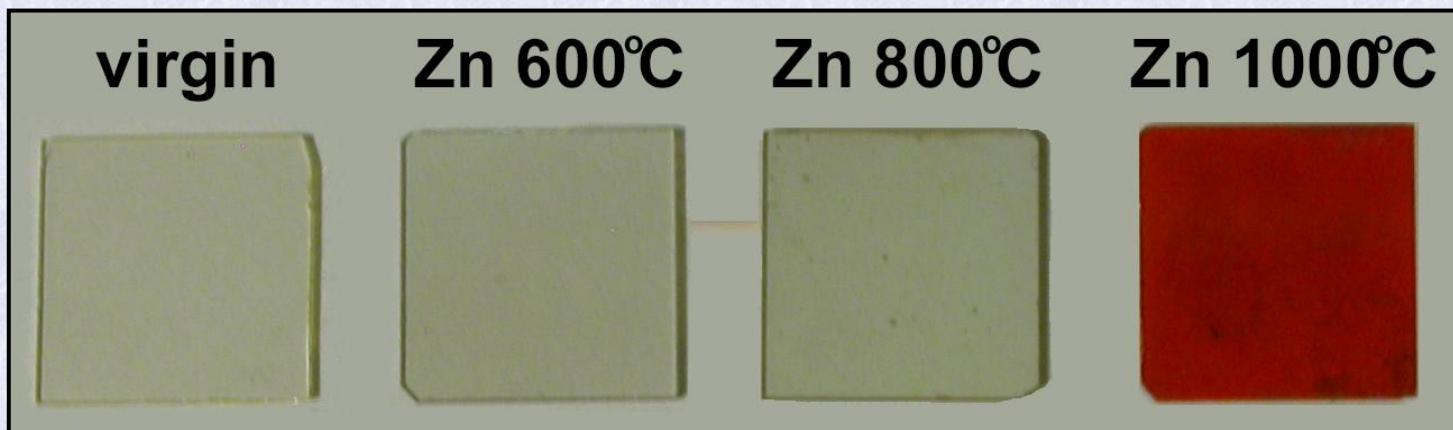
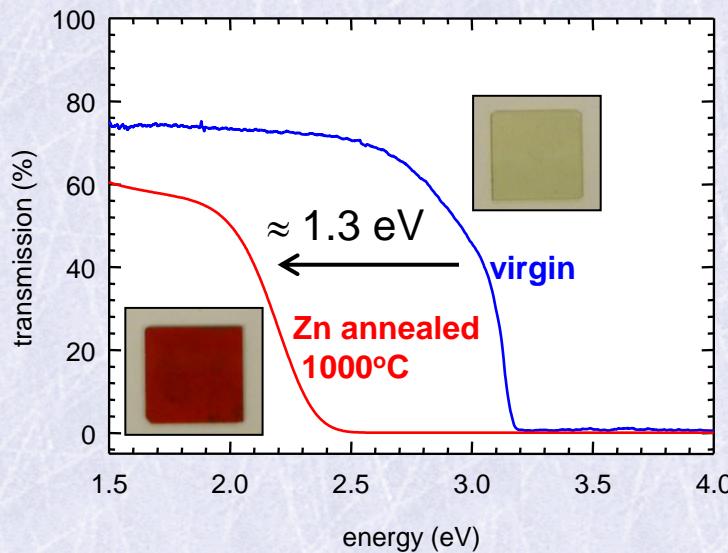
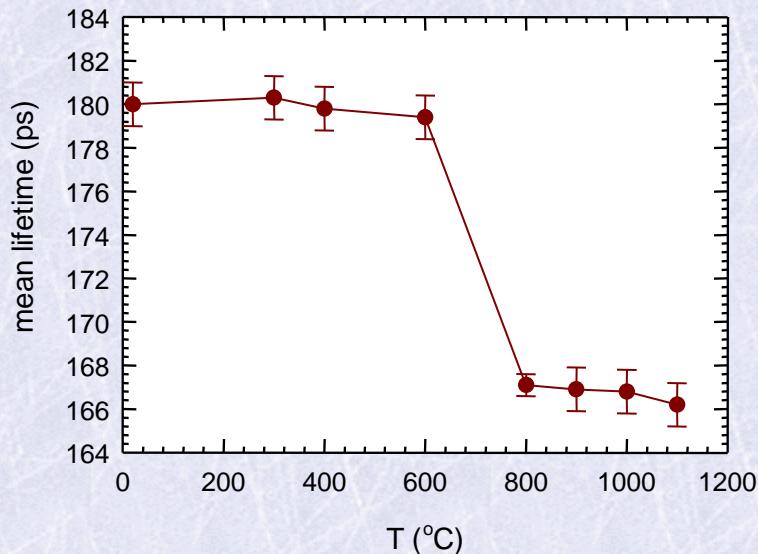
# Points defects in ZnO

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- $V_O$  is deep donor



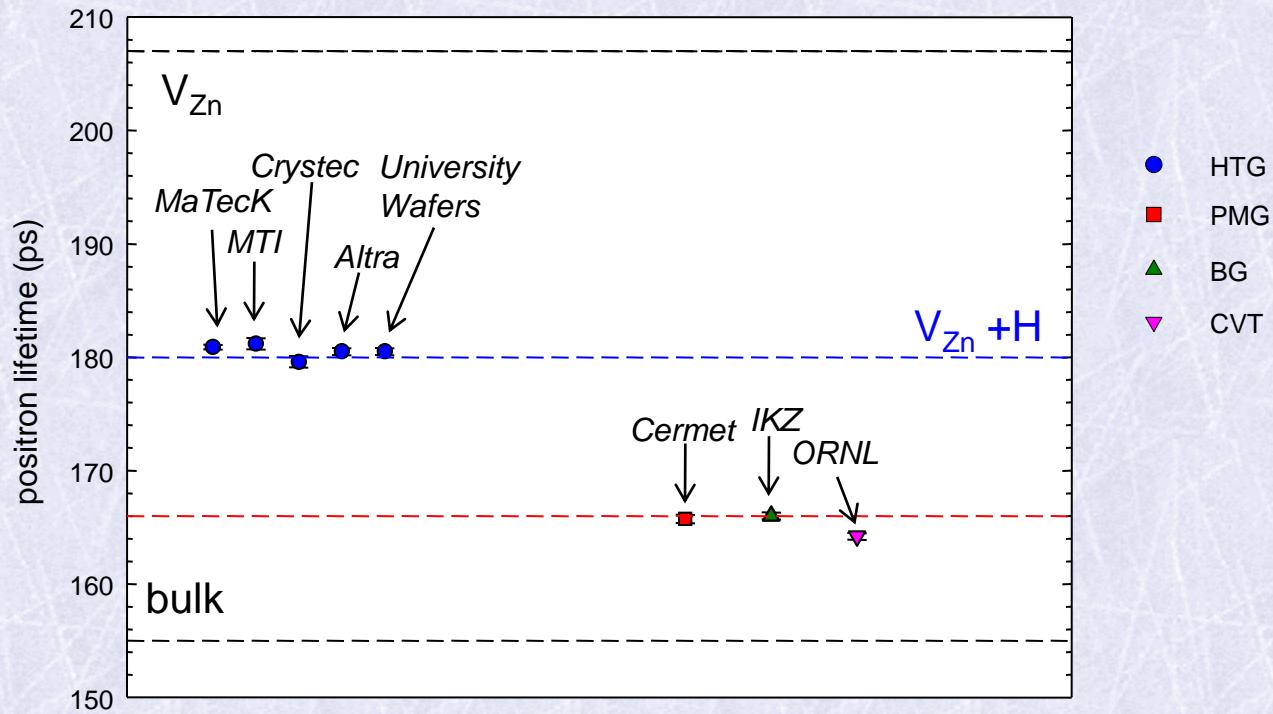
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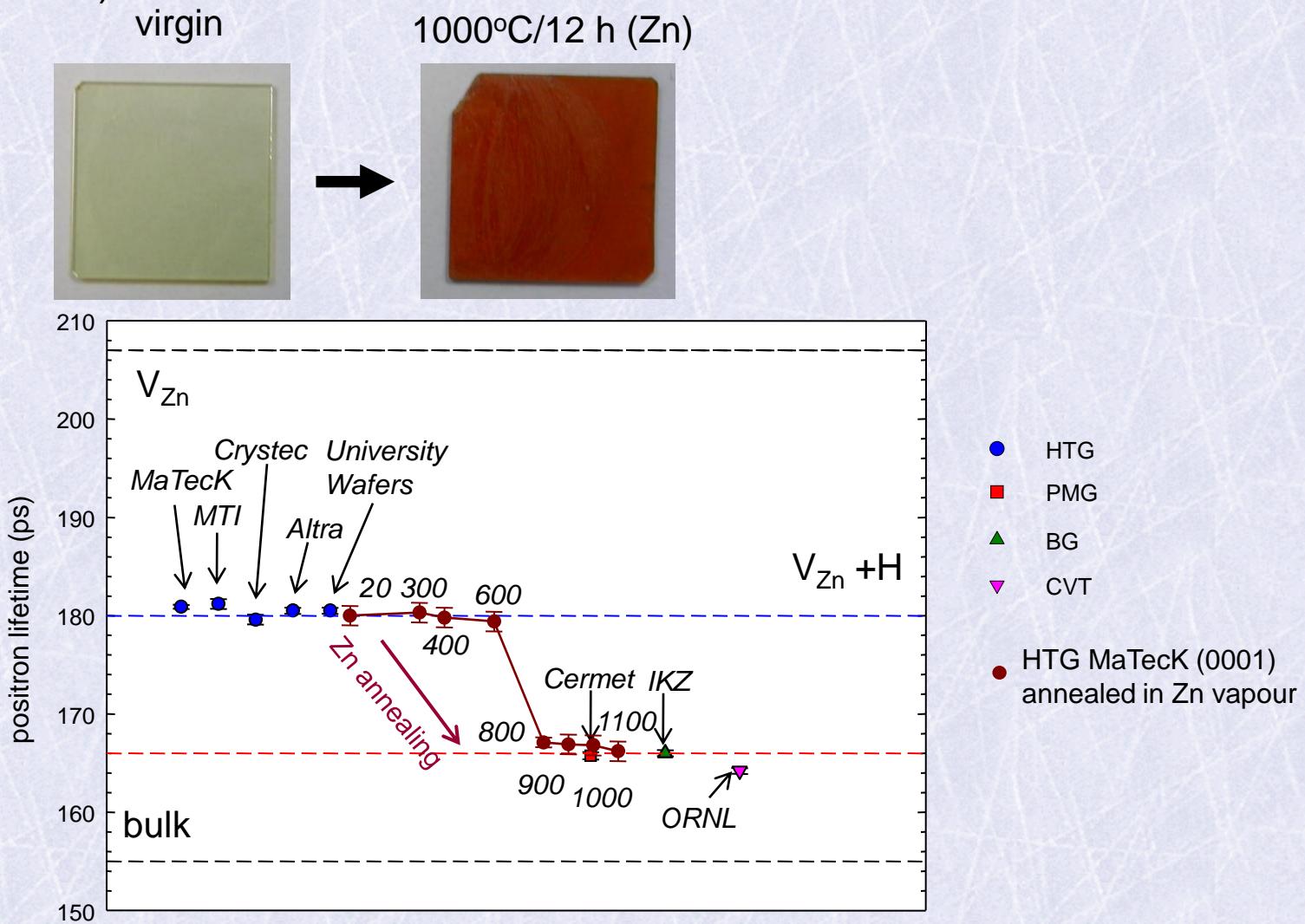
# Annealing of ZnO crystals in Zn vapour

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# Annealing of ZnO crystals in Zn vapour

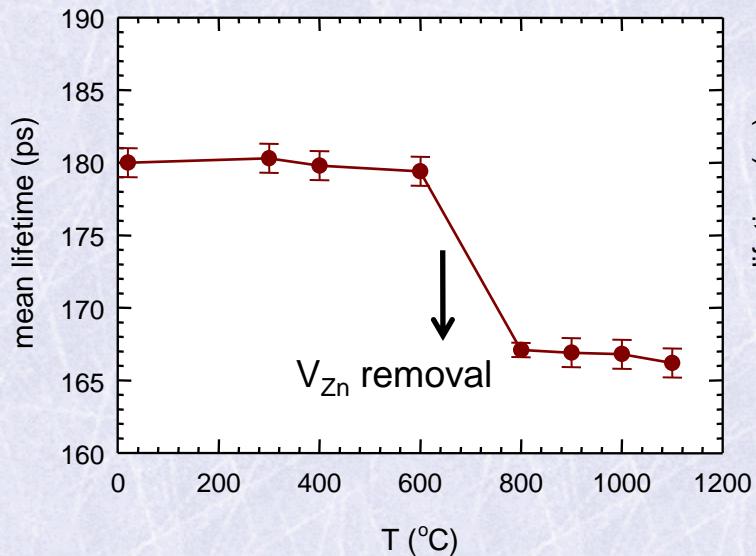
- HTG ZnO (MaTeCK)



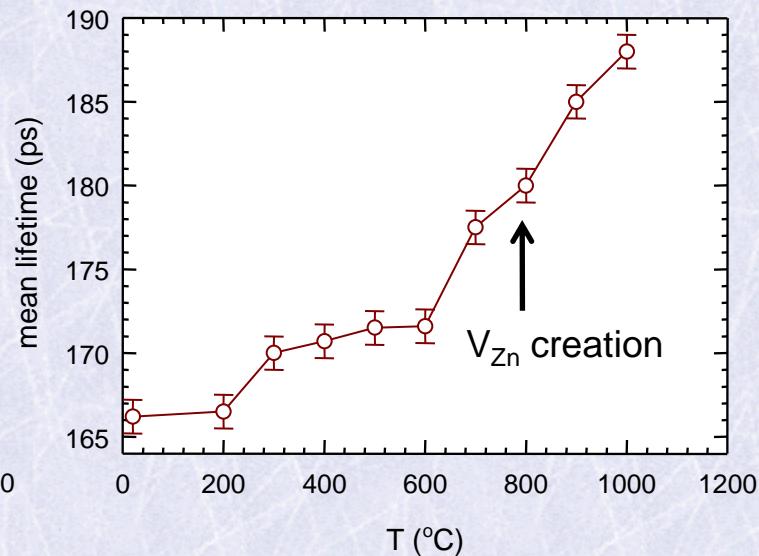
## Annealing of ZnO crystals in Zn vapour

- HTG ZnO (MaTeK)
- annealing in evacuated ampoule with metallic Zn at various temperatures for 12 h
- post-annealing in air at various temperatures for 12 h

Zn-annealing

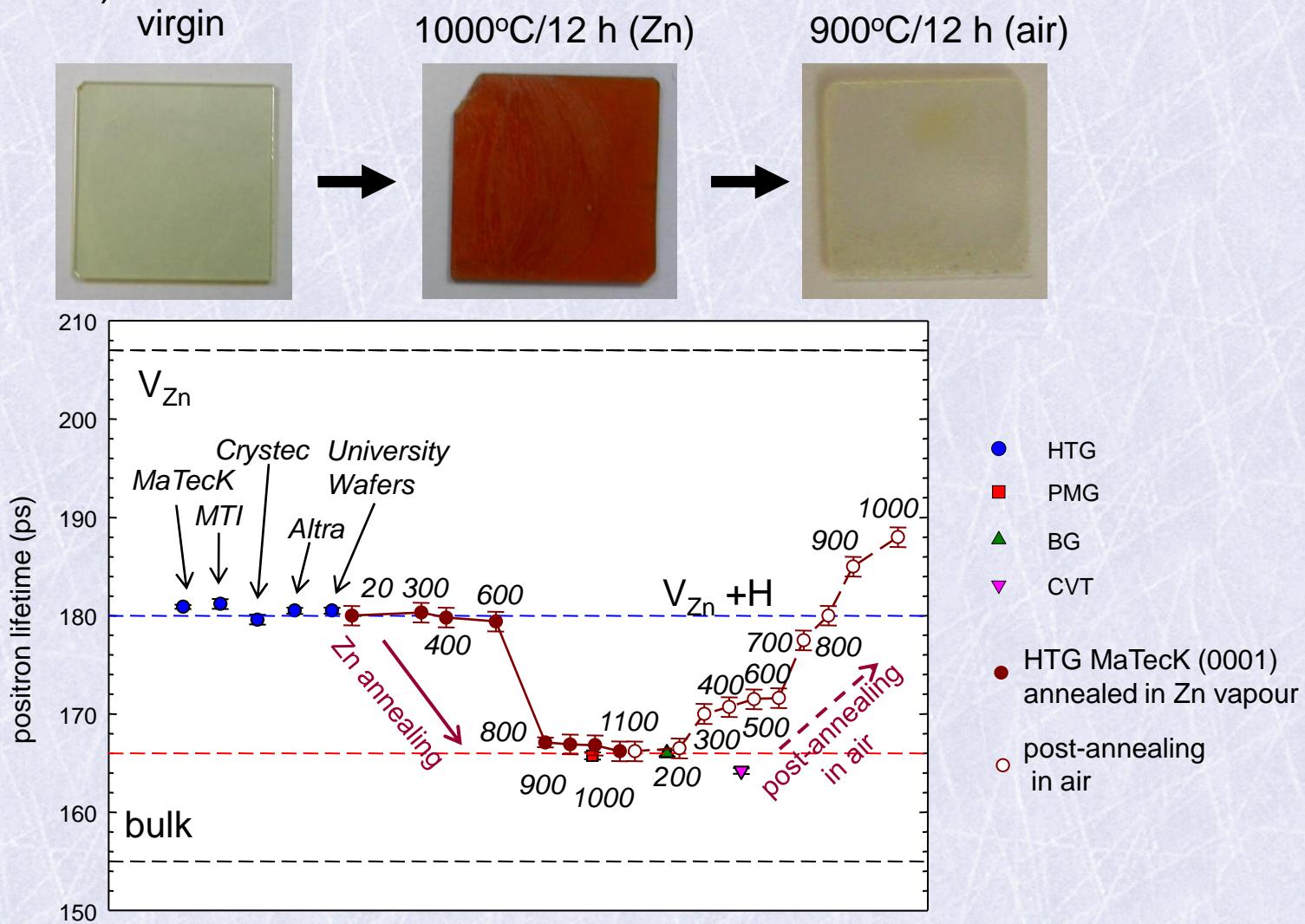


post-annealing in air

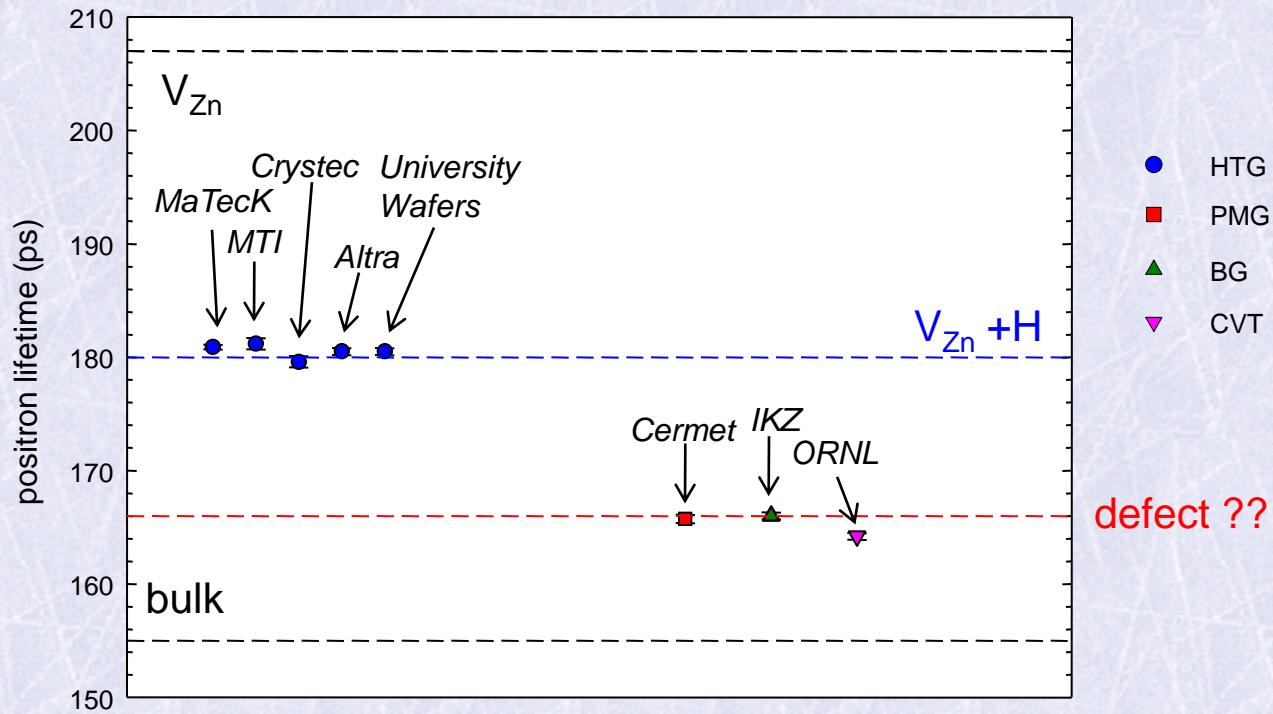


# Annealing of ZnO crystals in Zn vapour

- HTG ZnO (MaTeCK)



# ZnO crystals grown by various methods

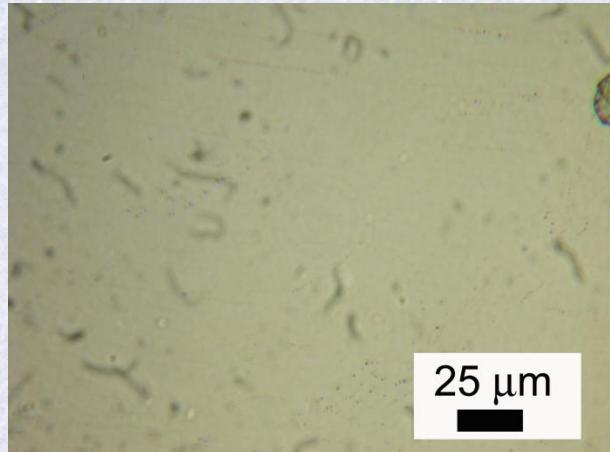


# Dislocation density in ZnO crystal

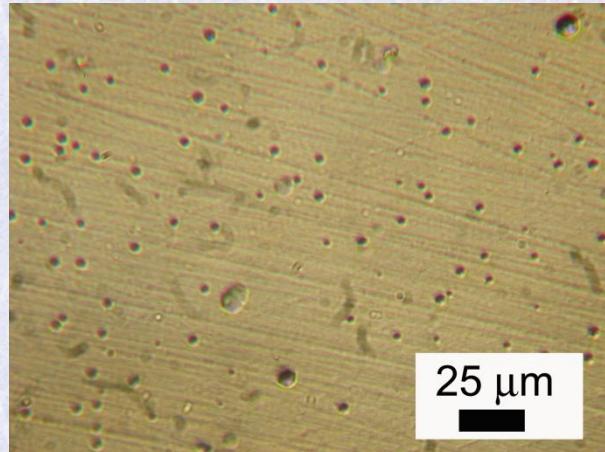
- etch pitting ( $\text{H}_3\text{PO}_4$  + glycerine 1:2)

- PMG (Cermet)

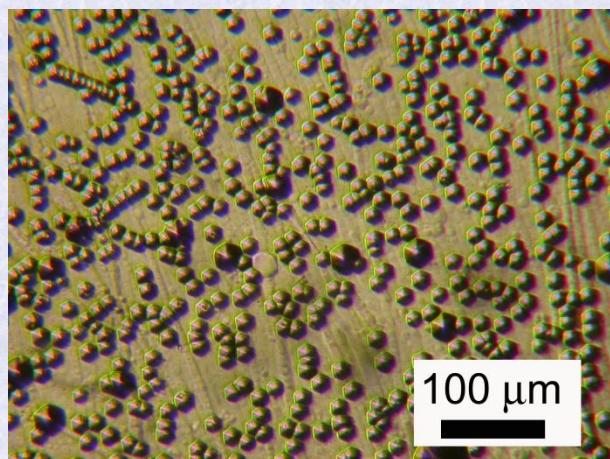
virgin



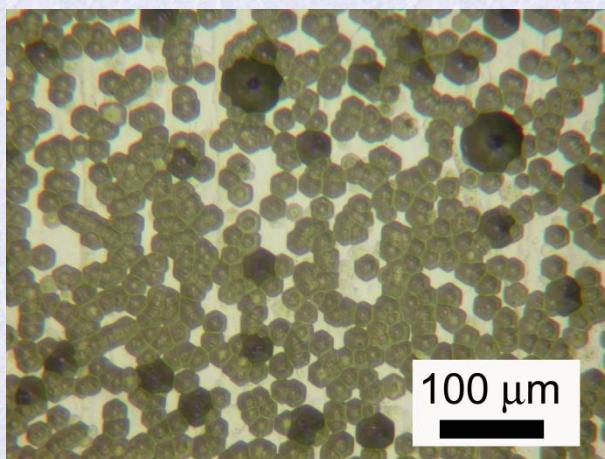
15 min etching



75 min etching



165 min etching

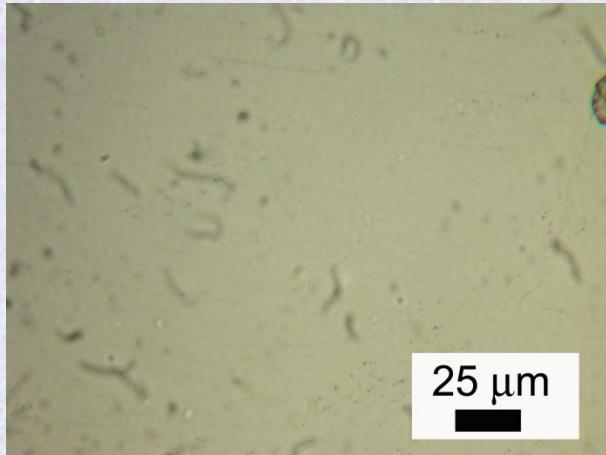


# Dislocation density in ZnO crystal

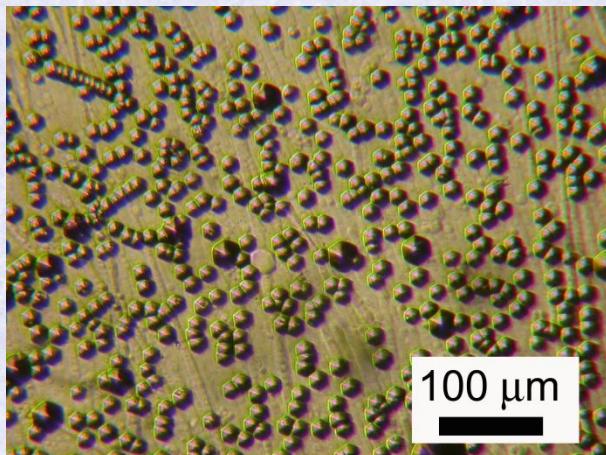
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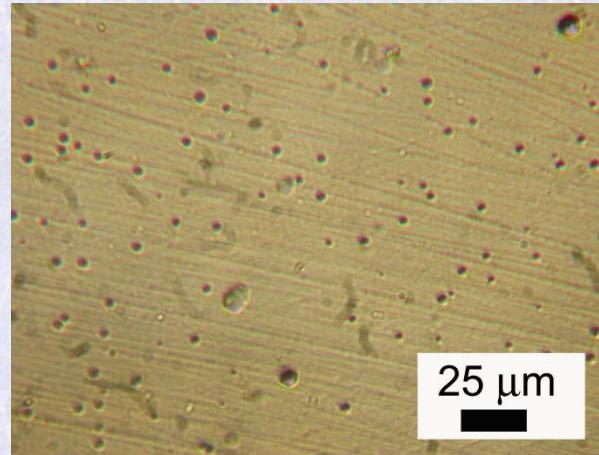
virgin



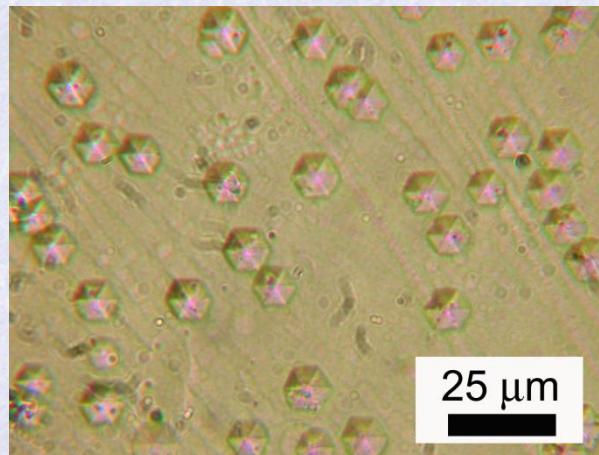
75 min etching



15 min etching



detail of etch pits

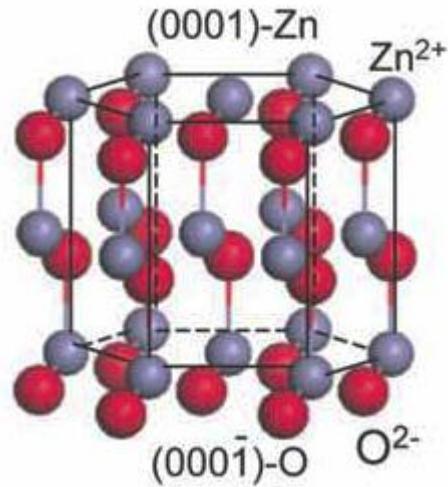
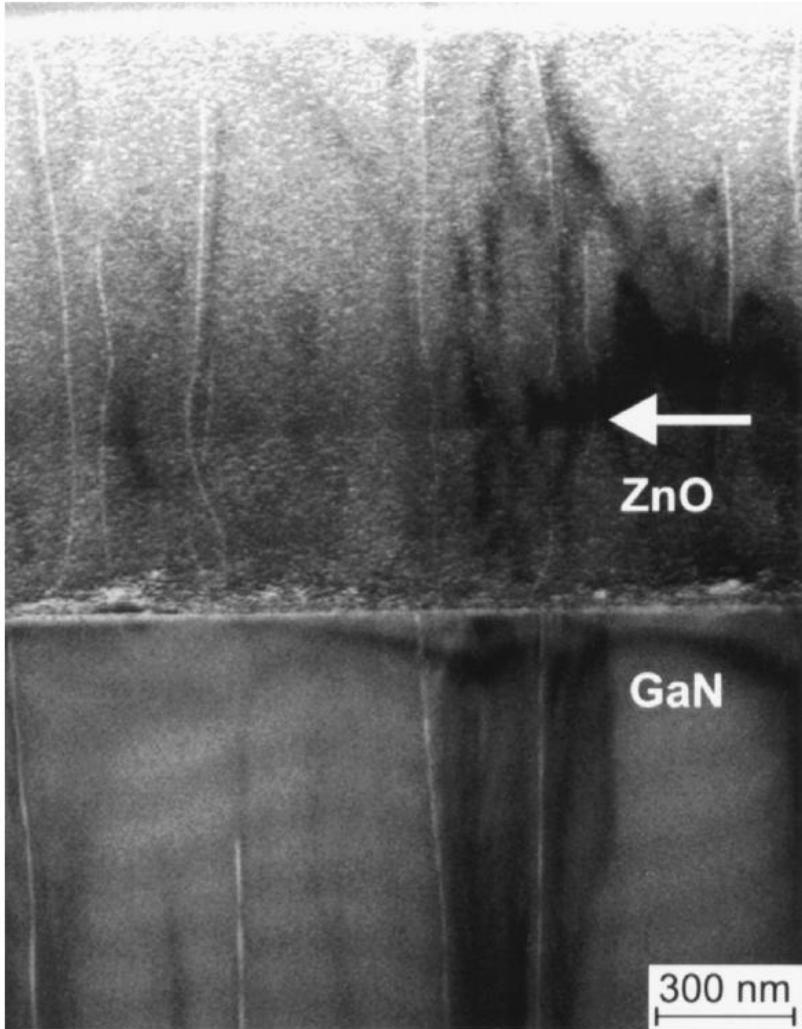


- dislocation density  
 $\rho_D \approx 3 \times 10^{10} \text{ m}^{-2}$

- too low to explain saturated trapping of positrons

## Stacking faults in ZnO

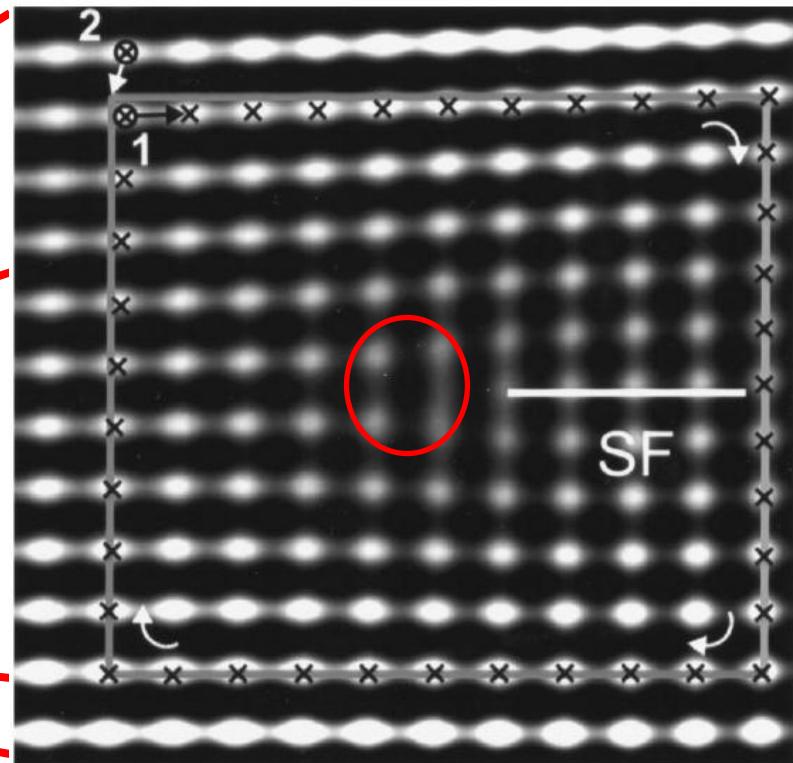
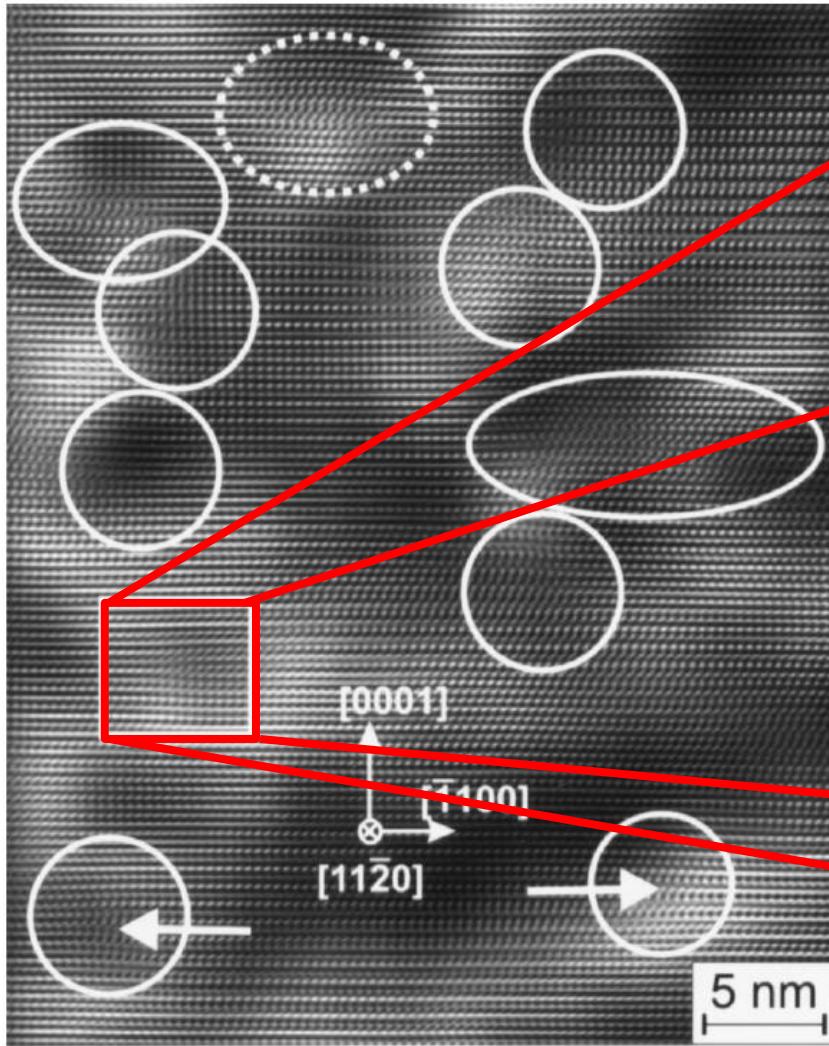
- epitaxial ZnO film grown by metalorganic vapour phase epitaxy (MOVPE)
- TEM image in cross-section of the film



D. Gerthesen et al. *APL* **81**, 3972 (2002)

# Stacking faults in ZnO

- epitaxial ZnO film grown by metalorganic vapour phase epitaxy (MOVPE)
- HRTEM image in cross-section of the film

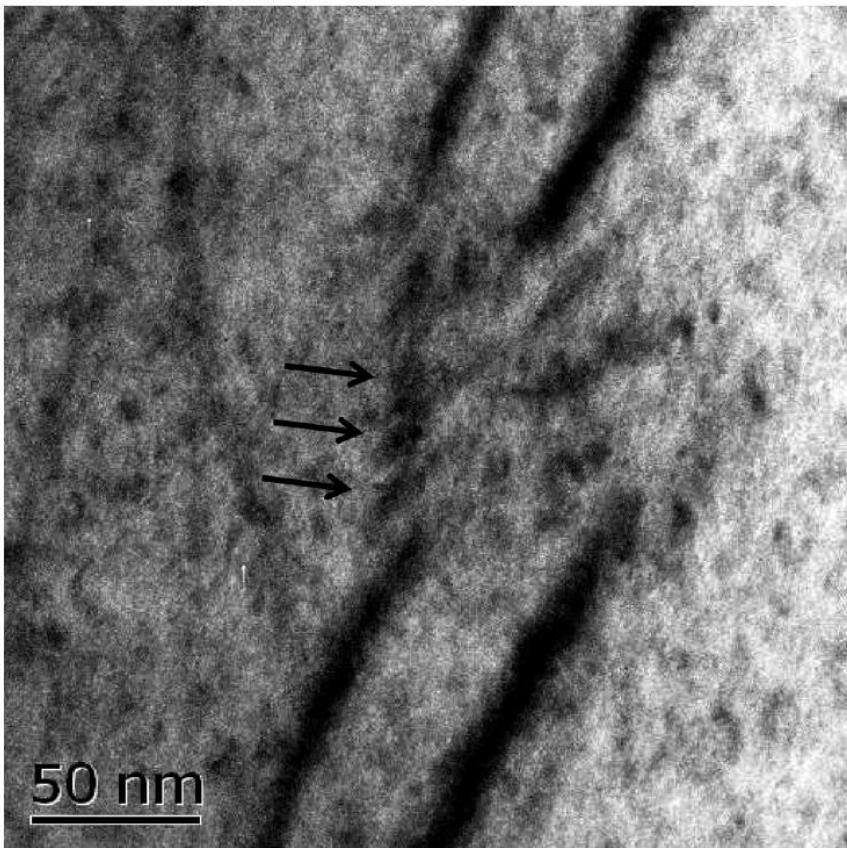


D. Gerthesen et al. APL 81, 3972 (2002)

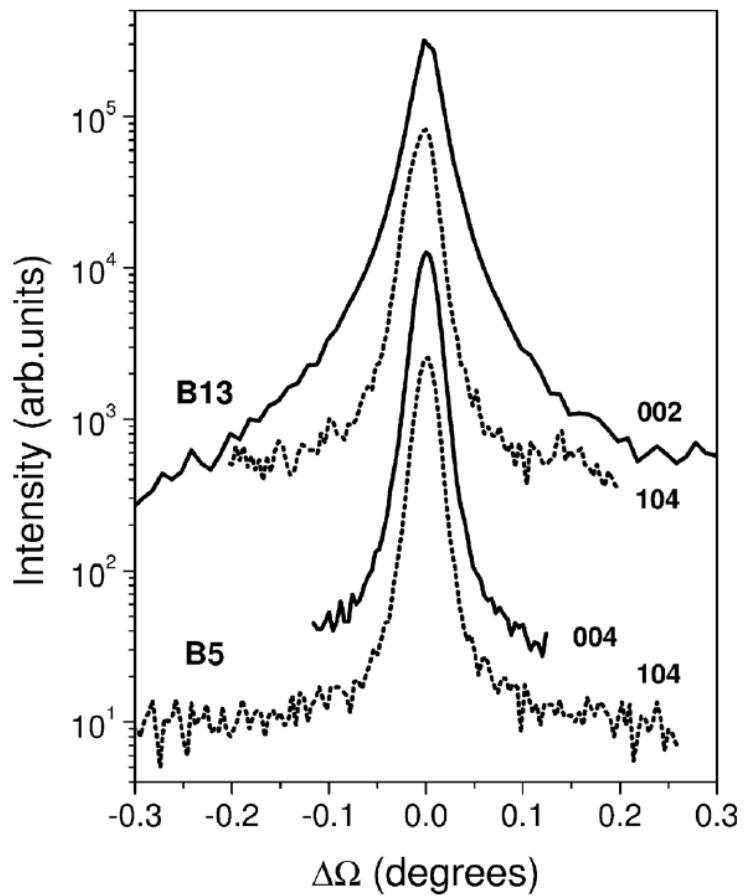
# Stacking faults in ZnO

- lifetime of 166 ps: positron trapping at misfit defects associated with stacking faults
- BG (IKZ), virgin

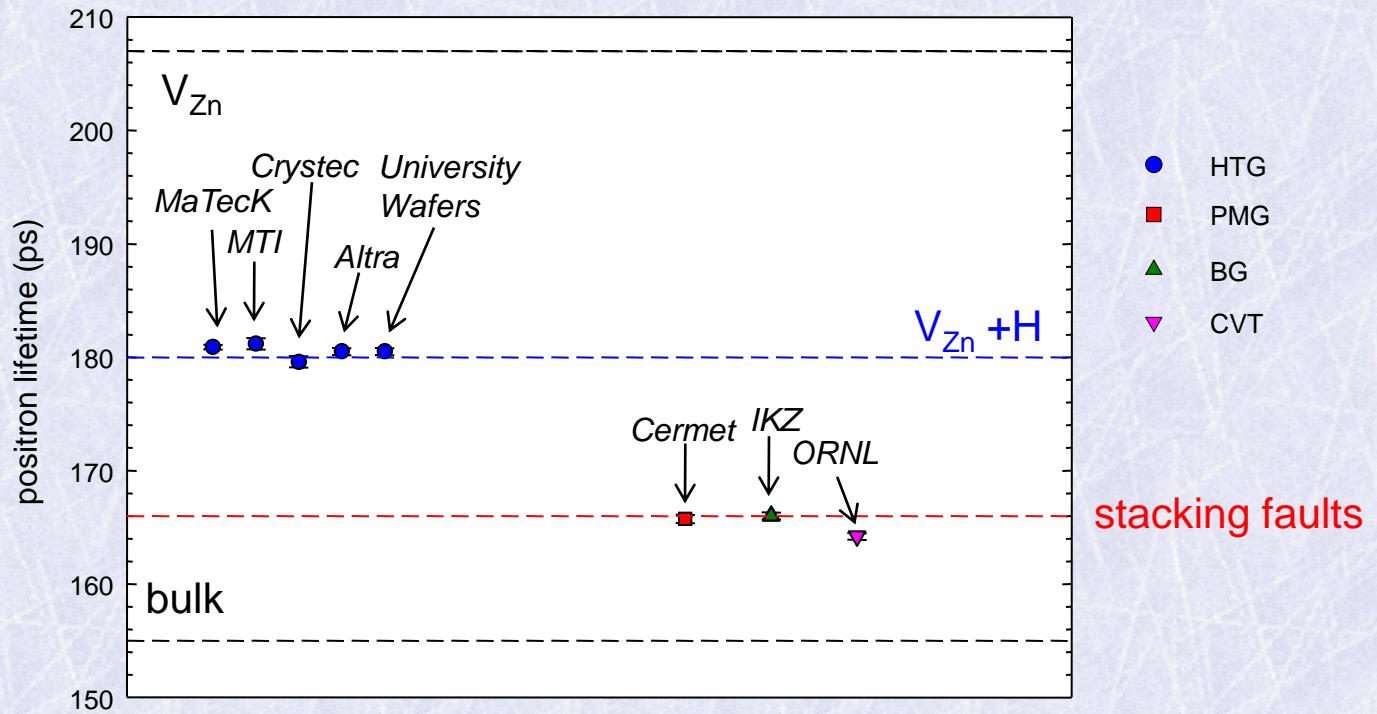
bright field TEM micrograph



X-ray diffraction profiles

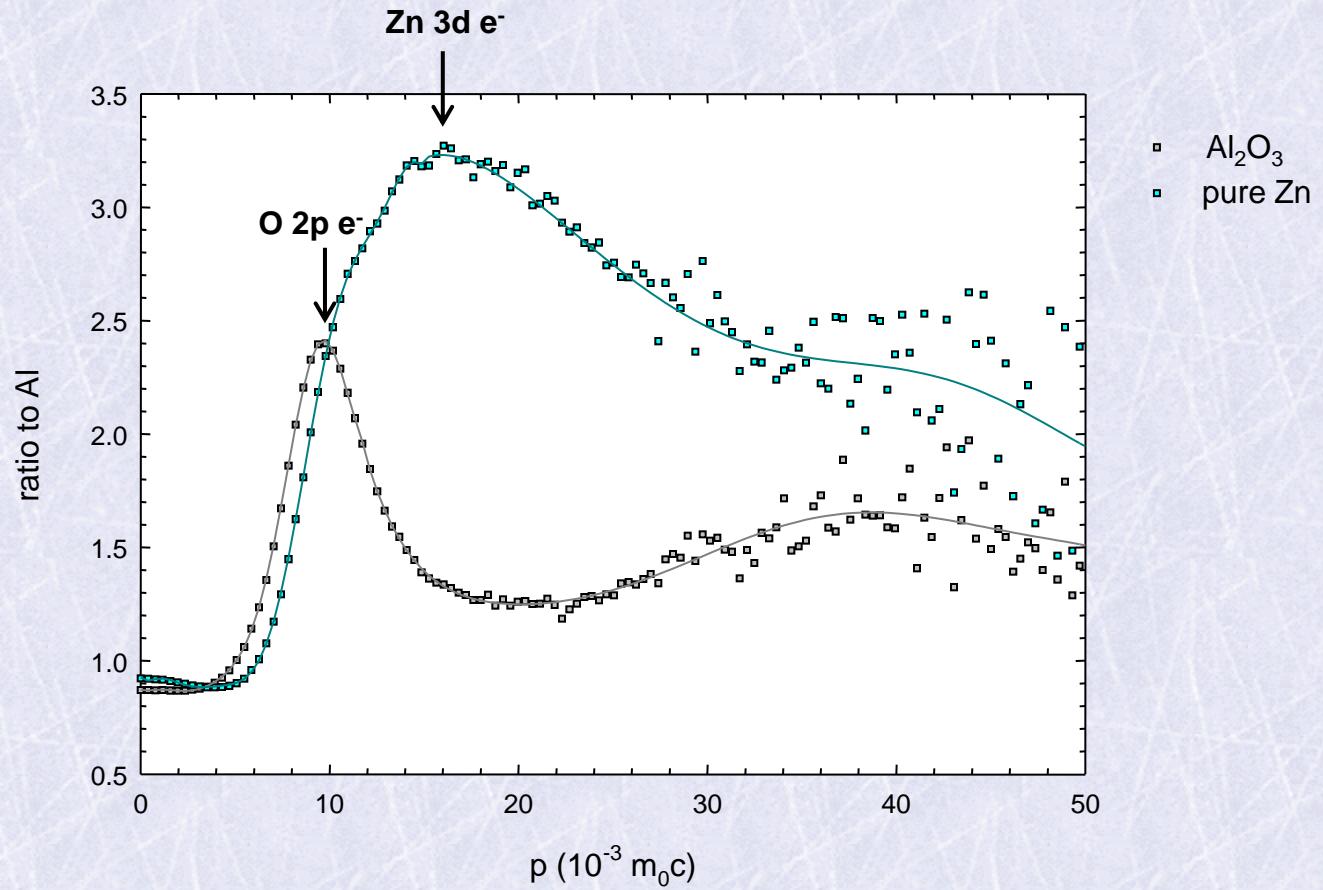


# ZnO crystals grown by various methods



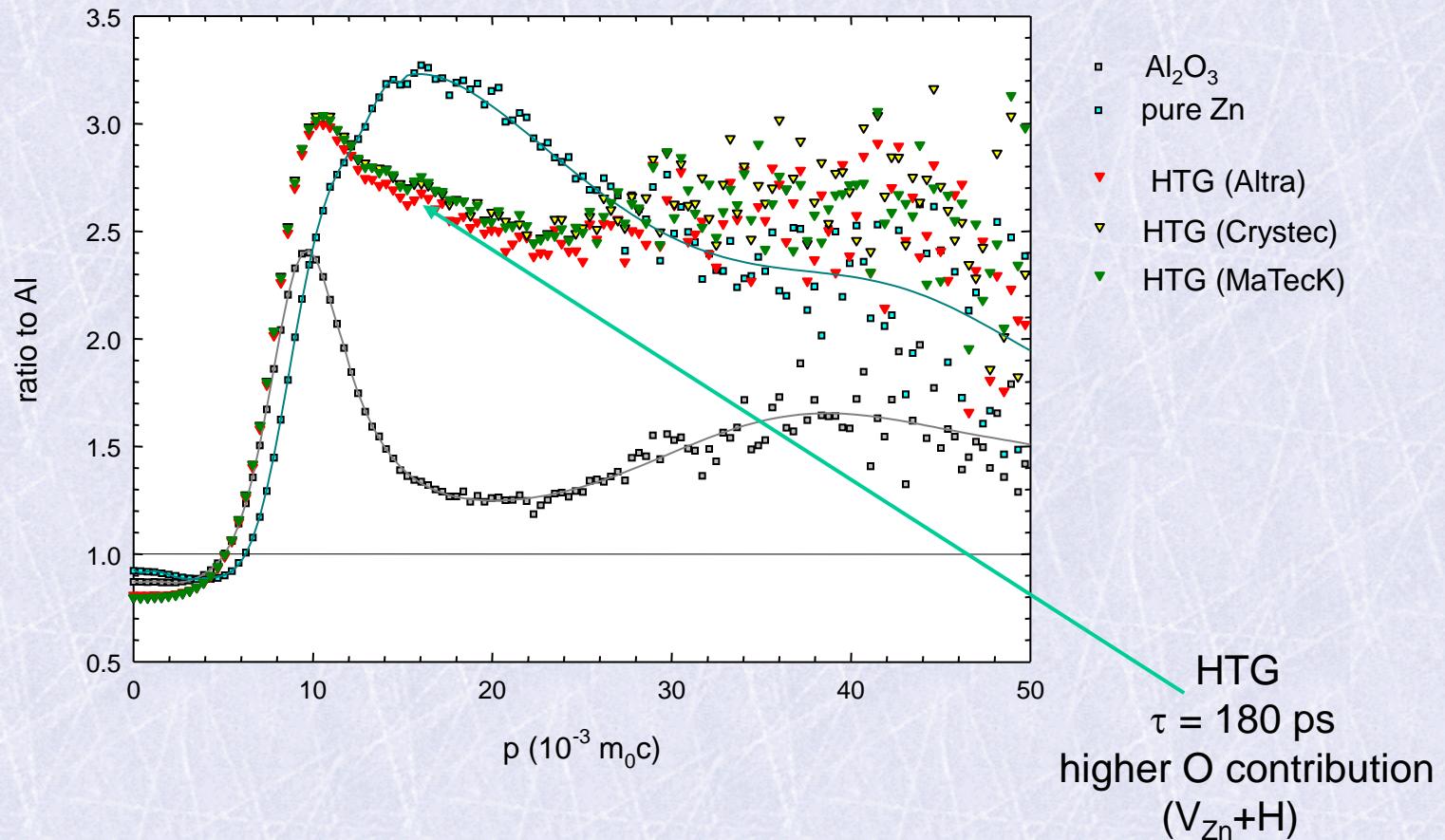
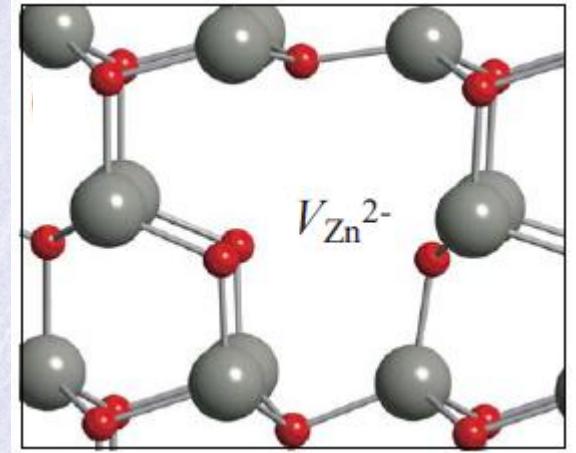
## CDB results

- reference samples (pure Zn and Al<sub>2</sub>O<sub>3</sub>)



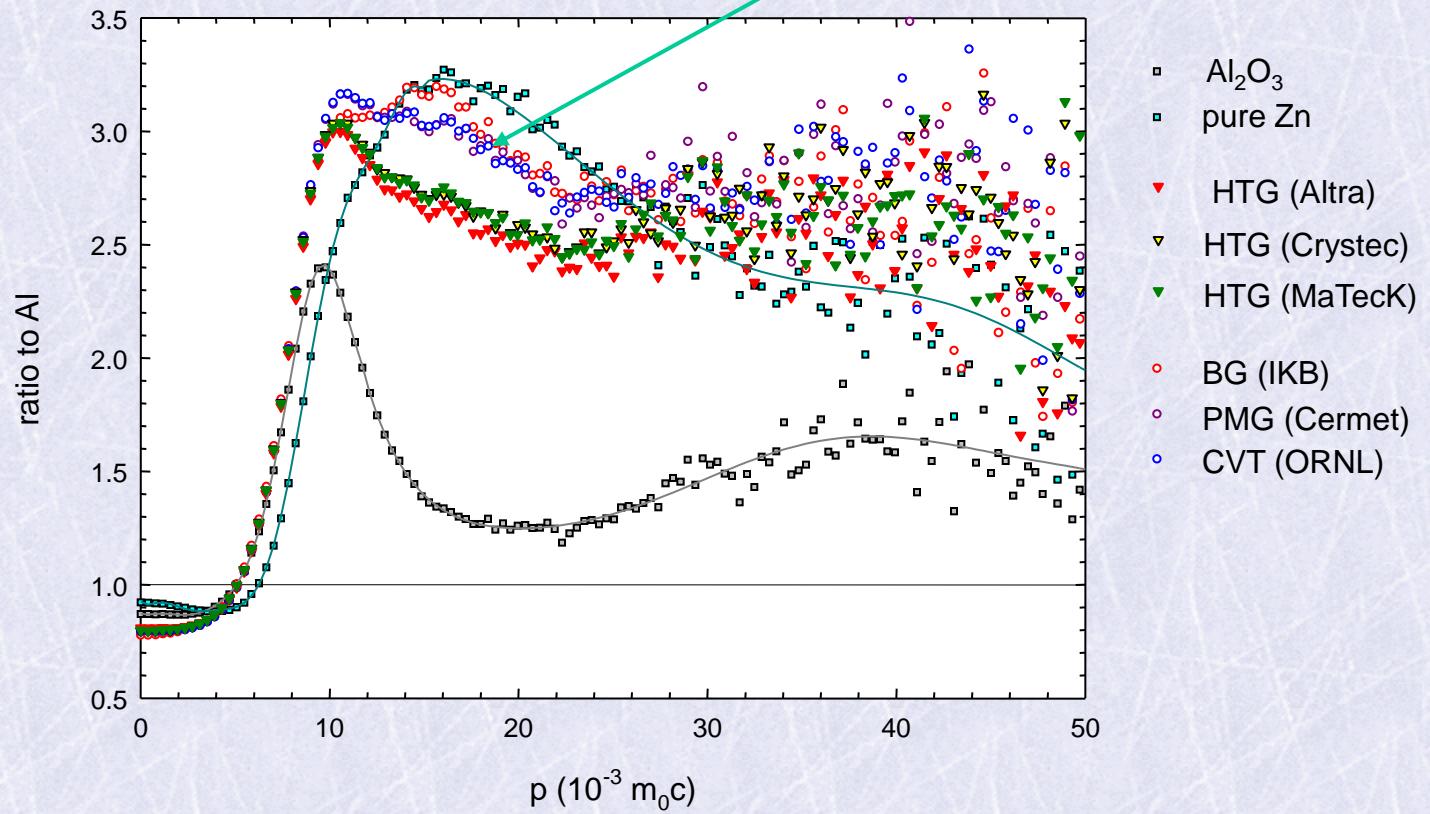
## CDB results

- virgin ZnO crystals grown by various methods
- dominating O contribution in HTG crystals  
is consistent with  $e^+$  trapping in  $V_{Zn} + H$



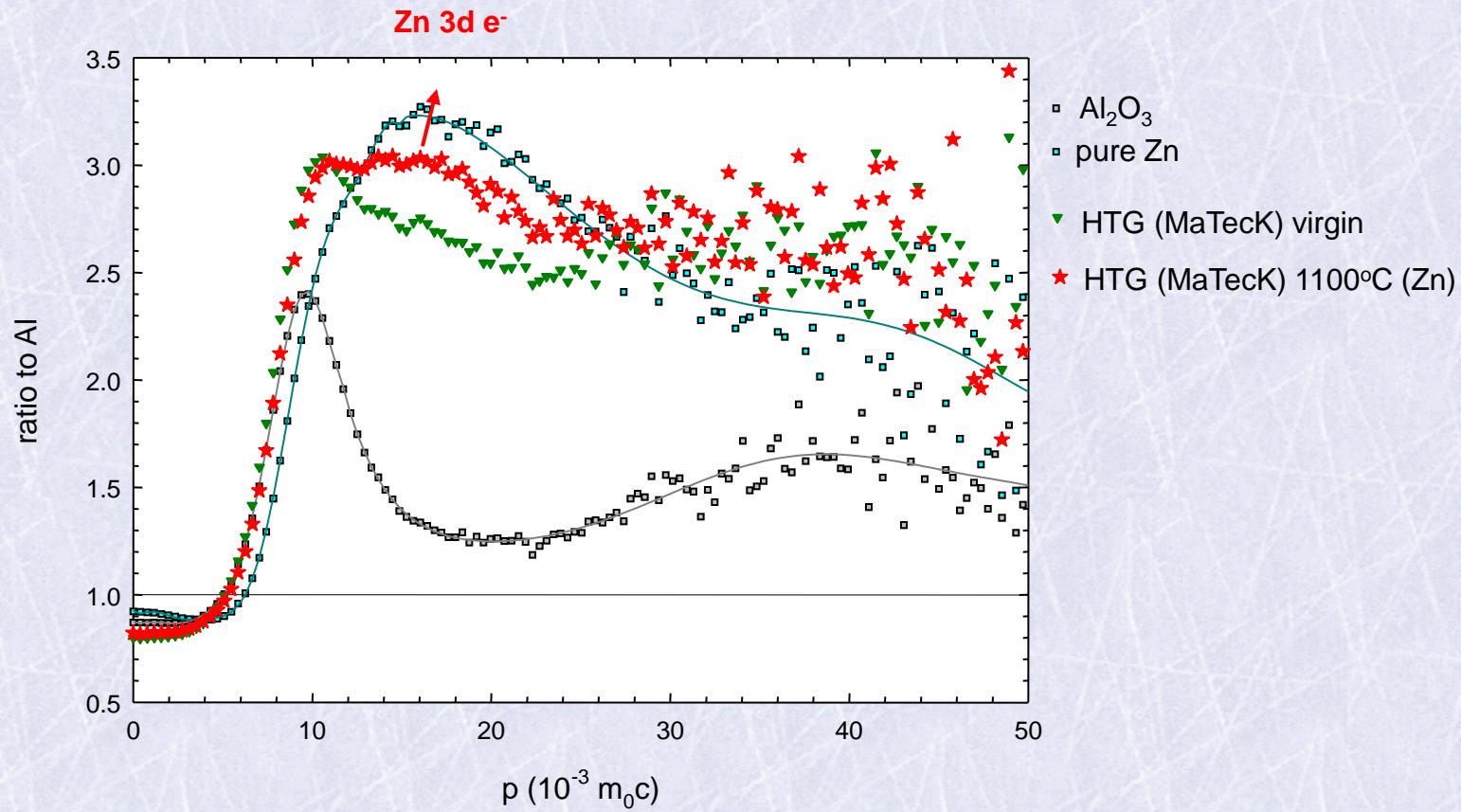
## CDB results

- virgin ZnO crystals grown by various methods
  - dominating O contribution in HTG crystals  
is consistent with  $e^+$  trapping in  $V_{Zn} + H$
  - enhanced Zn contribution in PMG, BG and CVT crystals  
is consistent with  $e^+$  trapping in stacking faults
- PMG, BG, CVT  
 $\tau = 166$  ps  
higher Zn contribution  
(stacking faults)



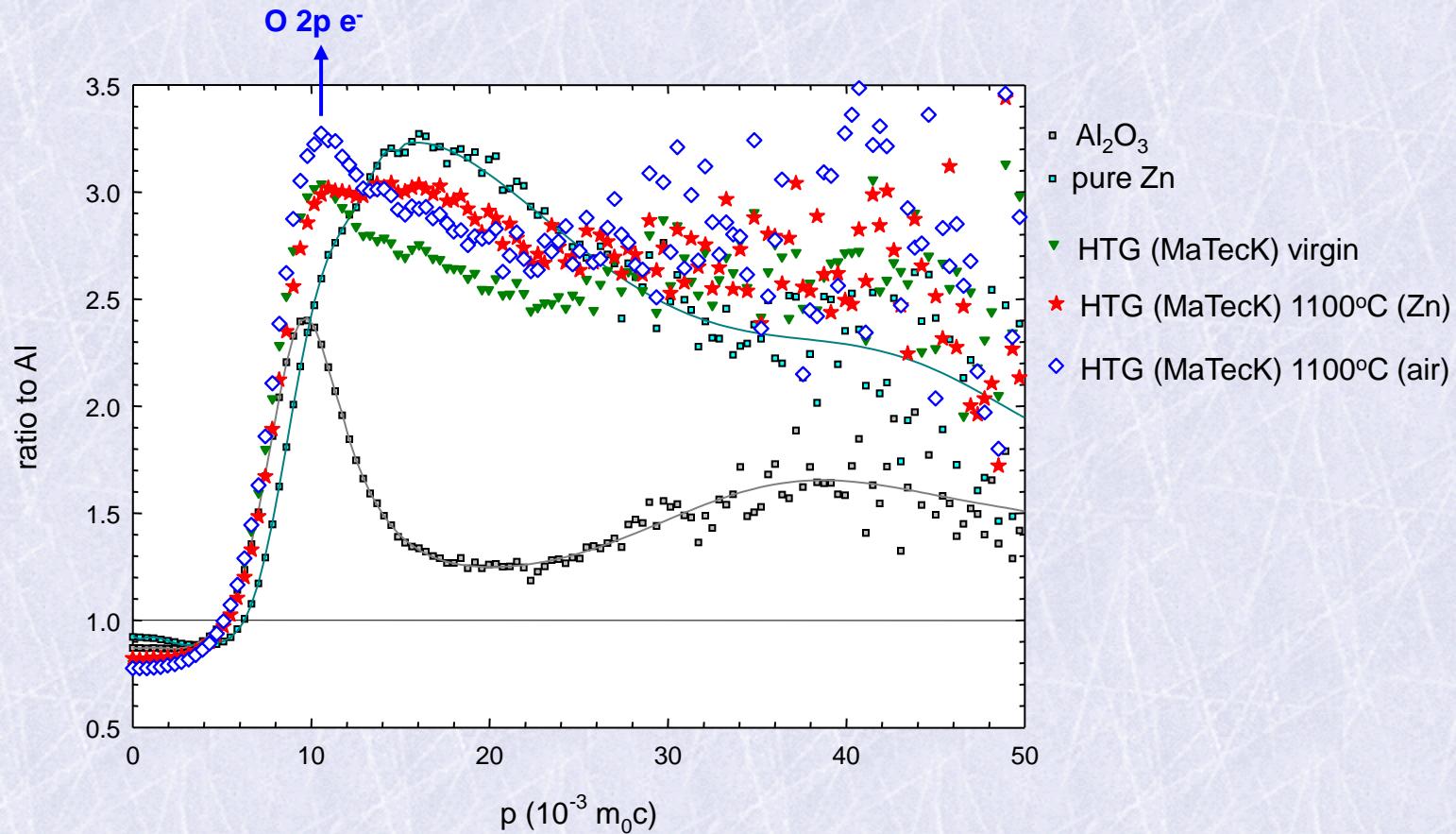
## CDB results

- HTG ZnO - effect of annealing
- annealing in Zn vapour → increase of Zn contribution (removal of  $V_{Zn}$ )



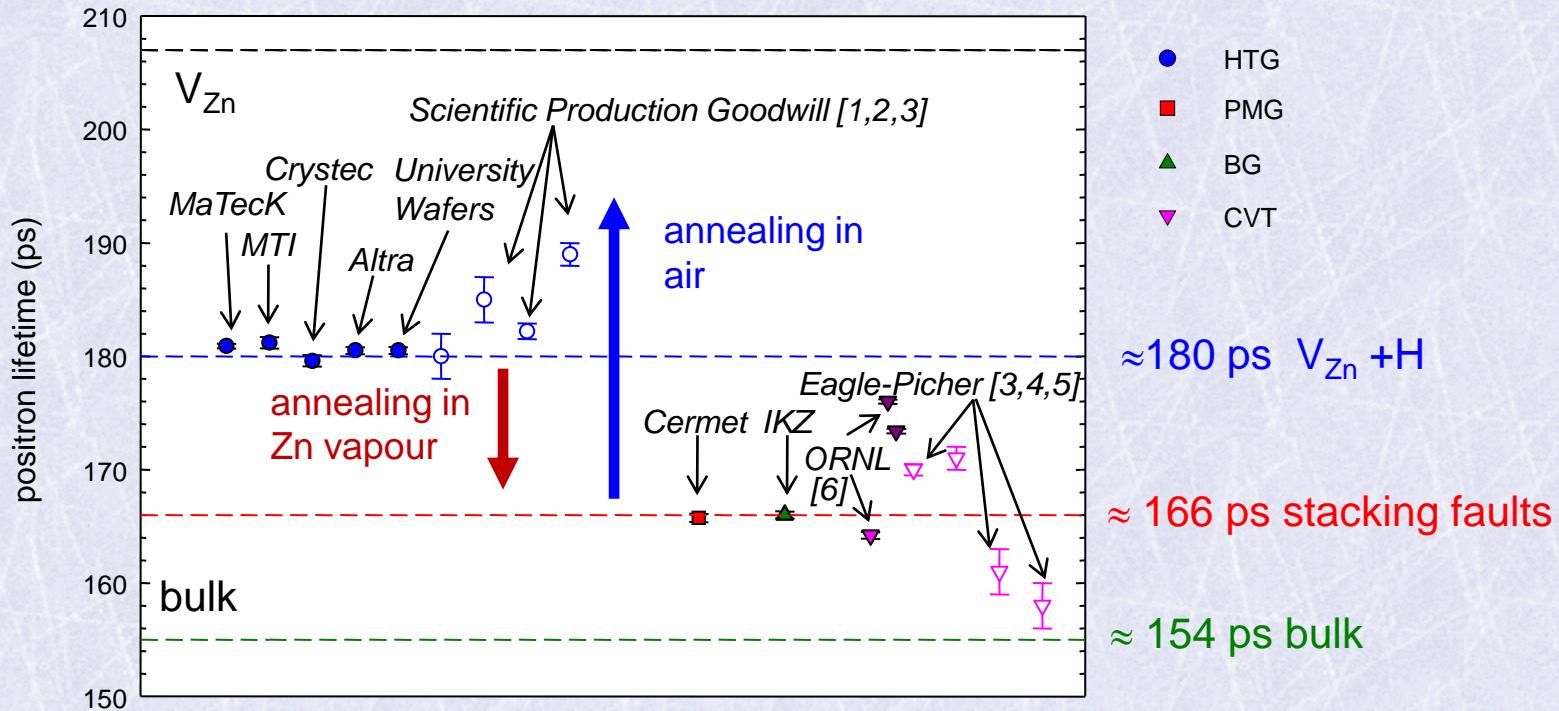
## CDB results

- HTG ZnO - effect of annealing
- annealing in Zn vapour → increase of Zn contribution (removal of  $V_{Zn}$ )
- annealing in air → increase of O contribution (creation of  $V_{Zn}$ )



# Conclusions

- HTG crystals – saturated trapping in  $V_{Zn+H}$
- PMG, BG crystals – saturated trapping in stacking faults
- annealing in air creates  $V_{Zn}$
- annealing in Zn vapour removes  $V_{Zn}$  and introduces  $V_O$



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# SLOPOS -15

Prague, Czech Republic

September 2-6, 2019

See you in Prague

